Nanoarchitectonics of Ultraporous Nanoparticle Networks for High Performance UV Photodetectors

Noushin Nasiri-Varg

March 2017

A thesis submitted for the degree of Doctor of Philosophy of The Australian National University
The research described in this thesis is my own original work, except where otherwise acknowledged.

Noushin Nasiri
March 2017
This thesis is dedicated to my parents, Ebrahim and Behjat, who have always loved me unconditionally and whose good examples have taught me to work hard for the things that I aspire to achieve.

And also to my best and lovely friend, Leila, who has been a constant source of support and encouragement during the challenges of my PhD life.
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<tr>
<td>UV</td>
<td>Ultraviolet</td>
</tr>
<tr>
<td>UNN</td>
<td>Ultraporous nanoparticle network</td>
</tr>
<tr>
<td>CMOS</td>
<td>Complementary metal–oxide–semiconductor</td>
</tr>
<tr>
<td>0D</td>
<td>Zero dimensional</td>
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<tr>
<td>1D</td>
<td>One dimensional</td>
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<td>2D</td>
<td>Two dimensional</td>
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<tr>
<td>3D</td>
<td>Three dimensional</td>
</tr>
<tr>
<td>LEDs</td>
<td>Light-emitting diodes</td>
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<tr>
<td>CB</td>
<td>Conduction band</td>
</tr>
<tr>
<td>VB</td>
<td>Valence band</td>
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<tr>
<td>EQE</td>
<td>External Quantum Efficiency</td>
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<td>LDR</td>
<td>Linear Dynamic Range</td>
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<tr>
<td>QDs</td>
<td>Quantum dots</td>
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<tr>
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<td>Vapour-liquid-solid</td>
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<td>CVD</td>
<td>Chemical vapour deposition</td>
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<tr>
<td>PLD</td>
<td>Pulsed laser deposition</td>
</tr>
<tr>
<td>ALD</td>
<td>Atomic laser deposition</td>
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<tr>
<td>MBE</td>
<td>Molecular beam epitaxy</td>
</tr>
<tr>
<td>MOCVD</td>
<td>Metal-organic chemical vapour deposition</td>
</tr>
<tr>
<td>SEM</td>
<td>Scanning Electron Microscopy</td>
</tr>
<tr>
<td>TCO</td>
<td>Transparent conductive oxide</td>
</tr>
<tr>
<td>TNRCs</td>
<td>Transferable TiO$_2$ nanorod cloths</td>
</tr>
<tr>
<td>FTO</td>
<td>Fluorine-doped tin oxide</td>
</tr>
<tr>
<td>PTE</td>
<td>Polyethylene terephthalate</td>
</tr>
<tr>
<td>UFP</td>
<td>Ultra-fine particles</td>
</tr>
<tr>
<td>TEM</td>
<td>Transmission electron microscopy</td>
</tr>
<tr>
<td>SD</td>
<td>Surface density</td>
</tr>
<tr>
<td>PET</td>
<td>Poly-ethylene-terephthalate</td>
</tr>
<tr>
<td>FSP</td>
<td>Flame spray pyrolysis</td>
</tr>
<tr>
<td>HAB</td>
<td>Height above the burner</td>
</tr>
<tr>
<td>RTD</td>
<td>Resistance temperature detector</td>
</tr>
<tr>
<td>XRD</td>
<td>X-Ray diffraction</td>
</tr>
<tr>
<td>Abbreviation</td>
<td>Description</td>
</tr>
<tr>
<td>--------------</td>
<td>-------------</td>
</tr>
<tr>
<td>BET</td>
<td>Brunauer-Emmett-Teller</td>
</tr>
<tr>
<td>SSA</td>
<td>Specific surface area</td>
</tr>
<tr>
<td>Vis</td>
<td>Visible</td>
</tr>
<tr>
<td>NIR</td>
<td>Near infrared</td>
</tr>
<tr>
<td>DC</td>
<td>Direct current</td>
</tr>
<tr>
<td>FTIR</td>
<td>Fourier Transfer Infrared Spectroscopy</td>
</tr>
<tr>
<td>IMONNs</td>
<td>Integrated metal-oxide nanoparticle networks</td>
</tr>
<tr>
<td>HMDSO</td>
<td>Hexamethyldisiloxane</td>
</tr>
<tr>
<td>TTIP</td>
<td>Titanium isopropoxide</td>
</tr>
<tr>
<td>EDX</td>
<td>Energy-dispersive X-ray</td>
</tr>
<tr>
<td>3DNH</td>
<td>Three-dimensional network of nanoscale heterojunctions</td>
</tr>
<tr>
<td>LD</td>
<td>Light density</td>
</tr>
<tr>
<td>SSB</td>
<td>Surface band bending</td>
</tr>
<tr>
<td>HAp</td>
<td>Hydroxyapatite</td>
</tr>
<tr>
<td>BCP</td>
<td>Biphasic calcium phosphate</td>
</tr>
<tr>
<td>WLI</td>
<td>White light interferometer</td>
</tr>
<tr>
<td>PBS</td>
<td>Phosphate buffered saline</td>
</tr>
<tr>
<td>TCP</td>
<td>Tissue culture plates</td>
</tr>
<tr>
<td>HMDS</td>
<td>Hexamethyldisilazane</td>
</tr>
<tr>
<td>BSA</td>
<td>Bovine serum albumin</td>
</tr>
<tr>
<td>DSC</td>
<td>Differential scanning calorimetry</td>
</tr>
<tr>
<td>Nomenclature</td>
<td>Definition</td>
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<tr>
<td>--------------</td>
<td>------------</td>
</tr>
<tr>
<td>$R$</td>
<td>Responsivity</td>
</tr>
<tr>
<td>$I_{ph}$</td>
<td>Output current per unit area</td>
</tr>
<tr>
<td>$P_{opt}$</td>
<td>Illumination power per unit area</td>
</tr>
<tr>
<td>$D$</td>
<td>Detectivity</td>
</tr>
<tr>
<td>$A$</td>
<td>Effective area</td>
</tr>
<tr>
<td>$B$</td>
<td>Bandwidth</td>
</tr>
<tr>
<td>$NEP$</td>
<td>Noise-equivalent power</td>
</tr>
<tr>
<td>$e$</td>
<td>Electron charge</td>
</tr>
<tr>
<td>$I_{dark}$</td>
<td>Dark current</td>
</tr>
<tr>
<td>$G$</td>
<td>Photoconductive gain</td>
</tr>
<tr>
<td>$N_{el}$ ($N_{electron}$)</td>
<td>Number of electrons collected per unit time</td>
</tr>
<tr>
<td>$N_{ph}$ ($N_{photon}$)</td>
<td>Number of absorbed photons per unit time</td>
</tr>
<tr>
<td>$I_{photo}$</td>
<td>Photo current</td>
</tr>
<tr>
<td>$h\nu$</td>
<td>Photon energy of incident light</td>
</tr>
<tr>
<td>$P$</td>
<td>Power of incident light</td>
</tr>
<tr>
<td>$\eta$</td>
<td>Quantum efficiency.</td>
</tr>
<tr>
<td>$\Phi$</td>
<td>Photon flux</td>
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<tr>
<td>$d_p$</td>
<td>Particle diameter</td>
</tr>
<tr>
<td>$F_d$</td>
<td>Film thickness</td>
</tr>
<tr>
<td>$L_d$</td>
<td>Domain length</td>
</tr>
<tr>
<td>$\varepsilon_{film}$</td>
<td>Average film porosity</td>
</tr>
<tr>
<td>$\varepsilon_{min}$</td>
<td>Minimal film porosity</td>
</tr>
<tr>
<td>$\varepsilon_{q-a}$</td>
<td>Quasi-asymptotic film porosity</td>
</tr>
<tr>
<td>$Pe$</td>
<td>Péclet-number</td>
</tr>
<tr>
<td>$D_p$</td>
<td>Diffusion coefficient</td>
</tr>
<tr>
<td>$v$</td>
<td>Particle translational velocity</td>
</tr>
<tr>
<td>$K_b$</td>
<td>Boltzmann constant</td>
</tr>
<tr>
<td>$T$</td>
<td>Temperature</td>
</tr>
<tr>
<td>$f$</td>
<td>Friction coefficient</td>
</tr>
<tr>
<td>$K_n$</td>
<td>Knudsen number</td>
</tr>
<tr>
<td>$\mu$</td>
<td>Viscosity</td>
</tr>
</tbody>
</table>
\( \lambda \)  
Wavelength

\( C_c \)  
Cunningham correction factor

\( T_F \)  
Aerosol temperature

\( T_S \)  
Surface temperature

\( T_p \)  
Particle temperature

\( \mu_F \)  
Fluid dynamic viscosity

\( v_T \)  
Thermophoretic velocity

\( \rho_F \)  
Fluid density

\( \delta_F \)  
Boundary layer thickness

\( K_T \)  
Thermophoretic coefficient

\( A_{dp} \)  
Horizontal shadowed area

\( \pi \)  
Pi number

\( A_{stat} \)  
Collision area

\( A_{dyn} \)  
Horizontal swept area

\( X \)  
Brownian displacement

\( A_{over} \)  
Overlapped area

\( K_{RPF} \)  
Randomly Path Factor

\( \lambda_{dp} \)  
Particle mean free path

\( t \)  
Travelled time

\( \alpha_{max} \)  
Maximal incident angle

\( \delta \)  
Debye length

\( T_{Film} \)  
Film average transmittance

\( I_{Film-out} \)  
Transmittance through the glass

\( T_{Glass} \)  
Glass transmittance

\( d_{BET} \)  
Particle sauter diameter

\( d_{TEM} \)  
Average particle diamter

\( d_{XRD} \)  
Average crystal size

\( n_c \)  
Carrier concentration

\( T_d \)  
Deposition time

\( R_a \)  
Root mean square (rms) surface roughness
Abstract

Accurate detection of ultraviolet radiation is critical to many technologies including wearable devices for skin cancer prevention, optical communication systems and missile launch detection. Si-based photodetectors, relying on n-p type semiconductor homojunction technology, are the most established commercial solution for measurement of ultraviolet light. These devices have some significant shortcomings including high operation voltage, the requirement of longpass filters to block low energy photons and cooling systems to reduce noise and leakage current. This significantly hinders their integration in wearable technologies and alternative solutions are intensively sought. Here, we report a hierarchical design and a rapid synthesis approach for the fabrication of highly performing visible-blind photodetectors based on wide bandgap semiconductors. Combined nano- and micro-scale fine-tuning of the film optical and electrical properties results in record-high photo-currents (milliampere) while preserving pico-ampere dark-currents and excellent selectivity to ultra-low ultraviolet (UV) light densities. In addition, we show that structural engineering of the nanoparticle grain boundaries can drastically enhance the performance of ultraporous nanoparticle network (UNN) photodetectors leading to gigantic photo to dark current ratios with low operation voltages (< 1 V). This is attributed to the optimal interplay of surface depletion and carrier conduction resulting in the formation of an open-neck grain boundary morphology. This is a significant improvement over state-of-the-art devices where a compromise is necessary between high photo-current and low dark-currents. As a result, these photodetectors do not require bulky and costly read-out circuitry and can be directly integrated in portable Complementary metal–oxide–semiconductor (CMOS) based electronics that is currently utilized in many wearable devices.

Furthermore, we present a highly performing nanoscale architecture for band-selective UV-photodetectors that features unique tunability and miniaturization potential. The device
layout relies on the three dimensional (3D) integration of ultraporous layers of tailored nanoparticles. By tailoring the transmittance window between the indirect band gap of titanium dioxide (TiO$_2$) nanoparticles and the sharp edge of the direct band gap of zinc oxide (ZnO), we achieve a band-selective photoresponse with tunable bandwidth to less than 30 nm. However, a standing challenge with wide bandgap photodetectors is to drastically improve the sluggish response time of these nanostructured devices. In this research, we also present a three-dimensional nanoscale heterojunction architecture for fast-responsive visible-blind UV photodetectors. The device layout consists of p-type nickel oxide (NiO) clusters densely packed on the surface of an ultraporous network of electron-depleted n-type ZnO nanoparticles featuring a significant decrease in the rise and decay times compared to the pure ZnO device. These drastic enhancements in photoresponse dynamics are attributed to the stronger surface band bending and improved electron-hole separation of the nanoscale NiO/ZnO interface. These findings demonstrate a superior architecture for the engineering of miniaturized wearable UV-photodetectors with largely suppressed dark-currents, fast photocurrent dynamics and ultra-low power consumption.
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Chapter One

Wide bandgap Semiconductors for Visible-Blind Ultraviolet Photodetectors
1.1 Introduction

Wide bandgap semiconductors are an important class of materials for electronic and optoelectronic applications. Concerning the former, wide bandgap semiconductors are used in high power and high temperature electronic applications. These materials are also ideal for electronic applications where radiation hardness is required. With regards to the latter, ultraviolet, blue and green emitting semiconductor photodetectors, lasers and Light-emitting diodes (LEDs), and solid-state electroluminescent flat panel displays are examples of optoelectronic applications of wide bandgap semiconductors.

Wide bandgap ultraviolet photodetectors have gained particular momentum for their application in the area of ultraviolet optoelectronics, such as space communications, flame and missile launch detectors, and chemical sensors. As the most common devices for UV photodetection, silicon photodetectors exhibit some intrinsic limitations, such as difficulty of blocking out visible and infrared photons and degradation of devices under UV irradiation. By contrast, for wide bandgap semiconductor-based UV photodetectors, these types of limitations are easily ruled out because of their wide and direct bandgaps and ability to operate in harsh environmental conditions. The ideal photodetector is generally designed to display a high responsivity, a good linearity of the photocurrent as a function of the incident optical power, a low noise level, and good visible rejection (i.e., high spectral selectivity). A short response time can also be of great importance in applications where a real-time fast signal treatment is necessary.

Recently, the use of low-dimensional wide-bandgap semiconductor nanostructures materials with tailored geometry as building blocks for visible-blind UV photodetectors has attracted intense attention. The electrical integration of synthesized low-dimensional nanostructures has been achieved with lithography and optical integration, which promises high speeds and greater device versatility. Low-dimensional nanostructures can be divided
into zero-dimensional, one-dimensional (1D) and two-dimensional (2D) nanostructures, based on their shapes and morphologies. These wide bandgap semiconductor nanostructures, such as quantum dots (QDs), nanotubes, nanowires, nanorods, nanobelts, nanocables, core/shell structures, nanostructure arrays, epitaxial film and heterostructures are expected to play key roles in visible-blind UV photodetectors. Compared with UV photodetectors based on traditional thin-film and bulk materials, low-dimensional UV nanostructured photodetectors usually have the advantage of higher responsivity and photoconductivity gain because of their high surface-area-to-volume ratios and the reduced dimension of the effective conductive channel.

Generally, the large surface-to-volume ratio significantly increases the number of surface trap states and prolongs the photocarrier lifetime. In addition, the reduced dimensionality can confine the active area of the charge carrier and shorten the transit time. For fabrication of visible-blind UV photodetectors, many wide-bandgap materials with bandgap larger than 3.3eV have been investigated as building blocks of visible-blind UV photodetectors, including gallium nitride (GaN), tin oxide (SnO₂), TiO₂, silicon carbide (SiC) and ZnO. Furthermore, nano- and microstructured wide bandgap UV photodetectors have been produced by several methods, such as physical vapour deposition including magnetron sputtering⁵-⁷ and pulsed laser deposition,⁸-¹¹ chemical vapour deposition,¹²-¹³ flame spray pyrolysis¹⁴ and sol-gel.¹⁵-¹⁶

In this chapter, we provide a comprehensive review of the state-of-the-art research activities on wide bandgap semiconductor UV photodetectors. We concentrate on a number of different semiconductors reported as potential wide bandgap materials for various photodetecting applications and on a variety of nanostructured morphologies fabricated in the area of high-performance UV photodetectors.
1.2 Photodetection Mechanism

Wide bandgap semiconductors have been investigated under different conditions to understand the fundamental process and enhancing the response to the UV light. The key principle on which photodetection relies is the conversion of absorbed photons into an electrical signal. The photoresponse characteristics of nanostructured devices are significantly influenced by a number of factors, such as the presence of different amounts of defect concentration in the material, crystallographic orientation, grain size, and processing condition. These factors could influence the photoresponse characteristics and explain the large variation in photoresponse results previously reported by various groups for the same material. Several different mechanisms by which this can be accomplished in ultraviolet photodetectors have been reported. Herein, we mainly focus on three different type of device structure, which can serve as a guideline for understanding the structural-functional relations of nanostructured photodetector devices fabricated by several synthesis methods.

1.2.1 Photoresistors

A photoconductor, consisting of a semiconductor with two ohmic contacts, is essentially a radiation-sensitive resistor. The schematic structure and operation of the photoconductor are shown in Figure 1.1a,b. ZnO is the most common UV photoresistor investigated in detail by a number of groups resulting in significantly high photodetection performance. The high photodetection properties of ZnO are the results of oxygen-related hole-trap states at the photodetector surface.\textsuperscript{2,17} In fact, the surface traps tend to adsorb oxygen molecules from the air causing capture of free electrons from the n-type semiconductor (Figure 1.2).\textsuperscript{14} This leads to the formation of an electron depletion region near the surface which induces surface band bending and significantly decreases the device’s conductance (Figure 1.2c). Such a surface band bending establishes an internal electric filed, which can spatially separate photo-generated electron-holes leading to suppressed photo-carrier recombination and dramatically
prolonging carrier life-times. These effects are particularly prominent in nanocrystalline films, where the surface area is large and the depletion regions may extend throughout the entire bulk of the film.

**Figure 1.1** Schematic and current-voltage characteristic of (a,b) Ohmic contact photoresistor, (c,d) Schottky contact and (e,f) photodiodes.

Upon illumination with photon energy higher or equal to the semiconductor band gap, electron-hole pairs are generated. In fact, the electrons in the valence band (VB) could be excited to the connection band (CB) with simultaneous generation of the same number of holes in the VB (Figure 1.2b). The holes that migrate to the surface along the potential gradient produced by band-bending either discharge the negatively charged adsorbed oxygen ions to photodesorb oxygen from the surfaces or effectively get trapped at the ZnO surfaces
This results in an increase in the free carrier concentration and a decrease in the width of the depletion layer (Figure 1.2b,d). When the UV illumination is turned off, the residual accumulated holes recombine with the unpaired electrons, while oxygen is gradually reabsorbed into the surface resulting in a slow current decay.

![Figure 1.2](image)

**Figure 1.2.** Schematic of a (a,b) nanowire and a (c,d) nanoparticles network photoconductor under (a,c) dark condition and (b,d) UV illumination. In the dark condition (a,c), oxygen molecules adsorbed at the surface that capture the free electron present in the n-type semiconductor forming low-conductivity depletion layer near the surface. Under UV illumination (b,d), photogenerated holes migrate to the surface and are trapped, leaving behind unpaired electrons in the nanowire that contribute to the photocurrent. The lifetime of the unpaired electrons is further increased by oxygen molecules desorption from the surface when holes neutralize the oxygen ions.

### 1.2.2 Schottky Contacts

Schottky diodes in their simplest form consist of a metal layer, such as gold, silver and aluminum, in contact with a moderately doped n-type semiconductor. Figure 1.1c,d present the schematic structure of the Schottky contact photodetector. It is a unipolar device because it has electrons as majority carriers on both sides of the junction. Hence, there is no depletion layer formed near the junction and no significant current from the metal to the semiconductor with reverse bias. Thus, the delay present in the junction diodes due to hole-electron recombination time is absent here.
Due to the electrostatic barrier between the metal and the semiconductor caused by the difference in their work functions, the Schottky contact devices exhibit a rectifying behaviour. Here, two mechanisms contribute to the photoresponse. The first is the ‘‘primary current’’ maintained by carriers optically generated in the depletion region. The ‘‘secondary current’’ is due to the lowering of the Schottky barrier caused by illumination and trapping at interface states. In fact, in the Schottky contact devices, the photogenerated electron-hole pairs can be separated quickly by the local electric field at the Schottky barrier region, which would reduce the electron-hole recombination rates and increase the carrier lifetime, resulting in an increase in the free carrier density. The increased carrier density in the semiconductor photodetector changes the Fermi energy and the work function of semiconductor, resulting in the reduction of the Schottky barrier height and width between the semiconductor layer and electrodes. Both of these account for the high photocurrent on-off ratio and rapid rising speed of the UV detectors based on Schottky. Once the UV illumination is turned off, electron-hole pairs will quickly recombine in the photodetector device and the Schottky barrier is recovered, which may explain the fast recovery speed in these types of UV photodetectors.

1.2.3 Photodiodes

A photodiode is a p-n junction or p-i-n structure which is commonly used in a variety of applications, including UV photodetection. The device consists of a highly-doped transparent p-type layer and an n-type highly doped layer (Figure 1.1e) with an undoped absorbing layer in the middle in the case of p-i-n structure. When p-type and n-type materials are placed in contact with each other, the junction behaves very differently than either type of material alone (Figure 1.1f). Specifically, current will flow readily in one direction (forward biased) but not in the other (reverse biased), creating the basic diode (Figure 1.1f). This non-reversing behavior arises from the nature of the charge transport process in the two types of materials. In the p-type region, there are holes from the acceptor impurities and in the n-type
region there are extra electrons. When a p-n junction is formed, some of the electrons from the n-region which have reached the conduction band are free to diffuse across the junction and combine with holes. Filling a hole makes a negative ion and leaves behind a positive ion on the n-side. A space charge builds up, creating a depletion region which inhibits any further electron transfer unless it is helped by putting a forward bias on the junction. Under UV illumination, the photogenerated electron-hole pairs contribute to an induced photocurrent with a large transport under reverse bias.

1.3 Key Figures of Merit

Photodetection is a process of converting light signals to electric signals including three physical mechanisms of light harvesting, exciton separation, and charge carrier transport to corresponding electrodes. In order to quantify and compare the performance of different types of photodetectors, it is essential to have an in-depth understanding of their figures of merit. In the past several decades, a number of different figures of merit have been introduced in order to characterize UV photodetectors. Here we only discuss the figures of merit that are currently accepted and used by several groups in the UV photodetecting field.

1.3.1 Responsivity

By definition, responsivity is the ratio of photo-current obtained by a device per unit area to the incident light power at a given wavelength and can be calculated as follows:

\[ R = \frac{I_{ph}}{P_{opt}} \]  

(1-1)

where \( I_{ph} \) is the output current obtained by the device per unit area and \( P_{opt} \) is the illumination power on the detection area of the device. The spectral response of the photodetector is obtained by plotting the responsivity against the wavelength, and usually follows the absorption spectrum of the photosensitive semiconductor material used for the fabrication of the detector.
1.3.2 Specific Detectivity

Another important figure of merit is the detectivity, which represents the ability to detect signal from noise and is defined as:

\[ D = \frac{\sqrt{AB}}{NEP} \]  \hspace{1cm} (1-2)

where \( A \) is the effective area of the detector, \( B \) is bandwidth and \( NEP \) is the noise-equivalent power. If the dark-current is the major contribution to the noise limiting the detectivity, this equation can be simplified as follows\(^{18}\):

\[ D = \frac{R}{\left(2e \cdot \frac{I_{dark}}{A}\right)^{1/2}} \]  \hspace{1cm} (1-3)

where \( R \) is the responsivity, \( e \) is the electron charge \((1.6 \times 10^{-19} \text{ coulombs})\) and \( I_{dark} \) is the dark current of the device.

1.3.3 Photoconductive Gain

By definition, photoconductive gain (\( G \)) is defined as the ratio of the number of electrons collected per unit time \((N_{el})\) to the number of absorbed photons per unit time \((N_{ph})\) which can be derived by:

\[ G = \frac{N_{electron}}{N_{photon}} = \left(\frac{I_{photo} - I_{dark}}{e}\right) \left(\frac{h\nu}{e}\right) \left(\frac{1}{P} \right) \eta \]  \hspace{1cm} (1-4)

Where \( I_{photo} \), is the photo current, \( I_{dark} \), is the dark current, \( e \) is the electron charge \((1.6 \times 10^{-19} \text{ coulombs})\), \( h\nu \) is the photon energy of incident light \((5.37 \times 10^{-19} \text{ J for } 370 \text{ nm})\), \( P \) is the power of incident light and \( \eta \) is the quantum efficiency.

1.3.4 External Quantum Efficiency (EQE)

The efficiency of light energy utilization can be described by EQE:

\[ EQE = \frac{I_{photo}}{e\Phi} = \frac{h\nu I_{photo}}{eP} \]  \hspace{1cm} (1-5)
where \( I_{\text{photo}} \) is the photo current, \( e \) is the electron charge \((1.6 \times 10^{-19} \text{ coulombs})\), \( \Phi \) is the photon flux, defined as the number of incident photons, \( h \nu \) is the energy of one single photon and \( P \) is the power of incident light.

### 1.3.5 Linear Dynamic Range (LDR)

The LDR of a detector is a measurement of the minimum detectable signal, to the maximum signal that will start to compress the detector. LDR is one of the important figures of merit for a photodetector which is defined as the maximum linear response of the device divided by the detector noise. Most detectors eventually become non-linear as sample size is increased and this upper point is usually well defined. The LDR can be calculated as:

\[
LDR = 20 \log \left( \frac{I_{\text{photo}}}{I_{\text{dark}}} \right)
\]

where \( I_{\text{photo}} \) is the photocurrent and \( I_{\text{dark}} \) is the dark current.

### 1.4 Photodetector’s Nanostructure

#### 1.4.1 Zero Dimensional (0D) Nanostructures

Quantum dots (QDs) are small semiconducting nanocrystals (2-10 nm)\(^{19}\) that can be made of a variety of different elements, such as silicon (Si),\(^ {20-21}\) cadmium selenide (CdSe)\(^ {22-23}\) or cadmium sulphide (CdS).\(^ {24-25}\) The size, energy levels and emission colour of QDs can be precisely controlled, which makes them extremely useful in a variety of applications. Because of their reduced size, QDs behave differently from bulk solids due to the quantum-confinement effects that are responsible for their remarkably attractive properties.\(^ {19}\) These semiconducting materials are able to absorb light and transform it into different colours when they release the absorbed energy.\(^ {26}\) The specific colour that QD produced depends on their size (Figure 1.3a) and not the material.\(^ {26}\) In fact, their bandgap changes in accordance with their size due to quantum confinement. When light excites the QD, the larger the size of the
Figure 1.3. (a) Colloidal quantum dots irradiated with a UV light. Different sized quantum dots emit different colour light due to quantum confinement. SEM image of (b) regularly patterned ZnO nanorods grown with the hydrothermal method,\textsuperscript{28} (c) belt-like structure fabricated by an improved vapour-liquid-solid (VLS) process with a uniform belt thickness of \(~200\) nm\textsuperscript{29} and (d) ZnO nanodisk with a diameter of \(5\) μm fabricated by drop-casting process.\textsuperscript{30} Cross-sectional SEM image of (e) dense TiO\(_2\) structure grown on silicon slot structures using atomic layer deposition technique,\textsuperscript{31} (f) porous TiO\(_2\) film on the silicon substrate fabricated by spin-coating technique\textsuperscript{32} and (g) ultraporous nanoparticles network made by flame spray pyrolysis system.\textsuperscript{14}

History of QDs begins with their first discovery in glass crystals in the 1980s by A. I. Ekimov and his colleagues at the Ioffe Physical-Technical Institute in St. Petersburg.\textsuperscript{33} They noticed unusual optical spectra from samples of glass containing the semiconductors cadmium sulphide or cadmium selenide.\textsuperscript{33} Systematic advancement in the science and technology of QDs came after 1984, when Luis Brus discovered the relation between size and bandgap for semiconductor nanoparticles.\textsuperscript{34} However, it took nearly a decade for a new level in QD research to reach with the successful synthesis of colloidal Cd\(_X\) (\(X = S, Se, Te\)) QDs
with size-tunable band-edge absorption and emissions.\textsuperscript{35} To date, various methods have been developed to synthesize monodisperse and solution-stable QDs of less than 10 nm, including hydrothermal method,\textsuperscript{36} electrochemical strategies,\textsuperscript{37} the solution chemistry method,\textsuperscript{38} and the ultrasonic and microwave method.\textsuperscript{39}

\textbf{1.4.2 One Dimensional (1D) Nanostructures}

\textbf{1.4.2.1 Nanowires}

Nanowires are 1D nanomaterials with diameters in the order of a few hundred nanometres or less, and lengths ranging from several hundreds of nanometre to as long as a few centimetres.\textsuperscript{40-41} Because of their nanoscale dimensions in the radial direction, they have size confinement effects that give them novel physical properties compared to bulk materials. Benefitting from a large surface-to-volume ratio and a Debye length comparable to their small size, 1D semiconductor nanostructures are considered the most promising building blocks for photodetectors with superior sensitivity, high quantum efficiency, and fast response speed.\textsuperscript{42-45} The length and diameter of nanowires as well as their alignment affect the emission and absorption properties and need to be controlled since they dominate the physical, chemical and optical states of nanowires.\textsuperscript{40,42,46} In fact, the critical device size is defined during the growth process and can be controlled with atomic scale resolution. The key issue related to the growth of nanowires is how to induce 1D crystal growth in a controlled manner. Regarding this, many approaches have been studied, including vapour-liquid-solid (VLS),\textsuperscript{47} chemical vapour deposition (CVD),\textsuperscript{13,48-49} wet synthesis\textsuperscript{50} and pulsed laser deposition (PLD).\textsuperscript{51}

\textbf{1.4.2.2 Nanorods}

Similar to the nanowires, nanorods with a dimension range from 1 to 500 nm (Figure 1.3b), have been the focus of considerable attention because of their potential to answer fundamental questions about one-dimensional systems and their critical role in different
applications ranging from molecular electronics to novel scanning microscopy probes.\textsuperscript{52-54} In the device applications of nanorods, it is important not only to grow nanorods with a high degree of regularity and uniformity in terms of their height and cross-sectional size, but also to accurately control their positions (Figure 1.3b).\textsuperscript{55-57} Good control of nanorods position and shape can improve the performance of fabricated electronic and optoelectronic devices.\textsuperscript{11,56,58}

1.4.3 Two Dimensional (2D) Nanostructures

Nanobelts, with intermediate morphology between one and two dimensional (Figure 1.3c), have been intensively studied in the last few years, because they may be the ideal system to fully understand dimensionally confined transport phenomena and building functional devices along individual nanobelts.\textsuperscript{1,29,59-60} They were reported by Wang and co-workers for the first time in 2001\textsuperscript{61} as a structurally controlled nanomaterial with well-defined facets, unique growth directions, and a typical rectangular cross section. With large surface areas exposed to the light, various kinds of nanobelts have been assembled into nanoscale optical devices.

As mentioned previously, nanostructured materials with lower dimensionality can lead to higher optical responses as compared to their bulk counterparts. In fact, the electron and hole energy states become discrete due to the spatial confinement, which will considerably prolong the photocarrier lifetime.\textsuperscript{62-63} However, the electrical performance of QD devices is limited due to the severe scattering from a very large number of grain boundaries within the QD device with the nanoscale grain size.\textsuperscript{64} For the 1D materials, the incomplete surface coverage is considered as a drawback for their photodetection performance.\textsuperscript{62} Therefore, ultrathin 2D nanostructures are more able to satisfy the requirements of ultrathin structures, low-cost, portability, and mechanical stability in high performance flexile optoelectronic devices.\textsuperscript{65} In addition, it has been reported that polar facets of some nanostructures, such as ZnO, contain more oxygen vacancies than the other facets, which have a significant impact
on the electronic properties and enhance the efficiency of the electron-hole separation.\textsuperscript{30,66} Hence, the efficient separation of charges and the low dimensionality of the conductive volume should be particularly significant for the presented thin nanodisks (Figure 1.3d) combining large surface-to-volume ratio and polar exposed facets.\textsuperscript{30} In fact, the high quality of single crystal ZnO nanodisks and nanosheets results in a reduction of the disadvantageous effects of grain boundary recombination, as well as enhancing carrier transport, providing a high active area of the charge carriers. Compared to the QDs zero dimensional structure and the nanowires, nanorods and nanoribbons one dimensional structure, the 2D structures can be more compatible with available micro-fabrication techniques, and can be more easily transformed into more complex structures.\textsuperscript{67}

1.4.4 Nanostructured Films

1.4.4.1 Dense Structures

Nanostructured dense films (Figure 1.3e) fabricated by different methods such as atomic laser deposition (ALD) and molecular beam epitaxy (MBE) have been investigated in the past decades as UV photodetectors resulting in high photodetection properties and fast photoresponse to UV illumination. Ultrathin nanostructured films are of particular interest, due to the device potential involving the quantum confinement effects. The optoelectronic properties of nanometer-thickness films, however, are often controlled by the surface-dominated phenomena due to the large surface-to-volume ratio. In fact, extremely thin films with thickness smaller than twice Debye length are required to ensure the participation of the whole structure in the photodetection mechanism avoiding the formation of non-electron-depleted domain that could act as bottlenecks. However, this ultralow thickness might results in low conductivity and poor mechanical stability of the device.
1.4.4.2 Porous Structures

The porous nanostructured films (Figure 1.3f) are the most common structures used in UV photodetection field due to their higher active area resulting in more adsorptive capacity enhancing the photodetection performance of the fabricated device. Several methods, such as hydrothermal, sol-gel and other wet synthesis methods are utilized previously to fabricate porous nanostructure films as UV photodetectors. The surface area of the nonporous films made by wet synthesis methods is also found to be highly dependent on the number of coatings on the substrate. In fact, a single layer film is a porous structure regardless of the film thickness. While, if the film is prepared with multi-layers, the pores in the first layer will be filled by the following layer. Compared to the dense films, porous structures enhance light harvesting by reducing the reflection and the transmission. Two reasons are responsible for higher light absorption of the porous sample. One is the film thickness and the other is the stronger light scattering in a porous sample. The porous film is recognized to enhance the light harvesting due to light scattering within the pores by increasing the optical path length of light, especially in the wavelength range corresponding to the band edge. The results suggest that the porous structure can enhance light absorption more effectively near band edge region.

1.4.4.3 Ultraporous Structures

Very recently, ultraporous nanoparticle networks (98% porosity) have been reported \(^{14,68-70}\) as a highly performing super-structural design (Figure 1.3g) for visible-blind UV-photodetectors. The authors claimed that in addition to the particle morphology, \(^{10}\) film thickness, \(^{71}\) and grain necking, \(^{66}\) a key structural property impacting the performance of wide bandgap photodetectors is the film porosity. \(^{14,68-70}\)

Figure 1.4 present the $I-V$ characteristic of spin-coated porous nanostructure \(^{72}\) and flame-made ultraporous ZnO-based photodetectors \(^{14}\) at the applied bias of 5 V but different density
of UV light. This comparison revealed a $10^3$ order of magnitude lower photo-current of ca. 2 mA for spin-coated porous structure even under 8 time higher light density (830 µW.cm$^{-2}$).\textsuperscript{72}

While the ultraporous structure resulted in higher photo-current of 1.2 mA at very low light density of 100 µW.cm$^{-2}$.\textsuperscript{14} As a result, it is found that the ultraporous structures have a superior performance as photodetectors offering several advantages such as high photocurrents (milliampere), low dark currents (nanoampere) and detection limit of low light densities at low operation voltages. In fact, the strong penetration of light in these ultraporous nanostructures allow photo-excitation of the bottom layers of the device resulting in significantly higher light absorption and electrical conductivity compared to the other nanostructured films.\textsuperscript{14,72} In contrast, for the porous structures with the film porosity between 40% and 60%, the higher proportion of UV light might be absorbed by the top layers of the device which are not connected to the electrodes,\textsuperscript{72} resulting in absorption of significantly smaller fraction of incoming UV light in bottom layers of the film, and thus lower optical density.

![Figure 1.4. I-V characteristics of ZnO-based photodetectors with porous structure fabricated by spin-coating method\textsuperscript{72} in comparison with ultraporous structure made by flame spray pyrolysis synthesis.\textsuperscript{14} The photodetection properties of the fabricated devices were investigated under UV illumination with the light density of 830 and 100 µW.cm$^{-2}$, for porous and ultraporous structures, respectively.](image-url)
1.5 Materials

There are a number of semiconductors reported as potential wide bandgap materials for various photodetection applications, such as chemical, environmental, and biological analysis, monitoring flame and radiation detection, astronomical studies, and optical communications. In this section, recent progresses in UV photodetection properties are highlighted with respect to several kinds of wide bandgap semiconductors, including TiO$_2$, $^{73-76}$ SiC, $^{77-78}$ ZnO, $^{14,44,72,79}$ GaN $^{80-82}$ and SnO$_2$. $^{42,83}$

1.5.1 SiC-based photodetectors

SiC is considered as one of the most important wide band gap materials ($\sim$2.2-3.0 eV) $^{84-85}$ in the development of UV photodetectors because of their large gains, high signal-to-noise ratios and solar-blind operation. $^{77,86-87}$ These properties make SiC a promising material in certain applications for monitoring the UV spectrum without the need for solar rejection filters. $^{88-89}$ Furthermore, semiconductor SiC offers a high thermal conductivity ($\sim$120 W.m$^{-1}$K$^{-1}$), $^{90-91}$ high hardness and Young’s modulus (typically $\sim$450 GPa compared with $\sim$130 GPa for Si), $^{92-93}$ and an outstanding long term stability even under high-intensity UV radiation and high operating temperature. $^{77,89}$ This combination of excellent electronic and mechanical properties offers many possibilities for using SiC as a material for a wide range of sensors, particularly in applications featuring high temperatures or hostile environments. $^{78,94-96}$

The SiC exists in a large number of polytypes which are different crystal structures built from the same Si-C sub-unit organized into a variety of stacking sequences. $^{97-98}$ There are over 100 of these polytypes known, $^{99}$ but the majority of research and development has focused on 3C, 6H and 4H. $^{84,86-87,100}$ Among them, the 4H-SiC (3.2 eV)$^{101}$ is the most common polytype for electronic devices, due to its overall superior material properties. $^{102-104}$
Typically, 4H-SiC based UV photodetectors achieve photosensitivity spectrum of 200-380 nm and peak responsivity at around 290 nm.\textsuperscript{102-104}

Nanostructured SiC has superior properties compared to bulk SiC for applications in light-emitting diodes and UV photodetectors due to the higher light-emission efficiency. The first commercial nanostructured photodetector device based on SiC was fabricated on p-type 6H-SiC in 1993\textsuperscript{105} and presented a very low dark current of about 100 nA.cm\textsuperscript{-2} at 1.0 V reverse bias even at a temperature of 200°C.\textsuperscript{105} Recently more and more research groups have paid attention to the development of high-performance UV photodetectors using 4H-SiC material systems.\textsuperscript{77,103-104,106-107} For example, by using laser plasma deposition system, Aldalbahi et al.\textsuperscript{77} developed a 2 \( \mu \)m thick SiC film on Si-wafer with a responsivity of up to 0.18 A.W\textsuperscript{-1} at illumination density of 2 mW.cm\textsuperscript{-2}, which is significantly higher compared to the SiC UV detectors previously reported (0.03-0.08 A.W\textsuperscript{-1}).\textsuperscript{106,108-109} In addition, a response time of 18 s under 350 nm wavelength of incident radiation was observed.\textsuperscript{77}

### 1.5.2 GaN-based photodetectors

GaN with a room-temperature bandgap of 3.39 eV (366 nm) is among the most promising material for semiconductor photonic devices operating in the UV regions of the spectrum.\textsuperscript{40,44,82,110} The transparency of high quality GaN at wavelengths longer than the band gap\textsuperscript{111-112} make it an ideal material for photodetectors capable of rejecting near infrared and visible regions of the solar spectrum while retaining near unity quantum efficiency in the UV.\textsuperscript{113} The superior radiation hardness and high temperature resistance of GaN make the fabricated devices suitable for working in extreme conditions.\textsuperscript{114} Moreover, by using its alloys with aluminium and indium, the cut-off wavelength will be tunable in the range from 366 nm to 200 nm.\textsuperscript{115}

Various types of GaN-based photodetectors have been reported, including p-n junctions,\textsuperscript{116-118} Schottky barrier photodetectors,\textsuperscript{119-121} solar-blind ultraviolet
photodetectors,122-124 and UV avalanche photodiodes.125-127 The motivation to investigation $p$-$n$ photodetectors is to take advantage of its structure for better sensitivity and faster response.116-118 Chen et al.80 were the first to report a self-powered GaN p-n junction photodetectors with an abrupt wavelength cut-off at 370 nm, a responsivity of 90 mA.W$^{-1}$ at 370 and a response time of $\sim 0.4$ ms at 325 nm at zero bias.

![Figure 1.5](image.png)

**Figure 1.5.** (a) Schematic and (b,c) AFM analysis of the GaN-based photodetector fabricated using MOCVD after Ag nanoparticles deposition.113 The (d) photoresponse and (e) responsivity of the GaN-based photodetectors with and without Ag under an applied bias of 5 V.113

Recently113 nanoplasmmonic enhancement using Ag nanoparticles was proposed as a great method for improving the performance of GaN-based devices. Li et al.113 have reported that through the excitation of the surface plasmon, the incident light interacts with Ag nanoparticle and significantly enhances the scattering cross-section (Figure 1.5a-c). They have grown a $\sim 3$ $\mu$m thick GaN epilayer on a sapphire substrate using metal-organic chemical vapour deposition (MOCVD) and Ag metal nanoparticles were deposited on the surface of GaN by electron beam evaporation (Figure 1.5a). The responsivity of the
fabricated device increased by a factor of 30 with annealed Ag nanoparticles on the GaN surface from 0.148 A.W⁻¹ to 4.0 A.W⁻¹ (Figure 1.5d,e).¹¹³

Schottky structure is also a good choice of producing GaN-based ultraviolet photodetectors since it does not need the realization of p-type GaN material. However, fabricating high performance GaN Schottky barrier ultraviolet photodetector is still challenging due to the problem of surface states, which increase the recombination of photo-generated electron-hole pairs.¹²⁸-¹²⁹ To accelerate the development of GaN Schottky barrier photodetectors, it is necessary to reduce the negative influence of surface states on their performance.

1.5.3 SnO₂-based photodetectors

Among a variety of semiconductor compounds available for UV detecting application, SnO₂ is a very interesting n-type semiconductor with a wide direct bandgap of ≈3.6 eV (≈340 nm)⁸,¹³⁰ and transparency in the visible-light region of the spectrum,⁴¹,¹³¹ and thus has been proposed to be applied as a potential material for visible-blind photodetectors.⁷⁴,¹³² In addition, SnO₂ found its application in field emission since it has a relatively low work function (4.7 eV)¹³³-¹³⁴ in contrast to carbon nanotube (5 eV)¹³⁵-¹³⁶ and ZnO (5.3 eV).¹³⁷-¹³⁸ The electrical conductivity of intrinsic SnO₂ depends strongly on the surface properties of this material. In fact, surface molecular adsorption/desorption affects the band modulation and space-charge layer which make SnO₂ an important conductance-type gas-sensing material.¹³⁹-¹⁴² Due to the complicated spatial arrangement, the hierarchical architectures can provide extraordinarily high activated surface area¹⁴¹-¹⁴² and also robustness.¹⁴³ Thus far, the reported SnO₂ nanostructures are mostly one dimensional structures, such as nanowires,¹⁴⁴-¹⁴⁷ nanorods,⁵⁸,¹⁴⁸-¹⁴⁹ nanobelts,⁵⁹,¹⁵⁰-¹⁵¹ and nanotubes.¹⁵²-¹⁵⁴

Recently, thin SnO₂ nanowires with uniform diameter of 26 nm (Figure 1.6a) were synthesized by a facile VLS process with Au-layer as catalyst (Figure 1.6b).⁴²
photodetector exhibited a photo-current and dark-current of 2.1 µA and 19.4 nA with \( I_{UV}/I_{dark} \) ratio of \( 10^2 \) (Figure 1.6e) under 320 nm light illumination with the density of 0.91 mW.cm\(^{-2}\).\(^{42}\) In another approach,\(^{130}\) a 2D SnO\(_2\) monolayer nanofilm (Figure 1.6c,d) was fabricated using an oil-water interfacial self-assembly method resulting in a significantly higher photocurrent of 375 µA (Figure 1.6f) at the same light illumination and applied bias. However, the device exhibited low photo- to dark-current ratio of only 4\(^{130}\) due to a significantly higher dark-current of 90 µA (Figure 1.6f).\(^{130}\)

This higher dark-current is attributed to the significantly larger number of nanoparticle neighbours in the 2D SnO\(_2\) monolayer film that results in higher electrical conductivity.\(^{14}\)

Figure 1.6. (a) SEM image of a SnO\(_2\)-nanowire photodetector and (b) and the observed gold (Au) nanoparticle is indicated by a circle.\(^{42}\) (c) The cross-sectional and (d) surface SEM images of 2D ordered SnO\(_2\) nanofilms.\(^{130}\) The I–V characteristics of the (e) SnO\(_2\)-nanowire photodetector\(^{42}\) and (f) 2D ordered SnO\(_2\) nanofilm\(^{130}\) illuminated with light of four different wavelengths and under dark conditions. The schematic illustration of the fabricated nanowire and 2D ordered photodetectors are presented in inset (e) and (f), respectively.
fact, this low photo- to dark-current ratio is attributed to poor penetration of light into the film limiting the photo-excitation to the top film layers.\textsuperscript{14} Higher thickness of the 2D SnO\textsubscript{2} monolayer (94 nm)\textsuperscript{130} compared to a thinner diameter of the SnO\textsubscript{2} nanowire (less than 26 nm) fabricated by Hu et al.\textsuperscript{42} might lead to formation of gas-tight SnO\textsubscript{2} domains, which are not electron depleted and thus less sensitive to light (Figure 1.6e).\textsuperscript{14} While in the case of nanowire device, a higher volume fraction of the nanowire is electron-depleted in the dark condition resulting in considerably lower dark-current of only 19.4 nA (Figure 1.6f)\textsuperscript{42} at the applied bias of 1V.

1.5.4 TiO\textsubscript{2}-based photodetectors

TiO\textsubscript{2} is a well-known transparent conductive oxide (TCO) which is particularly suitable for UV detection against a background with infrared and visible light.\textsuperscript{76,155} Due to the appropriate bandgap (3.2 eV for anatase\textsuperscript{75,156} and 3.0 eV for rutile\textsuperscript{157-158}), distinctive absorption characteristics,\textsuperscript{159} high refractive index,\textsuperscript{73,160} and low fabrication cost, TiO\textsubscript{2} is emerging as a promising material for photodetectors. With large specific surface areas, 1D TiO\textsubscript{2} nanostructures gained special attention in recent years due to their excellent performance in many well-known research areas.\textsuperscript{53,76,158}

Recently, 1D nanostructure of assembled free-standing TiO\textsubscript{2} attracted great interest in this field because of its transferable feature for special applications.\textsuperscript{155,159} Using carbon cloth as an efficiently sacrificial template (Figure 1.7b,c), Wang et al.\textsuperscript{155} reported the first synthesis of flexible and transferable TiO\textsubscript{2} nanorod cloths (TNRCs) from a fast and catalyst-free microwave heating route with post heating treatment at 800°C (Figure 1.7a-c). This novel hierarchical structure of interlaced hollow fibres with nanorods on the surface (Figure 1.7c) can be readily transferred onto a fluorine-doped tin oxide (FTO), Ti foil and polyethylene terephthalate (PTE) providing a promising way to develop devices for applications in many emerging research fields, such as flexible solar cells\textsuperscript{161} and flexible electronic devices.\textsuperscript{46}
Their fabricated TNRC-based photodetectors illustrated a good sensitivity of ca. 7 at different illumination wavelengths of 365 and 254 nm.\textsuperscript{155} However, the device exhibited a low responsivity (0.015 A.W\textsuperscript{-1}) under light illumination of 1.25 mW.cm\textsuperscript{-2} and the applied bias of -1 V. In another approach, Zou et al.\textsuperscript{76} reported a very high UV-sensitive photoconductance of a pure TiO\textsubscript{2} nanotube arrays (Figure 1.7d) made by electrochemical anodization which resulted in a great photosensitivity (\textgtr10\textsuperscript{4}) and also a fast response with rise time and decay time of only 0.5 and 0.7 s, respectively.\textsuperscript{76} The high responsivity of 13 A.W\textsuperscript{-1} was also found under 1.06 mW.cm\textsuperscript{-2} UV (312 nm) illumination at 2.5 V bias (Figure 1.7d).\textsuperscript{76} This high responsivity mainly comes from the internal gain induced by desorption of oxygen from the nanotube large surfaces (Figure 1.7e,f) and the reduction of the Schottky barrier at TiO\textsubscript{2}/Ag contact under UV illumination.\textsuperscript{76,162}

**Figure 1.7.** Spectral response of (a) the TNRC-based device\textsuperscript{155} and (d) TiO\textsubscript{2} nanotube array device\textsuperscript{76} at a bias of 1 and 2.5 V, respectively. (b,c) Optical image of the flexible carbon cloths partly grown with TiO\textsubscript{2} nanorods. (e) Top and (f) cross-sectional view SEM images of the as-anodized TiO\textsubscript{2} nanotube arrays made by electrochemical anodization.

### 1.5.5 ZnO-based photodetectors

With wide direct bandgap (3.37 eV) and large exciton binding energy (=60 meV) at room temperature,\textsuperscript{14,72,163} ZnO nanostructures are amongst the most investigated materials for different nanotechnological applications, such as field effect transistors, diodes, surface
acoustic wave devices, electromechanical devices, and gas sensors.\textsuperscript{2,14,50,164-165} Among various applications for ZnO semiconductors, the UV photodetector is an excellent device that has a wide range of chemical and environmental detecting applications.\textsuperscript{3,49,72,132,166-168}

\textbf{Figure 1.8.} Responsivity and dark current of (a) nanowires and (b) nanostructured UV photodetectors made by different wide bandgap semiconductors.\textsuperscript{13-14,49,53,68,70,76-77,86,106,109,113,116,155,169-183}

Figure 1.8a,b present the responsivity and dark-current of nanowires and nanostructured devices made by different materials, such as GaN, TiO\textsubscript{2}, SiC and ZnO. For all different materials, higher responsivity results from a higher dark-current (Figure 1.8a,b). According to the literature, a higher device responsivity is usually obtained by increasing the applied voltage,\textsuperscript{49,72} device aspect ratio,\textsuperscript{72} and/or structural density.\textsuperscript{184} Liu et al.\textsuperscript{49} fabricated a ZnO micro/nanowire arrays device on single-layer graphene sheets using CVD method featuring a high responsivity of ca. 14 A.W\textsuperscript{-1}, which is significantly high compared to ZnO-based UV photodetectors. However, considering an applied bias of 8.5 V used in their research, the device responsivity can be calculated as 1.62 A.W\textsuperscript{-1} per volt, which is not high compared to the literature. In another approach, a highly performing dense films of electron-depleted ZnO nanoparticles was fabricated using spin-coating method resulting in a high responsivity of 26 A.W\textsuperscript{-1}. However, due to a very low device aspect ratio of ca. 0.75, a giant applied voltage of 120 V was used to achieve this high UV responsivity. In fact, simply increasing the voltage
or changing the device aspect ratio/structure density is not an optimal way to increase the
device performance.

**Figure 1.9.** The responsivity and dark-current of ZnO-based photodetectors with different
nanostructured morphology.\textsuperscript{13-14,48-49,68,72,171-173,180-181,184-187}

Figure 1.9 illustrates the device responsivity and dark-current for ZnO-based
photodetectors with different structural morphology, such as single nanowires,
nanostructured and nanowire films. As mentioned above, for all different nanostructured
morphologies, the higher responsivity results from a higher dark-current. Surprisingly, single
nanowire devices obtained the highest UV photoresponsivity with considerably low dark-
current. This high responsivity might be attributed to the effective surface area considered in
device responsivity. In fact, for single nanowire device, the cross-sectional area is usually
considered as effective surface area in responsivity measurement while the entire outer area
of the nanowire is exposing to UV light and contributing to the light absorption.

Recently, Liu et al.\textsuperscript{43} have fabricated ZnO nanowires with the diameter of 150 nm (Figure
1.10a) and a length of about 10 µm using CVD method featured a low dark current of 9.7 pA
and a photo- to dark- current ratio of about 10\(^3\) at the applied bias of 5V (Figure 1.10c) and
under the light density of 1.3 mW.cm\(^{-2}\).\textsuperscript{43} In addition, they have reported that the
photodetection properties of their device have been improved significantly by decorating the
ZnO nanowires using Au nanoparticles (Figure 1.10a) resulting in an ultralow dark current of
0.13 pA and $I_{\text{photo}}/I_{\text{dark}}$ ratio of $5 \times 10^6$ (Figure 1.10c). Nevertheless, similar to the other ZnO-based UV photodetectors,$^{14,188}$ their device exhibited a slow response speed (25 s and 40 s rise time and 10 s and 300 s decay time with and without Au decoration) due to the inherent defects, such as oxygen vacancies and zinc interstitials.$^{43}$

Figure 1.10. SEM image and schematic of (a,b) ZnO nanowire with Au nanoparticles$^{43}$ and (d,e) ZnO nanowires$^{189}$ fabricated by CVD and thermal oxidation, respectively. I-V characteristics of (c) single nanowire$^{43}$ and (f) multi nanowires$^{189}$ devices both in dark and under 350 nm UV light illumination with the light density of 1.3 mW cm$^{-2}$.

In another approach, Boruah et al.$^{189}$ fabricated highly dense ZnO nanowires grown on a glass substrate by thermal oxidation of metallic Zn thin film in air. Later, they used the reactive thermal evaporation (RTE) process to deposit the Aluminum electrodes of 300 nm thickness on top of the graphene with a gap of 90 μm between the electrodes. Their fabricated device featured a significantly higher photo-current of 1.65 mA (5 orders of magnitude) compared to Liu et al.$^{43}$, at the same applied bias and light density. This higher photo-current might be attributed to the higher solid mass of ZnO nanowires compared to a single nanowire resulting in a greater number of photogenerated electron-hole pairs. However, increasing the number of nanowires resulted in a considerably higher dark-current of 80 mA compared to
the very low dark-current of only 9.7 pA for single ZnO nanowire device. As a result, the photo- to dark-current ratio decreased from $10^3$ of the single nanowire to only 20 of multi nanowires device. In fact, the device conductivity increases significantly by increasing the number of nanowires (higher mass) used in the photodetector.

![SEM image and measured photo response](image)

**Figure 1.11.** SEM image and measured photo response as a function of time as the UV lamp switched on and off for (a) an individual ZnO nanowire\textsuperscript{190} and (b) a multi ZnO nanowires device\textsuperscript{191} fabricated by vapour phase transport process and self-catalysed VLS process, respectively.

Similar results were obtained by kind et al.\textsuperscript{190} using an individual ZnO nanowire device in comparison with the results reported for low temperature synthesized vertical ZnO nanowires.\textsuperscript{191} In fact, under the same applied bias of 5 V and light density of 0.3 mW.cm\textsuperscript{-2}, the photo-current increased significantly from 0.25 µA of the single nanowire\textsuperscript{190} to 13.5 µA of the vertical ZnO nanowires device,\textsuperscript{191} while the photo- to dark-current ratio decreased with more than 3 orders of magnitude due to a higher dark current of 0.2 µA of multi nanowires device\textsuperscript{191} compared to only 1 pA of the single nanowire.\textsuperscript{190}
1.6 Summary and outlook

Advanced in wide bandgap semiconductors have opened the possibility of developing low-cost selective UV photodetectors, capable of operating in harsh atmospheres and featuring significantly high photodetection performances compared with their Si-based counterparts. Several research have been done to fabricate wide bandgap UV photodetectors featuring high photodetection performances, such as high responsivity, detectivity, photoconductive gain, EQE%, and LDR. Different nanostructured morphology, such as 0D, 1D, 2D and 3D nanostructured devices (nanostructured films) were investigated previously in order to achieve the highest photodetection performance. Among the variety of nanostructured devices, 1D nanomaterials with diameters of a few nanometers or less exhibited significantly higher photodetection performances due to their high surface-to-the-volume ratio compared to the other nanostructured devices. In addition, a variety of wide bandgap semiconductors including TiO₂, SiC, ZnO, GaN and SnO₂ were investigated in the last decades as potential materials for UV photodetection applications. Among all wide band gap semiconductors, ZnO is the most investigated material for UV photodetectors applications due to its wide direct bandgap of 3.37 eV at room temperature, ease of fabrication and high transmittance for visible light. However, increasing the performance of ZnO-based photodetectors, particularly their response speed, is still one of the major issues of these types of UV photodetectors, and continuing efforts have been devoted to this issue.

In this thesis, I will investigate the fabrication, photodetection performance and also the detection mechanism of ultraporous nanostructured networks made by self-assembly deposition of hot ZnO nanoparticle aerosols on a glass substrate with interdigitated electrodes. The fabricated nanostructured device will be presented as a highly performing super-structural design due to their extremely high porosity (98%) featuring very high surface-to-the-volume ratio compared to the previously reported nanostructured films.
(porosity of up to 60%). The findings achieved by this research demonstrated a highly performing structure and a flexible and scalable platform technology for the rapid low-cost fabrication and integration of ultraviolet photodetectors in CMOS-compatible portable devices.
1.7 References


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Chapter Two

Self-Assembly Dynamics and Accumulation
Mechanisms of Ultra-Fine Nanoparticles
Publication relevant to this chapter:


Abstract

The self-assembly of nanomaterials into three-dimensional hierarchical structures is a fundamental step impacting a large number of synthetic and natural processes. These range from the scalable fabrication of nano-devices such as batteries, sensors and third generation solar cells to the uptake and accumulation of particulate pollution in the lung alveoli. Here, we show that the dynamic behaviours of ultra-fine particles (UFP < 100 nm) diverge significantly from that of sub- and micro equivalents. For freely diffusing bodies, this leads to the formation of stochastically reproducible films that mimic the morphology and density of ballistically deposited ones. A novel deposition mechanism and regime are proposed that successfully capture the full spectrum of size-dependent self-assembly dynamics. These findings are a significant step toward the engineering of scalable parallel nano-fabrication approaches, and the understanding of the interaction of unbound nanostructures with their surroundings.
2.1 Introduction

Understanding the interaction of nanomaterials with their surrounding is focus of a rising multi-disciplinary research effort. This has become a main priority as both energy generation by hydrocarbon combustion and the development of scalable nano-fabrication processes are rapidly increasing the anthropogenic production and emission of nanostructures. The ultra-fine component of these emissions (< 100 nm) is sufficiently small to penetrate the cardiovascular system upon uptake in the lungs and induce oxidative stress with a resultant dysfunction of lung endothelial cells\textsuperscript{1}. This underlies the development of various diseases\textsuperscript{2} with epidemiological studies showing a correlation between environmental particulate air pollution and a range of endpoints of lung morbidity and mortality\textsuperscript{3-4}. In addition, the commercial production of highly performing nanomaterial-based devices such as high-storage capacity batteries, sensors and solar cells requires scalable fabrication processes. A major challenge is to develop methods that enable robust integration of zero-, one- and three-dimensional nanomaterial with sub-micrometre accuracy and control.

Amongst scalable self-assembly routes, gas-phase nucleation/clustering and aerosol deposition are at the core of industrial nanomaterial production with several nanostructured commodities such as carbon black, Titania pigments and fumed silica produced in megatons per year by flame synthesis\textsuperscript{5}. Collision and coalescence of bodies in the gas-phase is a widespread process\textsuperscript{6-7} that controls the self-assembly of matter from initial atoms\textsuperscript{8} to molecular clusters\textsuperscript{9} and their rapid growth into nano- and micro-scale particles\textsuperscript{10-11}. Collision and dwell conditions govern the resulting body density and morphology. Non- and poorly-coalescing bodies undergoing Brownian collision, for example, can rapidly form fractal-like structures such as soot\textsuperscript{12-13}, deemed a main agent in environmentally induced lung cancer\textsuperscript{14-16} and carbon-black, a
key material in tire and ink production. Synthesis of three-dimensional nanostructures has been demonstrated by deposition of diffusing nanoparticles. This is a scalable low-cost route for the wafer-level parallel fabrication of highly performing nano-devices\textsuperscript{17-18} with potential for emerging technologies such as third-harmonic-upconversion antennas.\textsuperscript{19} However, the limitations and commercial potential of aerosol-based approaches is ultimately determined by the ability of controlling the accumulation and self-assembly dynamics of nanomaterials on a surface.\textsuperscript{20}

The dynamics of nanomaterials in the gas phase is usually described in terms of the ratio between the constant displacement induced by an advective velocity and the stochastically-distributed one induced by Brownian motion, namely the Péclet number (Pe). Several studies\textsuperscript{21-23} have proposed that the resulting key structural properties and morphologies are determined by this ratio alone and are independent of the depositing body size. For example, spherical particles of 5 and 500 nm colliding with a solid surface at a constant Péclet number are expected to lead to the self-assembly of films with the same morphology. However, recent findings\textsuperscript{24-25} have questioned the validity of these models and underlying assumptions. Numerical solutions to the Langevin’s equation of motion have shown an up to 500% increase in film density for deposition of 5 nm spherical particles in the diffusion regime. Similar discrepancies from the Péclet-scaling law were observed by direct Monte Carlo simulations for deposition of 10 nm spheres. As interfacial phenomena are a determinant factor in the interaction of nanomaterial with their surroundings\textsuperscript{26} an improved understanding of nanostructure deposition and accumulation is of significant potential impact to our health and nano-fabrication capabilities.

Here, the dynamics of unbound nanoparticles is investigated over three orders of magnitude in scale aiming to determine a comprehensive mechanistic description of
their accumulation and self-assembly behaviours. Particle displacement is computed by large-scale, grid-free numerical solutions of the Langevin’s equation of motion from the ballistic to the diffusion regime. Validation of the resulting morphologies is pursued by aerosol deposition of freely diffusing nanoparticles and topographical mapping by atomic force and scanning electron microscopes. A novel deposition regime that combines features of ballistic- and diffusion-driven dynamics is proposed. This enables quantitative predictions of micro- to nano-particle interaction with their surroundings providing a unified model of their diverging self-assembly mechanisms.

2.2 Results and Discussion

Initially, conditions were determined to capture the multi-scale porosities and hierarchical film structures resulting from the directed (ballistic regime) and undirected (diffusion regime) self-assembly of nanoparticles. To this aim, the dynamics of monodisperse spheres with a diameter \(d_p\) of 50 nm was simulated by grid-free solution of the Langevin equation of motion as it is discussed further.

2.2.1 Computational Model Outline

Figure 2.1 shows a schematic of a simulation domain consisting of drop and deposition cell. The particles are monodisperse with a constant diameter (5, 10, 30 and 50 nm) and a solid density of 1000 kg.m\(^{-3}\). Particle dynamics is modelled for isothermal condition at 298 K and considering deposition of one particle at a time. In order to obtain true random motion before deposition, a particle is initially released in a cell where particle deposition and film growth are not allowed (Figure 2.1, drop domain). The drop domain height for particle release was equal to 20\(d_p\) for all simulations. The next particle is released after deposition of the previous one. Deposition occurs when a particle touches another particle or the horizontal surface at the end of the deposition domain using a sticking coefficient of 100%. Electrical
charge, Van der Walls force and extra inter-molecular forces are neglected. The impact of temperature and air environment is already accounted in diffusion coefficient and advective velocity. Surface-bond agglomerates were identified by a subroutine determining the neighbor particles in physical connections. More details about the model outline are reported elsewhere\textsuperscript{27}.

\textbf{Figure 2.1.} Schematic of the simulated domain and deposition conditions for nanoparticles on a flat substrate reaching a constant film thickness. Particles are inserted at the drop point and flow downstream.

\subsection*{2.2.2 Simulation Domain Optimization}

Domain independent properties were obtained by asymptotic convergence of the film morphologies with increasing deposition surface/domain size (Figure 2.2 and Figure 2.3). For small Péclet-numbers, the advective velocity is nearby zero resulting in a diffusion driven deposition (diffusive regime/limit). For large Péclet-numbers, the advective velocity is dominant resulting in a ballistic limited deposition (ballistic regime). The simulations were repeated five times to obtain statistically relevant morphologies. The resulting particle distributions were investigated as a function of the total film thickness ($F_d$) and deposition
surface size (Figure 2.2a, b). The side \((L_d)\) of the square deposition surface was increased from \(20d_p\) to \(140d_p\) (Figure 2.2a, b) to assess the impact of geometrical simulation constrains on the resulting film morphology (Figure 2.2a, b, insets). In the diffusion regime, the average film porosity \((\epsilon_{\text{film}})\), calculated from 5 independent simulations, decreased rapidly with increasing total film thickness (Figure 2.2a) reaching a minimum between 0.5 and 1 µm. Further increasing the film thickness resulted in a slow quasi-asymptotic porosity increase. This porosity profile was consistent for all deposition surface size (Figure 2.2a, empty and full circles). However, its magnitude varied substantially with the deposition surface dimension. Increasing the surface side from \(20d_p\) (Figure 2.2a, empty circles) to \(140d_p\) (full circles) increased the minimal \((\epsilon_{\text{min}})\) and quasi-asymptotic \((\epsilon_{\text{q-a}})\) porosities from 0.966 to 0.983 and 0.973 to 0.987, respectively. This represents an up to 59% variation in film density and indicates that the deposition surface size has a considerable impact on the resulting film properties. This is in line with previous particle dynamics simulations (Table 2.1) and partially explains the considerable higher film densities reported in the diffusion regime for small deposition surface \((L_d = 30d_p)\)\(^{21, 24, 25}\). It is worth to mention that the simulation properties are independent of the volume. In fact, the self-assembly of the nanoparticles depends on the Péclet number, particle’s size and its advective velocity.

A different dependency from the simulation constrains was observed in the ballistic regime. There, the average porosity profiles (Figure 2.2b) did not feature a minimum but decreased monotonously with increasing total film thickness converging to a quasi-asymptotic value of 0.865 and 0.857 for a deposition surface side of \(20d_p\) and \(140d_p\), respectively. This corresponded to a maximal film density variation of 5.9% and thus 10 times smaller than that in the diffusion regime. Detailed analysis of the film morphologies (Figure 2.2a, b, insets) revealed that, upon deposition of the first particle layer, main agglomerates forms orthogonally from the deposition surface. These growths by collecting
most of the incoming particle flux; effectively shadowing the deeper film layers. The differences observed in the diffusion and ballistic regimes are attributed to the different horizontal spread (surface density) of these surface-bonded agglomerates.

In the diffusion regime, sufficiently large deposition surfaces enabled to simulate both inter- and intra-agglomerate film porosities (Figure 2.2a, inset ii). In contrast, a small deposition surface restricted the film morphology to that of single agglomerate (Figure 2.2a, inset i) forcefully increasing the resulting film density. This was not the case for the ballistic regime (Figure 2.2b) as the resulting agglomerate horizontal spread was considerably smaller. As a result in the ballistic limit, both small (inset i) and large (inset ii) deposition surfaces were able to capture the inter- and intra-agglomerate film porosities. This was further supported by visual rendering of the deposited particle three-dimensional distributions (Figure 2.2b, insets). These showed nearly indistinguishable film morphologies for large and small deposition surfaces. For all deposition conditions ($10^{-7} \leq Pe \leq 100$), it was found that the average film porosity (Figure 2.3a, b) increased with increasing deposition surface dimension and converged for $L_d \geq 100d_p$. This is in line with previous particle dynamics results\textsuperscript{23,27} showing consistent film densities for a simulation surface side larger than $100d_p$. 

Figure 2.2. Average film porosity ($\varepsilon_{film}$) as a function of total film thickness ($F_d$) with particle diameter of 50 nm and two domain lengths ($30d_p$ and $140d_p$) in the (a) diffusion and (b) ballistic regime.

![Figure 2.2](image-url)
(Table 1). As a result, here, further investigation of the deposition dynamics was conducted with a large simulation surface size of $140d_p$ that enabled the self-assembly of more realistic film structures.

**Table 2.1.** Comparison of film key structural parameters obtained by particle deposition dynamics.

<table>
<thead>
<tr>
<th>Particle Diameter</th>
<th>Peclet-Number</th>
<th>Domain Length</th>
<th>Film Thickness</th>
<th>Deposition Surface</th>
<th>Average Film Porosity ($\varepsilon_{film}$)</th>
<th>Ref.</th>
</tr>
</thead>
<tbody>
<tr>
<td>50 nm</td>
<td>$10^{-7}$-100</td>
<td>140$d_p$</td>
<td>120$d_p$</td>
<td>Flat Square</td>
<td>0.990 - 0.867</td>
<td></td>
</tr>
<tr>
<td>30 nm</td>
<td>$10^{-7}$-100</td>
<td>200$d_p$</td>
<td>180$d_p$</td>
<td>Cylindrical Capillary Walls</td>
<td>0.98 - 0.86</td>
<td>27</td>
</tr>
<tr>
<td>10 nm</td>
<td>$10^{-7}$-100</td>
<td>30$d_p$</td>
<td>160$d_p$</td>
<td>Flat Square</td>
<td>0.965 - 0.84</td>
<td>25</td>
</tr>
<tr>
<td>5 nm</td>
<td>$10^{-7}$-100</td>
<td>30d$p$</td>
<td>50$d_p$</td>
<td>Flat Square</td>
<td>0.969 - 0.848</td>
<td>21</td>
</tr>
<tr>
<td>30 nm</td>
<td>Diffusion &amp; Ballistic Regime</td>
<td>30$d_p$</td>
<td>50$d_p$</td>
<td>Flat Square</td>
<td>0.969 - 0.848</td>
<td>24</td>
</tr>
<tr>
<td>10 nm</td>
<td>Diffusion Regime</td>
<td>30$d_p$</td>
<td>100$d_p$</td>
<td>Flat Square</td>
<td>0.93</td>
<td></td>
</tr>
<tr>
<td>a$^a$</td>
<td>$10^{-1}$-100</td>
<td>512$d_p$</td>
<td>400$d_p$</td>
<td>Flat Square</td>
<td>0.98 - 0.86</td>
<td>23</td>
</tr>
<tr>
<td>a$^a$</td>
<td>$10^{-1}$-100</td>
<td>512$d_p$</td>
<td>--</td>
<td>Flat Square</td>
<td>0.98 - 0.86</td>
<td>28</td>
</tr>
</tbody>
</table>

$^a$The domain was structured in a cubic subdomain lattice with a side length of a.

$^b$The average porosity was estimated from the plateau packing density ($\Phi_{sl}$).

Increasing the Pe number from $10^{-7}$ (Figure 2.3a, pure diffusion regime) to 100 (Figure 2.3b, pure ballistic regime) leads to decreasing the porosity of composed film at all surface sizes. This significant change is attributed to the deposition style of the particles during transition from diffusion to the ballistic regime. In fact, at a small Pe number the particle transport is dominated by diffusion and its movement is scattered towards the deposition surface. In that case, the deposited film grows with a fractal-like structure.

In addition, it was found that small deposition surfaces having a square side ($L_d$) smaller than 120 times the particle diameter leads to up 59% artificially higher film
densities. This is attributed to the physical constrains that are not sufficient to achieve periodic symmetry conditions and thus do not enable establishment of the multi-scale nano- and micro-porosity observed by aerosol deposition of nanoparticles and agglomerates. This explains the drastic increase in film densities (ca. 500%) predicted in the diffusion regime for deposition of ultra-fine nanoparticles \( (d_p < 30 \text{ nm}) \) by recent small-domain-constrained studies. As a result, all further simulations were conducted with a large domain size of \( 140d_p \) that enables the self-assembly of more realistic, hierarchical film morphologies.

**Figure 2.3.** Average film porosity \((\varepsilon_{\text{film}})\) for spherical nanoparticles with a diameter of 50 nm as a function of domain length \((20d_p \text{ to } 140d_p)\) from (a) diffusion to the (b) ballistic regime.

### 2.2.3 Model Validation

Validation of these numerical results was obtained by comparison of the converged nanoparticle solid fraction with previous large-scale Monte Carlo simulations (Table 2.1) showing good agreement and a characteristic S-shaped dependency from the Péclet number in line with very recent results (Figure 2.4). Figure 2.4 shows the values for plateau packing density as a function of the Pe number for particle diameter of 50 nm in comparison to Rodriguez-Perez et al. and Castillo et al. on flat surface deposition and Elmøe et al. on a porous substrate. The resulted packing density is in agreement with these results. Rodriguez-
Perez et al.\textsuperscript{23} and Castillo et al.\textsuperscript{28} studied the particle deposition on a flat surface with structured grid domain resulting in an increase of order and density. Elmøe et al.\textsuperscript{27} simulated the particle deposition on a porous capillary substrate. The domain length used by both researches was sufficiently large ($512d_p$ and $80d_p$)\textsuperscript{23,27,28} leading to a good agreement with the results presented here. While, for Dreyer et al.\textsuperscript{24} and Ogunsola et al.\textsuperscript{22}, the domain length was not sufficiently resulting lower final porosities ($30d_p$ and $40d_p$ respectively) (Table 2.1).

\begin{figure}[h]
\centering
\includegraphics[width=0.7\textwidth]{figure2.4.png}
\caption{Plateau solid fraction as a function of the Pe number for deposition of single spherical particles of 50 nm in diameter by this work (diamond) and comparison with previous researches obtained for flat deposition surfaces\textsuperscript{23,28} (rectangles and circle) and capillary\textsuperscript{27} (triangles).}
\end{figure}

\subsection*{2.2.4 Self-Assembly Dynamics of Nanoparticle Films}

To determine the impact of the nanoparticle size on the film self-assembly dynamics, the structural properties obtained by deposition of 50 and 5 nm particles were further investigated. Figure 2.5 shows sections of the hierarchical morphologies formed by their self-assembly in the diffusion and ballistic regimes. Each contiguous set of touching particles, a surface-formed and bond agglomerate was labelled with a colour. It was found that independently of the deposition regime and particle size,
nanoparticle film self-assembly is driven by the formation of parallel agglomerates growing in the vertical direction (Figure 2.5). However, the density and horizontal spreading of these agglomerates was strongly dependent from the particle size and deposition conditions leading to significantly different morphologies and structural properties.

**Figure. 2.5.** Three dimensional plots of film sections self-assembled in the diffusion (a,b,c) and ballistic (d,e) regimes for particle 50 nm (a,d) and 5 nm (b,c,e) in diameter. Each contiguous set of particles (surface-bond agglomerate) was labelled with a colour.

For the 50 nm particles, two distinct characteristic accumulation behaviours were determined. In the diffusion regime, the film morphology was characterized (Figure 2.5a) by the rapid establishment of a prevailing agglomerate in the first $10d_p$ of
thickness. These large structures shadowed the deposition surface collecting the incoming nanoparticle flux. At $20d_p$ thickness, a single agglomerate became prevalent spreading over a horizontal surface of $10d_p \times 10d_p$. Further increasing the film thickness did not result in additional horizontal growth but in a series of laterally-confined agglomerates growing in parallel. This branch-like vertical growth is in line with the morphology observed for aerosol-deposited TiO$_2^{30}$ and SnO$_2^{31}$ nanoparticle films utilized as porous dye sensitized solar cells electrodes and chemical sensors, respectively. In contrast, ballistically-driven deposition led to a different films structure (Figure 2.5d). There it was not possible to identify prevailing agglomerate. Instead, several parallel agglomerates grew from the deposition surface. This is attributed to the relatively small path swept by each depositing particle at high Péclet numbers and in line with the high film density observed by deposition of nanoparticle aerosols in burner low-pressure impactors$^{32}$.

In contrast, the 5 nm particles did not feature these two opposite structural regimes. Instead, in the first $10d_p$ film thickness, both diffusion- (Figure 2.5b) and ballistic-driven (Figure 2.5e) growth revealed the same structural densities and morphologies as those observed for the 50 nm particles in the ballistic regime (Figure 2.5d). After $40d_p$ thickness (Figure 2.5c), diffusion-driven deposition of 5 nm particles led to the establishment of a single surface-bond agglomerate morphology. This is in line with the initial densification computed with decreasing particle size at low Péclet numbers. Furthermore, it shows that the self-assembly dynamics of ultra-fine spheres having a diameter below 50 nm differ from that expected for purely diffusive bodies and, close to the substrate interface, approaches ballistic-induced self-assembly. This is attributed to a self-induced variation of the collision mechanism with decreasing particle size leading to similar partially vertically-directed straight collision trajectories as for
ballistic bodies. These findings explain the high density observed for thin nanoparticle patterns obtained by parallel electrodynamics focusing of charged particle-laden aerosols\textsuperscript{17}.

2.2.5 Particle Size-Dependent Structural Properties

The correlations between key film structural properties and particle size were further investigated by computation of the film density profiles (Figure 2.6) as a function of the particle diameters in the ballistic (Pe = 100) and diffusion regimes (Pe = 10\textsuperscript{-7}). It was found that in the former all particle sizes lead to identical packing density profiles (Figure 2.6a). In contrast, in the diffusion regime the surface density of the first particle layer increases by more than 200\% with decreasing particle diameter from 50 to 5 nm. Furthermore, film growth (Figure 2.6b) did not lead to the establishment of a constant/plateau-density as for ballistically-driven self-assembly (Figure 2.6a). Instead, for diffusion-driven deposition, the density decreased continuously from an initial maximum near the substrate interface to a minimum on the top film surface. This is particularly relevant with respect to the accumulation of ambient UFP in the lung alveoli and the nano-fabrication of three-dimensional nanostructured layers as in both systems particle deposition is, usually, diffusion-driven. The high and variable densities of the nanoparticle-substrate interfaces, reported here, indicate that the established Péclet-scaling laws cannot be applied to model the interaction and accumulation of diffusive nanoparticles with their surroundings.

Further investigation of the nanoparticle film morphologies revealed a unique structure. Both for the ballistic and diffusion regimes, a ripple-like density profile (Figure 2.6a,b insets) was observed in the first 10\textit{d}_p film thickness. This was characterized by three main peaks representing the maxima and minima of the local
slice densities. The first density peak was located at $0.8d_p$ height from the deposition surface and, for ballistic deposition (Figure 2.6a, inset), reached the highest slice packing density of 0.3 and thus nearly half of the random close packing density (0.64) for monodisperse spheres. This is attributed to the discrete dimension of the depositing nanoparticles. In fact, for deposition of a single layer of spheres on a flat surface, the maximal density will always be found at a film height of $0.5d_p$. Here, the shift from $0.5d_p$ to $0.8d_p$ height is attributed to the intercalation of the layer during three-dimensional growth.

**Figure. 2.6.** Representative slice packing density profiles (a) in the ballistic and (b) diffusion regimes as a function of the particle diameter from 50 to 5 nm. Three main density maxima (a, b, insets) are determined at 0.8, 1.6, and 2.4 relative film thicknesses ($z/d_p$). The magnitude of these maxima is (a) independent from the particle diameter in the ballistic regime while (b) increases by more than 100% with decreasing particle size in the diffusion regime.

The second and third density peaks (Figure 2.6a,b inset) were found consistently at $1.6d_p$ and $2.4d_p$ thickness and attributed to the second and third particle layer maxima. Further smaller peaks were found at alternating film heights above $2.4d_p$ but their position and intensity did not converge among different simulations resulting in a destructive interference. This suggests that upon a thickness of $2.4d_p$, the film morphology evolves from a two- to a three-dimensional disordered state. However,
while for ballistically driven deposition the peaks’ magnitude was independent from the particle size (Figure 2.6a, inset), in the diffusion regime (Figure 2.6b, inset) it increases with decreasing particle diameter. The first peak (0.8\(d_p\)) slice packing density increased from 0.122 to 0.239 with decreasing particle size from 50 to 5 nm. As a result, a 5 nm nanoparticle film had an initially 100% higher density than that made of 50 nm particles. This significant densification of the substrate-nanoparticle interface explains the rapid shunting of nanoparticle-based ultra-sensitive sensors made by aerosol deposition of ca. 5 nm particle layers.18 Furthermore, it indicates that the mechanisms governing the accumulation of particles on an interface change with decreasing size. This leads to a significantly stronger substrate-nanoparticle interaction than previously modelled with sub-micro and micro-scale particles in the diffusion regime23.

Figure 2.7. TEM image of deposited non-agglomerated TiO\(_2\) particles on TEM grid by flame spray pyrolysis.

The validity of these predictions was assessed by characterization of the interface morphology obtained by deposition of particle-laden aerosols on polished Si-wafers. A hot TiO\(_2\) aerosol with an average particle diameter of 5 nm and a narrow size distribution was produced by flame synthesis of organometallic precursor as previously reported in details33. This aerosol was orthogonally impinged on a polished Si-wafer resulting in a thermophoretically-driven34 particle flux directed toward the wafer surface. The aerosol concentration and deposition conditions were controlled by
the precursor concentration, dilution and temperature gradient resulting in nearly non-agglomerated nanoparticles as determined by thermophoretic sampling on transmission electron microscopy (TEM) grids (Figure 2.7) and deposition Péclet numbers of $10^{-1}$-$10^{-2}$ (as computed in section 4.4.1). It was found that by sufficiently decreasing the deposition time a quasi-monolayer of particles in contact with the substrate surface could be self-assembled.

Figure 2.8. AFM topography and SEM images of (a, b) a quasi-monolayer and (d, e) a multi-layer of TiO$_2$ nanoparticles (5 nm in diameter) aerosol-deposited on polished Si-wafers. The AFM and SEM analysis revealed a consistent surface density (SD) of 0.2$\pm$0.015. Comparison of 5 nm particle size distributions computed by Langevin dynamics show comparable cross-sectional (a,b, insets) and (c, f) horizontal morphological features.

Figure 2.8a shows an atomic force microscopy (AFM) topographical scan of the Si-wafer surface upon deposition of a complete first layer of nanoparticles. The surface was characterized by nano-scale roughness with most peaks having an average height of ca. 5 nm in good agreement with the TiO$_2$ particle size. Some few peaks with a maximal height of ca. 17 nm were randomly distributed on the surface and are attributed to the initial formation of surface-bond agglomerates. Particle deposition and initial film self-assembly was confirmed by scanning electron microscopy (SEM)
analysis (Figure 2.8b). Simulation of 5 nm particle deposition at comparable conditions ($Pe = 10^{-2}$) and with a maximal film thickness corresponding to that measured by AFM (17 nm) led to structural similar morphologies (Figure 2.8c). These were also characterized by a rough matt of 5 nm asperities with some few higher peaks randomly spread on the surface. The impact of the temperature difference between the simulations and the flame-made aerosol deposition experiments was accounted by the computation of the Péclet number that results in the same diffusion coefficient to advection velocity ratio. The larger mean free path of the experimental particles is expected to lead to only slightly higher interface densities as the ratio between mean free path and particle size is close to one for both experimental and simulated particles.

Comparison of the film side view obtained by AFM and particle dynamics (Figure 2.8a, insets) showed consistent cross-sections with, however, smoother film height variations observed by AFM. This was attributed to the limited AFM inter-particle resolution not enabling to resolve small gaps between the deposited particles. Doubling the aerosol exposure time nearly doubled the film thickness (Figure 2.8d) leading to a maximal film height of nearly 35 nm. This is in line with the constant film growth rates reported for thermophoretic deposition of flame-made nanoparticle aerosols\textsuperscript{20}. This confirms further that upon deposition of the first nanoparticle monolayer (Figure 2.8a,b) the film growth proceed mainly by self-assembly of parallel agglomerates vertically-aligned to the deposition surface (Figure 2.8b,c).

This morphology was equivalent to that obtained by simulation of 5 nm nanoparticle deposition and a maximal film thickness of 35 nm (Figure 2.8d inset). A main difference between the simulated (Figure 2.8c,f) and aerosol-deposited films was the larger variation in size observed by SEM (Figure 2.8b,e). This is attributed to both the polydisperse nature of the flame-made nanoparticles, and the limited resolution of
the SEM not being able to discern primary particles of 5 nm within single agglomerates. Analysis of the nanoparticle surface by AFM and SEM revealed a surface density (SD) of 0.20±0.015 and thus very close to that (0.19±0.003) predicted by particle dynamics.

2.3 Experimental Validation

2.3.1 Péclet-Number Computation

Péclet-number is a non-dimensional number defined as:

\[ Pe = \left( \frac{d_p}{\nu} \right)^2 \]  

(2.1)

where \( d_p \) is the particle diameter, \( \nu \) is the particle translational velocity and \( D_p \) is the diffusion coefficient. The diffusion coefficient, \( D_p \), of a particle in a fluid is calculated by the Stokes-Einstein equation:

\[ D = \frac{k_b T}{f} \]  

(2.2)

where \( k_b \) is the Boltzmann constant \( (1.3806488 \times 10^{-23} \text{ m}^2\text{kg.s}^{-2}\text{K}^{-1}) \), \( T \) is the temperature and \( f \) is the friction coefficient of the particle in the fluid. In continuum \( (k_n << 1) \), transition \( (K_n \approx 1) \), and free molecular regime \( (k_n >> 1) \), where the friction coefficient, \( f \), is calculated by:

\[ f = 3\pi \mu d_p \]  

for \( k_n << 1 \)  

(2.3)

\[ f = \frac{3\pi \mu d_p}{C_c} \]  

for \( k_n \approx 1 \) and \( k_n >> 1 \)  

(2.4)

where \( \mu \) is the viscosity of the medium, \( d_p \) is the particle diameter, \( K_n \) is the Knudsen number \( (K_n = 2\lambda_{gas}/d_p, \ \lambda_{gas} \) is the gas molecule mean free path), and \( C_c \) is the Cunningham correction factor which is equal to:
\[ C_c = 1 + K_c (A_1 + A_2 e^{\frac{-2A_3}{K_c}}) \]  \hspace{1cm} (2.5)

where the values for \( A_1, A_2 \) and \( A_3 \) in the air are equal to 1.21, 0.40 and 0.78, respectively. The aerosol temperature \( (T_F) \) near the substrate is 773 K as experimentally presented. The fluid dynamic viscosity \( (\mu_F) \) at 773 K and \( C_c \) for \( K_c \) of 10-100 are \( 3.481 \times 10^{-5} \) kg.m\(^{-1}\).s\(^{-1}\) and 100 respectively. This calculation leads to a friction and diffusion coefficient of \( 1.64 \times 10^{-14} \) kg.s\(^{-1}\) and \( 6.5 \times 10^{-7} \) m\(^2\).s\(^{-1}\) which is in agreement with \( D \) reported by other researchers\(^{20,29}\). In the absence of electrical forces, the main nanoparticle deposition mechanisms are Brownian diffusion, thermophoresis and impaction. The thermophoretic velocity, \( v_T \), is usually described as\(^{20}\):

\[ v_T = -K_T \frac{\mu_F (T_F - T_S)}{\rho_F \delta_T T_P} \]  \hspace{1cm} (2.6)

where \( T_P \) is the particle temperature (approximated by the average of the aerosol \( (T_F) \) and surface \( (T_S) \) temperatures), \( \rho_F \) is the fluid density, \( \delta_T \) is the boundary layer thickness and \( K_T \) is the thermophoretic coefficient which is usually assumed independent of the particle size equal to 0.55. A surface temperature \( (T_S) \) of 410 K, a small boundary layer thickness between 0.01-1 mm and the air density of 0.4565 kg.m\(^{-3}\) at 773 K. This leads to an advective velocity of 2.57 m.s\(^{-1}\). Using diffusion coefficient of \( 6.5 \times 10^{-7} \) m\(^2\).s\(^{-1}\) results in a Péclet-number between \( 10^{-3}\)-\( 10^{-1}\).

2.3.2 Analytical Model

The different mechanisms for particle deposition at ballistic, randomly oriented ballistic and diffusion regimes is shown in Figure 2.9. The scaled particle SD is computed as a ratio of horizontal area shadowed by a deposited particle to that required for a particle to deposit. The horizontal area shadowed by a particle \( (A_{dp}) \) with the diameter of \( d_p \) is calculated from the following equation (Figure 2.9a, insets):
\[ A_{dp} = \frac{\pi d_p^2}{4} \]  

(2.7)

This value is constant for all different regimes as the particle size is constant. However, the required area for a particle to deposit is different for different regimes. In the ballistic regime, the advective velocity is dominant and particle deposits on a straight orthogonal trajectory to the surface due to the high advective velocity. In this case, the collision area for a particle to deposition on the surface before colliding with any other particle can be calculated as follows:

\[ A_{stat} = \pi d_p^2 \]  

(2.8)

**Figure 2.9.** Different deposition mechanism and scaled particle surface density in (a) ballistic, (b) randomly oriented ballistic and c, diffusion regime as a function of the (d) particle diameter and (e) mean free path. The increase in travelled path for diffusive particle \((\lambda_p/d_p<1)\) is accounted through the \(K_{BPF}\) factor as discussed in details in the analytical model section.

Despite different mechanism for particle deposition, this is the minimum area a particle requires to deposit on the surface without touching any other ones. The lowest porosity of the ballistic films and the highest SD are attributed to this minimum collision area required for particle (Figure 2.9a) when the particle dynamic is dominated by high advective velocity.
the randomly oriented ballistic regime, the particle is sufficiently small ($d_p < 10$ nm) and touches the surface on a single Brownian displacement (Figure 2.9b). The collision area calculated for these particles is the sum of the minimal area required for particle deposition ($A_{stat}$) and the additional horizontal area swept by a particle due to the Brownian displacement, $X$, within the potential collision length, $d_p$, ($A_{dyn}$). Thus, the collision area is calculated from the following equation:

$$A_{stat} + A_{dyn} = \pi d_p^2 + (2d_pX - A_{over}) \quad (2.9)$$

where $A_{over}$ is the area overlapped between the minimal area required for deposition and that due to single-step Brownian displacement which can be calculated as below:

$$A_{over} = 2 \int_0^X (d_p^2 - y^2)dy = X \sqrt{d_p^2 - X^2} + d_p^2 \sin^{-1}\left(\frac{X}{d_p}\right) \quad (2.10)$$

$$A_{over} = d_p^2 \left[X \sqrt{1 - X^2} + \sin^{-1}(X)\right] \quad (2.11)$$

The collision area of a particle in randomly oriented ballistic regime is calculated using equations (4.9) and (4.11):

$$A_{stat} + A_{dyn} = d_p^2 \left[\pi + 2\bar{X} - \bar{X}\sqrt{1 - \bar{X}^2} + \sin^{-1}(\bar{X})\right] \quad (2.12)$$

This results in a scaled particle SD equal to:

$$SD = \frac{A_{dp}}{A_{stat} + K_{RPF}A_{dyn}} \quad (4.13)$$

where the $K_{RPF}$ is the Randomly Path Factor and for a single-step Brownian displacement is equal to 1.

$$SD = \frac{\pi}{4 \left[\pi + 2\bar{X} - \bar{X}\sqrt{1 - \bar{X}^2} + \sin^{-1}(\bar{X})\right]} \quad (2.8)$$

For the diffusion regime, the amount of Brownian steps increases due to the particle mean free path ($\lambda_{dp}$) becoming smaller in the collision length (Figure 2.9d). The obtained $K_{RPF}$
factors resulting in an s-shaped profile between particle size and particle mean free path as a function of \( K_{RPF} \) factor.

### 2.3.3 Computation of the Brownian Displacement through the Collision Length

The Brownian’s motion induced horizontal displacement within the vertical collision length \( (d_p) \) was computed from the average transition time as a function of particle size and Péclet-number:

\[ v \cdot t + X = d_p \]  \hspace{1cm} (2.14)

where \( v \) is the particle velocity, \( t \) is the time, \( X \) is the Brownian displacement and \( d_p \) is the particle diameter. Following the Stokes-Einstein equation, the distance travelled by a particle suspended in a fluid is related to the diffusion coefficient of the particle in that fluid, \( D_p \), and the travelled time, \( t \):

\[ X = \sqrt{(2D_p \cdot t)} \]  \hspace{1cm} (2.15)

This leads to:

\[ d_p^2 - (2d_p \cdot v + 2D_p)t + v^2t^2 = 0 \]  \hspace{1cm} (2.16)

Solution of quadratic equation results in a transition time, \( t \):

\[ t = \frac{d_p}{v} + \frac{D}{v} - \frac{\sqrt{D^2 + 2d_p \cdot v \cdot D}}{v^2} \]  \hspace{1cm} (2.17)

By replacing this time in equation \( (2.16) \), we obtained an average Brownian displacement, \( X \):

\[ X^2 = \frac{2d_pD}{v} + \frac{D^2}{v^2} - \frac{2D\sqrt{D^2 + 2d_p \cdot v \cdot D}}{v^2} \]  \hspace{1cm} (2.18)

Considering the Péclet-number definition:

\[ Pe = \left( \frac{d_p/2}{D} \right)v \]  \hspace{1cm} (2.19)

This leads to a Brownian displacement, \( X \), equal to (Figure 2.10):
\[ X = d_p \sqrt{\frac{1}{Pe} + \frac{1}{2Pe^2} - \frac{1}{2Pe^2} \sqrt{1 + 4Pe}} \]  

(2.20)

**Figure 2.10.** Brownian displacement to the collision length (\(\alpha_d\)) ratio as a function of Péclet-number.

### 2.4 Self-Assembly Mechanisms and Regimes

The mechanisms underlying this interface densification and diverging self-assembly dynamics were assessed by analysis of the first particle layer/surface density (Figure 2.11) over a comprehensive range of deposition conditions. Independently of the particle size, all density profiles had an S-shaped dependence from the Péclet number (Figure 2.11a) and converged toward a density of 0.25 in the ballistic regime. However, at low Péclet numbers, the surface density was a function of the particle size. There, decreasing the particle size from 50 to 5 nm increased the surface density from 0.11 to 0.19. This is in very good agreement with the AFM- and SEM- surface densities (0.20±0.015) obtained by aerosol deposition of 5 nm particles at a Péclet number of \(10^{-2} - 10^{-1}\) (Figure 2.8a).
Here, it is proposed that the increase in interface density with decreasing particle size is due to a decrease in the horizontal area swept by the particle during its transition through the collision length. The latter can be computed by the minimal vertical collision distance from a particle deposited in the first layer and for monodisperse particles is equal to $d_p$.

**Figure 2.11.** Scaled particle surface density as a function (a) of the Péclet number and (b) particle mean free to diameter ratio at $Pe = 10^{-7}$ for different particle sizes. Comparison of the SD computed by (a, symbols) Langevin dynamics and (a, lines) modelled by equation (4.23) with corresponding $K_{RPF}$ show excellent agreement. Departure from the diffusion regime is observed (b) already for particles smaller than 100 nm.

Although in the diffusion regime both small (e.g. 5 nm) and large ($\geq 50$ nm) particles are expected to deposit by a random path, this is not always true within a small collision distance (Figure 2.11b, insets). In particular, if the collision length ($d_p$) is smaller than the particle mean free path ($\lambda_p$) than the particle can move on a straight trajectory before collision with the surface. This results in a decrease of the horizontal area swept by the particle and therefore of its collision likelihood. As a result, more ultra-fine particles can reach the deposition surface resulting in the higher interface density computed with decreasing particle size (Figure 2.11a).

This accumulation mechanism was validated by development of a comprehensive analytical model for the first layer density (Figure 2.9a, lines). As it is discussed in
details in section 4.4.2, the average surface density was estimated by the ratio between
the horizontal projections of the area occupied by a sphere ($A_{dp}$) and that required ($A_{stat} + K_{RPF} \cdot A_{dyn}$) to travel through the collision length ($d_p$):

$$SD = \frac{A_{dp}}{A_{stat} + K_{RPF} \cdot A_{dyn}}$$ (2.21)

with $A_{dp}$ being the horizontal area ($\pi d_p^2/4$) occupied by a deposited spherical particle, $A_{stat}$ being the horizontal collision area ($\pi d_p^2$) of a depositing particle, $A_{dyn}$ being the horizontal projection of the area swept by a particle moving at an incident angle $\alpha$ through the collision length, $\alpha$ being the angle between the vertical axis and the trajectory of a particle moving horizontally due to Brownian displacement ($X$) and vertically due to an advective velocity and Brownian displacement ($v \cdot t + X$), and $K_{RPF}$ being the additional path the resulting straight diagonal line swept by a particle due to the stochastic nature of diffusion. The horizontal projection of the area swept ($A_{dyn}$) is only a function of the particle size and Péclet number, and thus of the relative Brownian displacement ($\bar{X} = X/d_p$):

$$A_{dyn} = 2d_p^2 \bar{X} - d_p^2 \left[ \bar{X} \sqrt{1 - \bar{X}^2} + \sin^{-1}(\bar{X}) \right]$$ (2.22)

This leads to a general analytical equation for the first layer density with the only variables being the relative Brownian displacement and swept path ($K_{RPF}$ factor):

$$SD = \frac{\pi}{4 \left[ \pi + K_{RPF} (2\bar{X} - \bar{X} \sqrt{1 - \bar{X}^2} + \sin^{-1}(\bar{X})) \right]}$$ (2.23)

The validity of this analytical model (Figure 2.11a, lines) was assessed against the surface density computed by particle dynamics simulation (Figure 2.11a, symbols). For all particle size and Péclet number, equation (2.23) shows an excellent agreement with the numerical results with minor deviations observed only in the transition regime ($Pe = 10^{-1}-1$). In the ballistic regime, the Brownian-induced displacement within the
collision length approaches zero resulting in $A_{dyn} \ll A_{stat}$, and thus to a converging surface density $\approx A_{dp}/A_{stat} = 0.25$ (Figure 2.9). In contrast, at low Péclet numbers, the area swept by a depositing particle within the potential collision length increases leading to $A_{dyn} \approx A_{stat}$, and thus, for the 50 nm particles, in up to 50% less dense interface than in the ballistic regime (Figure 2.11a).

It was found that the length of the swept path and thus the magnitude of the $K_{RPF}$ factor decreased with decreasing particle size leading to more dense interfaces. This is attributed to the different deposition mechanisms. In fact, while purely diffusive particles ($\geq 50$ nm) perform a random trajectory within the collision length, sufficiently small particles can cross it on a straight line (Figure 2.9) due to their mean free path being larger than the collision length/particle diameter. However, such (straight) ballistic deposition behaviour differs from that in the ballistic regime, as the depositing particle trajectory is not orthogonal to the substrate but has an incident angle determined from the ratio between vertical and horizontal displacement. The maximal incident angle ($\alpha_{max}$) was found at $Pe \ll 1$ and represents an orthogonal, nearly isosceles, triangle having as hypotenuse the particle trajectory (Figure 2.9). This regime, here after referred as randomly-oriented ballistic regime, requires a larger area for a particle to deposit than in the pure ballistic regime but a considerably smaller than for purely diffusive bodies. This is in good agreement with the observed film (Figure 2.6b) and interface (Figure 2.11a) densification with decreasing particle size.

The conditions for departure from the diffusion to the randomly-oriented ballistic deposition regime and their impact on the $K_{RPF}$ factor were investigated for quasi-purely diffusing bodies ($Pe$ of $10^{-7}$). Figure 2.11b shows the resulting interface density at a Péclet number of $10^{-7}$ as a function of the ratio between particle mean free path ($\lambda_p$) and collision length ($d_p$) and particle size from the micro-scale ($1 \mu m$) to the
ultra-fine range (1 nm). The resulting monolayer density showed an S-shaped dependency from the $\lambda_p/d_p$ ratio approaching 0.21 and 0.08 for 1 and 1000 nm particles, respectively. Most importantly, in the randomly-oriented ballistic limit the $K_{RPF}$ factor converged toward 1. This is in excellent agreement with the proposed straight single-diagonal step deposition model and explains the different deposition mechanism observed for small (< 100 nm) nanoparticles.

In contrast, for large sub- and micro-scale particles having a mean free path considerably smaller than their diameter a true random walk is achieved throughout the collision length. This results in an increased swept path ($K_{RPF}$) approaching 17 times that travelled by the smallest particles (Figure 2.11b). These findings show that the dynamics of ultra-fine nanoparticles (< 100 nm) is not accurately captured by the diffusion regime, and their accumulation mechanism relies outside the validity of established Péclet scaling laws. Furthermore, as the swept path do not depend only from the particle size but from its ratio with the particle mean free path, with increasing surrounding temperature large nanoparticles will result in similar interface densifications as smaller ones.

Here, in contrast to previous studies\textsuperscript{21,24-25} we have shown that the densification of films synthesized by self-assembly of diffusive ultra-fine particles does not involve the whole film structure but is confined to a certain thickness from the deposition surface. As a result, sufficiently thick films (> 80$d_p$) converge toward the same density (Figure 2.6b). This densification is attributed to the straight diagonal trajectory followed by sufficiently small (< 100 nm) ultra-fine particles within the collision length with the deposited particle layer. Also in contrast to previous reports, this densification was observed to become predominant already below 100 nm, and thus for the whole ultra-fine particle range. An S-shaped densification was observed with particle size varying
from 1 µm to 1 nm identifying that the strongest morphology variation are expected between a particle size of 5 to 100 nm. Amongst other, this model is a significant step toward the large-scale fabrication of emerging nano-devices such as third-harmonic-upconversion antennas where ultra-fine semiconductor nanoparticles (< 25 nm) need to be precisely collocated in the small gap (e.g. 35 nm) of a plasmonic nanorod dimer\textsuperscript{19}. With respect to the self-assembly of polydisperse aerosols, often encountered in realistic conditions, two contrasting mechanisms are expected. Deposition of small particles on the surface of larger ones is known to increase the total film density by partially filling the pores between large particles. On the other side, if small particles would deposit on the deposition surface close to a, previously deposited, larger particles than the relative collision length would be increased resulting in a smaller mean free path to collision ratio. This would in turn decrease the film density close to the interface. As a result, the effect of polydispersity is not trivial and cannot be predicted independently from the specific size distribution, free mean path to average particle size ratio and film thickness.

2.5 Conclusions

A novel mechanistic description of the self-assembly mechanisms of nanoparticles into three-dimensional structures was presented. It was found that the structural properties of hierarchical films made of ultra-fine particles diverge from that expected in diffusion regime for sub-micron and micro equivalents leading to up to 300% denser interface morphologies. A new randomly-oriented ballistic deposition regime was successfully proposed to account for the collision and densification mechanisms of nanostructures. This enabled precise prediction of their accumulation and clustering dynamics by a simple analytical model that accounts for the degree of randomness of the deposition process.
In all regimes, the formation of surface-bond fractal-like agglomerates was determined as a main mechanism for the establishment of hierarchical morphologies. These findings are a significant step toward the understanding of the interaction of suspended nanostructures with their surroundings. This is of immediate impact to the engineering of several synthetic and natural nano-fabrication processes. For example, it elucidates the rapid achievement of electrical percolation in dispersed nanoelectrode devices, a bottleneck in improving the conductivity of nanoparticle films. It enables modeling and engineering of the properties of nano-patterned structures by scalable means such as electrodynamics focusing. Furthermore, this model can be applied to the investigation of the inflammatory effects of ultrafine particles (UFP < 100 nm) in human lungs providing new insights on the interaction of nanomaterials with delicate biological interfaces.
2.6 References


Chapter Three

Ultra-Porous Electron-Depleted ZnO Nanoparticle Networks for Highly Sensitive Portable Visible-Blind UV-Photodetectors
Abstract
The importance of UV detectors is growing because of the demand for wide range of environmental, military, industrial, flame sensing, water sterilization, and early missile plume detection applications. Here, we report a hierarchical design and a rapid synthesis approach for the fabrication of highly performing visible-blind photodetectors. Combined nano- and micro-scale fine-tuning of the film optical and electrical properties results in record-high milliampere photo-currents while preserving nano-ampere dark-currents and excellent selectivity to ultra-low UV light intensity. This is a significant improvement over state-of-the-art devices where a compromise is necessary between high photo-current and low dark-currents. As a result, these photodetectors do not require bulky and costly read-out circuitry and can be directly integrated in portable CMOS-based electronics that is currently utilized in many wearable devices.
3.1 Introduction

Portable visible-blind photodetectors have a wide range of application including UV dosage monitoring for skin cancer prevention, flame and missile launch detection, optical communication and astronomy.\textsuperscript{1-3} Si-based photodetectors, relying on n-p type semiconductor homojunction technology, are the most established commercial solution for measurement of ultraviolet light. These devices have some significant shortcomings including high operation voltage, the requirement of longpass filters to block low energy photons and cooling systems to reduce noise and leakage current. This significantly hinders their integration in wearable technologies and alternative solutions are intensively sought.\textsuperscript{4-5} Wide bandgap nanostructured semiconductors such as TiO\textsubscript{2} and ZnO are inherently visible-blind and can detect low concentration of ultraviolet light by a different mechanism, namely photo-generated variations in the concentration of surface-states.\textsuperscript{2,6}

Amongst highly performing materials, zinc oxide is a promising transparent metal oxide with a room temperature bandgap of 3.37 eV that matches well the lower edge of the visible light spectrum.\textsuperscript{3,7} Nano- and micro-structured ZnO photodetectors have been produced by several methods such as RF magnetron sputtering,\textsuperscript{8} sol-gel,\textsuperscript{9-10} chemical vapor deposition\textsuperscript{11} and pulsed laser deposition\textsuperscript{12} demonstrating significant improvement over bulk equivalents. Recently, Ji et al.\textsuperscript{13} have demonstrated fabrication of flexible devices with up to $1.56 \times 10^3$ photo- ($I_{\text{photo}}$) to dark-current ($I_{\text{dark}}$) ratio at a bias of 3 V by epitaxial growth of ZnO films on poly-ethylene-terephthalate (PET). Drop-coating of PET substrates with ZnO quantum dots - graphene solutions resulted in up to nearly 10 times higher $I_{\text{photo}}/I_{\text{dark}}$ ratio indicating further optimization potential of morphology and composition. However, these results\textsuperscript{14} were obtained at very high light intensities of $300^{13}$ and 6 W.cm\textsuperscript{-2},\textsuperscript{14} respectively, that are outside the range of many applications. To date, amongst the highest response to moderate UV light intensities has been achieved by electrospun ZnO-SnO\textsubscript{2} nanofibers films featuring a
I_{\text{photo}}/I_{\text{dark}} of 4.6 \times 10^3 at 10 V under a UV light intensity of 0.45 mW cm^{-2}. Despite these significant improvements in the photo- to dark-current ratio, the magnitude of these devices’ photo-current reached a maximum of only 35 nA at a bias of 2.4 V\(^1\). This is quite low and makes them incompatible with integrated CMOS micro-circuitry utilized in state-of-the-art portable devices such as smartphones, watches and security devices. Up to 900 µA photo-currents (Table 5.1)\(^{15}\) have recently been achieved by more conductive but less light-sensitive structures. However, this results in high dark-currents of 1.5 µA and reduced signal to noise ratio\(^{15}\) that undermine many of the high photo-current advantages.

Here, we present a novel hierarchical morphology for UV-blind photodetectors that results in excellent selectivity, record high milliampere photo-currents to very low ultraviolet light intensities and nanoampere dark-currents. We demonstrate the rapid (≤ 100s) one-step synthesis and self-assembly of transparent ultra-porous films composed of electron-depleted crystalline ZnO nanoparticles on low-cost glass substrates. Optimization of the film structure is performed resulting into absorption of more than 80% of the incoming ultraviolet radiation and transmission of nearly 90% of the visible light. Characterization of the photodetector performance is pursued at very low light intensity (0.1 mW.cm\(^{-2}\)) resulting in the highest (3.4\times10^5) photo- to dark-current ratio so far reported. These findings demonstrate a highly performing structure and a flexible and scalable platform technology for the rapid low-cost fabrication and integration of ultraviolet photodetectors in CMOS-compatible portable devices.

3.2 Experimental

3.2.1 Nanoparticles Deposition

A flame spray pyrolysis (FSP) system was used for the synthesis and direct deposition of ZnO nanoparticles films onto the glass substrates featuring a set of interdigitated electrodes. A solution of Zinc Naphthenate (10% Zn, Sigma Aldrich) and Xylene (Sigma Aldrich) was
prepared with a total Zn-metal atom concentration of 0.3 mol.l\(^{-1}\). This solution was supplied at a rate of 5 ml.min\(^{-1}\) through a syringe pump, and dispersed into a fine spray with 7 L.min\(^{-1}\) oxygen at a constant pressure drop of 2 bars. The spray was ignited by supporting premixed methane/oxygen flames (CH\(_4\) = 1.2 L.min\(^{-1}\), O\(_2\) = 2 L.min\(^{-1}\)). A water-cooled substrate holder placed at 20 cm height above the burner (HAB) was utilized to keep the substrate temperature below 150 °C. The photodetector substrates were made of glass with interdigitated gold lines with 5µm width and spacing and a total electrode area of 7×5 mm (G-IDEAU5, DropSens, Oviedo, Spain). All substrates were cleaned with multiple ethanol/drying cycles before nanoparticles deposition. For measurement of the film resistance in pure nitrogen gas and with 1% oxygen, alumina substrate (0.8 mm thick) with interdigitated Pt lines with 200 µm width and 300 µm spacing were used. The substrates had a Pt resistance temperature detector (RTD) on one side and a Pt heater on the other side. The overall dimensions of the alumina substrate were 15 mm × 13 mm (Electronic Design Center, Case Western Reserve University, Cleveland, OH, USA).

### 3.2.2 Materials Characterization

The morphology and patterning characteristics of the deposited particles and films were investigated by a Hitachi H7100FA transmission electron microscope (TEM) at 100 kV and an analytical scanning electron microscopy (SEM), using Zeiss Ultraplus (FESEM) at 3 kV. The crystal phases, size (d\(\text{XRD}\)) and surface compositions were characterized by X-Ray diffraction using Bruker system (XRD, D\(_2\) Phaser, U.S.A) equipped with Cu Ka radiation of average wavelength 1.54059 Å. The Brunauer-Emmett-Teller specific surface area (BET, SSA) of the deposited nanoparticles was measured by N\(_2\) adsorption using a porosity analyzer (Micromeritics, TriStar II, U.S.A). The nanoparticles were degassed at 200 °C for 8 hours prior to analysis. The substrates were kept in a furnace (Brother High Temperature Furnace XD-1.2KN) at 300 °C for 12 h, at ambient pressure prior photo-detecting tests, to
stabilize the nanoparticle size and avoid resistive-sintering during the photo-detection measurements.

3.2.3 Photodetection Analysis

Absorbance spectra of the ultra-porous and dense ZnO films deposited were measured with a Perkin-Elmer (Lambda 1050 UV/Vis/NIR) Spectrophotometer and a 150 mm integrating sphere. All optical measurements were carried out at room temperature. The For I-V measurements, DC currents were measured using a Picoammeter / Voltage source (Model 6487, Keithley). The detection of UV light was performed using a Newport Xenon lamp source 66920 and the UV-vis absorption spectra were recorded in the wavelength range 250–500 nm using Princeton Instrument Acton SP2500 (0.500m Imaging Triple Grating Monochromator/Spectrograph).

3.3 Results and Discussion

3.3.1 Nanostructured Device Characterization

Figure 3.1a-c shows a schematic of the photodetector fabrication by liquid-fed spray flame synthesis and aerosol deposition. A hot ZnO nanoparticle aerosol was generated by atomization and combustion of a zinc naphtenate solution. The particle size was controlled by the Zn-atom precursor solution concentration that was set to 0.3 mol.l$^{-1}$. Transmission electron microscopy (TEM) analysis revealed (Figure 3.2a) a spherical shape and a visible (d$_{TEM}$) average particle diameter of ca. 19 nm. Some rod-like structures were also observed (Figure 3.3) which is in line with previous reports on the flame synthesis of larger ZnO nano-powders and it is attributed to preferential growth along the (100) plane.$^{16}$ It is worth to mention that the fraction of rod-like particles was computed by analysis and counting 300 ZnO nanoparticles. It was found that the rod-like fraction was less than 12% for the precursor concentration of 0.3 mol.L$^{-1}$. In addition, as the deposited particles (both spherical and lod-
like ones) are smaller than twice the Debye length and thus, fully electron depleted, the nanoparticle’s shape might have no significant effect on the device photoconductivity.

This nanoparticle aerosol was orthogonally impinged on the water-cooled glass substrates resulting in the rapid self-assembly of ultra-porous nanoparticle films with a very high film growth rate of 5.5 µm.min⁻¹. The substrate surface temperature (Figure 3.1c) was kept below 150 ºC by a water-cooled substrate holder, and thus the temperature was too low to induce sintering of the ZnO nanoparticles within the maximal deposition time of 100 s utilized here. In fact, the particle diameters determined by nitrogen adsorption (BET) and TEM analysis of the powders collected from the substrate and filter were (d_{BET}) 16 nm and 18 nm and (d_{TEM}) 19 nm and 21 nm, respectively, confirming that no sintering finds place on the substrate during deposition. As a result, the film morphology (Figure 3.2) was mainly determined by the particle deposition dynamics¹⁸ resulting in an 98% porous network of nanoparticles that is hold together by weak van der Waals forces¹⁹.

![Figure 3.1](image)

**Figure 3.1.** Schematics of a (a) photodetector substrate and (b,c) flame spray pyrolysis synthesis and aerosol self-assembly of ultra-porous films made of electron-depleted ZnO nanoparticles at 20 cm height above the burner (HAB).
To decrease grain boundary barriers to electron conduction and increase the film mechanical stability, these fragile nanoparticle networks were post-sintered at 300 °C for 12 h. This step had no measurable effects on the film morphology and crystallinity. It was, however, detectable by a small increase in crystal size (d_{XRD}) from 11.7 to 13.3 nm indicating inter-particle sintering and grain boundary necking. Figure 3.4 shows X-Ray Diffraction (XRD) and Fourier Transfer Infrared Spectroscopy (FTIR) patterns of particles collected from the filter and the photodetector substrates before and after sintering. All the XRD spectra correspond to the hexagonal wurtzite ZnO (JCPDS No. 36-1451) structure.\(^5\)\(^{,}\)\(^20\) Zinc oxide has a hexagonal-close-packed crystal structure composed of alternating planes of Zn and O atoms.\(^11\) Height et al.\(^16\) reported an increased XRD lattice aspect ratio between the (100) and (002) planes by increasing the concentration of dopants during flame-synthesis. This ultimately led to increasingly more accentuated rode-shaped nanostructures.

Figure 3.2. (a) Schematics, (b) cross-section and (c) top view SEM images of a uniform and homogenous flame-made film composed of (d) mostly spherical-particles with an average TEM size of 19 nm.

Here, the (100)/(002) planes aspect ratio was found to be close to unity (1.05+/−0.05) and consistent for the particles collected from filter and substrate. This is in line with the predominant spherical-shape observed by TEM analysis (Figure 3.3) indicating homogenous particle growth by condensation and Brownian coagulation. During and after fabrication, the
photosensitive semiconductor surface can be contaminated by impurities. These usually undermine the device performance. The defect and impurity content in the flame-made ZnO nanoparticles and in the self-assembled ZnO films were characterized by FTIR (Figure 3.4b). The broad peaks at 3455 and 1146 cm\(^{-1}\) are assigned to the O-H stretching vibration of hydroxyl groups and attributed to adsorption of atmospheric moisture.\(^{21}\) The residual hydroxyl peaks may be ascribed to the surface adsorption of ambient water. Two sharp peaks around 1600 and 1400 cm\(^{-1}\) are attributed to the asymmetrical and symmetrical stretching of zinc carboxylate, respectively.\(^{22}\) The spectral signature of these C-H impurities completely disappears upon sintering at 300 °C. As a result, the post-sintered ZnO films had a highly pure surface with no detectable organic or inorganic contaminants.

**Figure 3.3.** TEM images of flame-made ZnO particles collected from (a) the filter (HAB of 50 cm) and (b) the substrate (HAB of 20 cm).

**Figure 3.4.** The (a) XRD and (b) FTIR patterns of the ZnO particles collected on the filters and substrate before and after sintering reveal a Wurtzite crystal structure and high purity.
3.3.2 Optical Properties

Figure 3.5 shows the optical transmittance of the ZnO films deposited on blank glass substrates as a function of the deposition time. All films were highly transparent to visible light with a relatively sharp cut-off below 370 nm. This is quite close to the end of the visible spectrum 400 nm and well within the UV-A range (400 - 320 nm). The film average integral transmittance for visible light, computed by subtraction of the fraction lost through the glass substrates (Figure 3.5, circles), decreased from 99% to 90% with increasing deposition time from 15 to 100 s in line with the increase in film thickness. Optical images of the films placed over a printed paper (Figure 3.5, inset) reveal a highly transparent surface up to a deposition time of 100 s. This is particularly noteworthy as the resulting visible film thickness, measured by SEM, was ca. 10 µm (Figure 3.6c).

![Figure 3.5. Optical transmittance spectra of ultraporous ZnO films deposited on blank glass substrates as a function of the aerosol deposition time and of a blank glass substrate (circles). Inset: Optical images of ZnO films deposited for 15 and 100 s on glass substrates placed over a printed paper.](image)

This superior transparency was attributed to the unique film morphology and the non-scattering nature of the small ZnO primary particles. Figure 3.6 show exemplary films
obtained by deposition of the hot nanoparticle aerosols on blank glass substrates for 100 s. At high magnification (Figure 3.6b), it is revealed that these aerosol self-assembled films have a very homogenous surface characterized by micro-sized pores between thin bridges of partially sintered ZnO nanoparticles resulting in an ultra-high average film porosity of 98%. This results in a ZnO mass/(bulk) thickness of ca. 200 nm and it is in line with the optical thickness of 152 and 244 nm estimated by the Beer-Lambert law from the transmittance spectra (Figure 3.5) at $\lambda = 375$ nm with an extinction coefficient of $8 \times 10^4$ and $5 \times 10^4$ cm$^{-1}$, respectively.$^{23}$

![Figure 3.6. SEM images of an exemplary film deposited for 100 s on a glass substrate reveal a highly porous and uniform (a,b) top surface and (c,d) cross-section.](image)

Analysis of the film cross-sections (Figure 3.6c-d) revealed a homogeneous thickness over several hundred micrometres (Figure 3.6c) with no visible cracks and other defects.$^{24}$ This morphology is similar to that previously reported for as-prepared flame-made SnO$_2$ chemical sensors$^{19}$ further confirming that, independently of the composition, aerosol self-assembly leads to highly reproducible, statically equivalent film morphologies$^{18,25}$. However, in contrast to previous studies on aerosol-deposited SnO$_2$ and WO$_3$ films where high-temperature in-situ flame-annealing was utilized as a second step to mechanically stabilize the films and improve the electrical conductivity,$^{19,26-27}$ here the lower thermodynamic
stability of ZnO enabled low temperature sintering, and thus to preserve the initial film porosity.

3.3.3 Photodetection Properties

The photo- to dark-current ($I_{\text{photo}}/I_{\text{dark}}$) and the UV to visible light current ($I_{\text{photo}}/I_{\text{vis}}$) ratios are two key figures of merit for visible-blind photodetectors. Figure 3.7 shows the $I-V$ response of the thickest films, with a deposition time of 100 s, to the edge of the visible spectrum (390 - 410 nm) and to representative UV-A radiation (350 - 370 nm). All the samples had very low dark-currents ($\leq 5$ nA) up to a bias of 5 V corresponding to a total film resistance of nearly 1 Gohm at room temperature. This is attributed to both the strong impact of surface states on the ZnO conductivity and to the very high film porosity that results in a small number of neighbouring particles.

![Figure 3.7. I-V characteristics of the ZnO ultra-porous photodetectors as a function of the applied light and bias.](image)

For sufficiently small nanoparticles the high density of surface states results in significant electron depletion and thus very low dark current that represent an off-state of the device. In contrast under illumination (on-state), the $I-V$ response was linear indicating an ohmic behaviour and sufficient availability of charge carriers to maintain a very high photo-current.
At a wavelength of 370 nm and at a very low illumination intensity of 40 µW/cm², the photocurrent reached up to 521 µA. This is more than five order of magnitude higher than the dark-current (3.61 nA) and demonstrate a highly sensitive sensing mechanism. It is important to note that although the light intensity used here (40 µW.cm⁻²) was ca. 23-times lower than that commonly utilized to probe state-of-the-art metal-oxide photodetectors⁴, it still resulted in the highest $I_{\text{photo}}/I_{\text{dark}}$ ratios (1.4×10⁵) so far reported at low bias for wide bandgap semiconductor devices (Table 3.1).

### 3.3.4 Photodetection Mechanism

This strong response is attributed to the unique morphology and composition of these films. With respect to the former, the very high porosity of these nanoparticle networks facilitates the penetration of oxygen into the lowest nanoparticle layers (Figure 3.8a,c). This ensures the participation of the whole film in the sensing mechanism avoiding formation of non-electron-depleted and/or light-insensitive domains that could act as bottlenecks reducing the relative increase in the film electrical conductivity and thus tampering the photo- to dark-current ratio. This feature arises mainly from the high film porosity (98%). In stark contrast, deposition of the same nanoparticles by spin-coating led to non-transparent, considerably less porous structures (40 - 60%).

Figure 3.9 shows the transmittance and absorbance spectra of an aerosol-deposited ultra-porous film (95% porosity) and a spin-coated dense one (50% porosity) on glass substrate composed of the same flame-made ZnO nanoparticles and having the same optical density (ca. 0.7) in the near UV. For wavelengths below ZnO bandgap ($\lambda = 360$ nm), the ultra-porous film absorbs ca. 84% of the incoming light while the spin-coated film absorbs 74%. Considering that the films have similar UV transmittance, the lower UV absorption of the spin-coated films is likely attributed to higher back-scattering.
Figure 3.8. Schematic model of the photo-response mechanisms of ZnO nanoparticle films based on the adsorption and desorption of molecular oxygen in (a,c) ultra-porous and (b,d) dense films. The high porosity (a,c) of these electron-depleted nanoparticle networks facilitates the penetration of oxygen and light into the lowest particle layers close to the electrodes. In contrast, the dense films (b,d) may result in the formation of non-electron-depleted and light insensitive domains.

Figure 3.9. (a) Transmittance and (b) absorption spectra of an aerosol-deposited ultra-porous film (red circles) and a spin-coated one (blue circles) both composed of the same flame-made ZnO nanoparticles and having the same light transmittance at the edge of the ZnO bandgap (ca. 370 nm).

The other critical feature of these flame-made photodetectors is the ultra-fine ZnO nanoparticle size. Similarly to chemoresistive gas sensors, the ultraviolet light sensing mechanism of wide bandgap semiconductor depends from the ratio between their Debye
length and the primary particle size\textsuperscript{26} (Figure 3.10). Due to the high porosity and hierarchical micro-pore size of these films, oxygen molecules can adsorb down to the deepest film layers (Figure 3.8a). Adsorption of $O_2$ on the ZnO nanoparticle surface results in the trapping of electron from the semiconductor conduction band.\textsuperscript{26} This forms an electron-depleted layer within the semiconductor Debye length from the surface. During illumination, the photo-generated holes can travel to the surface along potential gradient and desorb oxygen molecules from the surface (Figure 3.8c), resulting in an increase in the free carrier concentration within this depletion layer.\textsuperscript{20} The transduction of this photo-response on the semiconductor conductivity, and thus photo-current, depends mainly from the ratio between the Debye length ($\delta$) and the primary particle size ($d_p$). If $d_p$ is larger than twice $\delta$ than a light-insensitive conduction channel is formed. This leads to relatively high dark current and exposure to UV light results only in the modulation of the conduction channel width.

\begin{figure}[h]
\centering
\includegraphics[width=0.8\textwidth]{figure3.10}
\caption{As a function of the ratio between the particle diameter ($d_p$) and the Debye length ($\delta$), three photo-detection mechanisms (a-c) are expected\textsuperscript{6}. Particle size larger than twice the Debye length of ZnO leads to grain boundary or surface controlled responses with limited photo- to dark-current ratios, whereas particle size smaller than twice the Debye length leads to fully depleted nanostructures with an on/off switching behaviour.}
\end{figure}
Decreasing this channel and thus the particle size increases the contribution of the light-sensitive domains to the total film conductivity resulting in higher photo-response. Usually, a main distinction is made for \(d_p \gg 2\delta\) where the sensing mechanism is controlled by electron-transport at the grain boundary and \(d_p > 2\delta\) where a significant portion of the bulk participate to light sensing (Figure 3.10).

In contrast, if \(d_p \leq 2\delta\) than the whole particle is electron-depleted. This leads to highly resistive films with very low dark-currents. For this ultra-fine structures, exposure to ultraviolet light create a conduction channel resulting in a drastic increase in electrical conductivity and, potentially, very high photo-currents. For our ZnO films the Debye length\(^{24}\) can be computed as following\(^{28}\):

\[
\delta = \frac{\varepsilon_s K_b T}{e^2 n_c}
\]  

(3.1)

where \(\varepsilon_s\) is the static dielectric constant (13.5×8.5×10\(^{-12}\) F/m in ZnO), \(K_b\) is the Boltzmann’s constant (1.38×10\(^{-23}\)J/K), \(T\) is an absolute temperature (K), \(e\) is the electrical charge of the carrier (1.6×10\(^{-19}\) C), and \(n_c\) is the carrier concentration (ca. 5×10\(^{16}\) cm\(^{-3}\))\(^{29}\). At room temperature (\(T = 298\) K) for ZnO, this results in a Debye length of ca. 19 nm. Considering that the primary particle size (d\(_{\text{BET}}\)) of the flame-made ZnO is 16 nm and the crystal size is 13 nm, here, the low dark-current and the very high photo- to dark-current ratio of these films are partially attributed to the fully electron-depleted state of the nanoparticle network (Figure 4e, \(d_p \leq 2\delta\)).

This was confirmed by measurement of the resistance of the thick ZnO films aerosol-deposited for 100 s on gold interdigitated electrodes with back heaters (Figure 3.11). In pure nitrogen gas, the resistance decreased from 0.298 to 0.126 Mohm by increasing the sensor temperature from 150 to 240 °C. This is line with the behaviour expected by for n-type semiconductors such as ZnO. Increasing the O\(_2\) concentration from zero to 1% increased the...
film resistance by nearly 300 times (from 0.298 to 87 Mohm at 150 °C). Similar results were obtained up to a film temperature of 240 °C. This indicates that the conductivity of these ultra-porous electron-depleted ZnO films is mainly controlled by adsorption and desorption O₂ molecules. The high porosity of these films is beneficial to ensure penetration of oxygen and thus formation of electron-depleted ZnO particles in the whole film structure and in particular in the lowest layers adjacent to the electrodes (Figure 3.8a,c).

![Figure 3.11. Film resistance in N₂ as a function of the temperature O₂ content.](image)

To assess the impact of the film morphology on the resulting photodetector performance, the photo-response of denser (spin-coated) films having an average porosity of ca. 50% and the same UV optical density (0.7) of the ultra-porous films (Figure 3.12) was further investigated. All dense films had a very high dark-current ranging from micro- to milliampere and very low photo- to dark-current ratio (ca. 1). The high dark-current was attributed to the denser morphology (ca. 50% porosity) of the spin-coated films that results in a significantly larger number of neighbouring particles and drastically higher film electrical conductivity than the ultra-porous films. Also, as oxygen penetration may be limited in the dense films, some of the ZnO particles may not be fully electron-depleted leading to higher conductivity.
The low photo-currents indicate that the amount of photo-excited extra carriers in the dense films is significantly less than in the ultra-porous ones.

As schematically described in Figure 3.8, this is likely attributed to two main structural differences. First, the lower porosity decreases the penetration of oxygen and may lead to formation of gas-tight ZnO domains that are not fully electron-depleted and thus less sensitive to light (Figure 3.8b). Second, the higher UV light back-scattering of the dense films (Figure 3.9) suggest that a larger fraction of the incoming light may be trapped and absorbed in the top layers relatively far away from the electrodes (Figure 3.8d). Both these effect may lead to the formation of light-insensitive domains reducing the amounts of photo-excited extra carriers.

![Graphs showing photo- and dark-currents](image)

*Figure 3.12. Photo- and dark-currents of (a) a spin-coated and (b) ultra-porous films composed of the same flame-made ZnO nanoparticles and having both an optical density of ca. 0.7 at λ of 370 nm.*

It should be noted that highly performing dense films of electron-depleted ZnO nanoparticles have been previously obtained by spin-coating.\(^2\) However, these thin films had low UV optical density (ca. 0.3) and a very low electrode aspect ratio (ca. 0.75) resulting in lower photo-currents (ca. 1.8 μA at a bias of 5 V and 0.84 mW.cm\(^{-2}\) UV light intensity) than the one achieved here by the ultra-porous films (1.2 mA at 5 V and 0.1 mW.cm\(^{-2}\)). These results show that electron-depleted particles are critical but not sufficient to obtain milliampere high photo- and nanoampere low dark-currents at low UV light intensities. The
ultra-porous film morphology, developed here, is a key structural property required to individually optimize photo-excitation and electrical conductivity.

Figure 3.13 shows the spectral responsivity of the photodetectors as a function of the illumination wavelength and applied bias. It was observed that decreasing the wavelength below 400 nm sharply increased the responsivity that reached its peak value at about 370 nm. The responsivity increased by a factor of 7 (from 1.7 to 12.1 µA) by decreasing the wavelength from 390 to 370 nm. The sharp cut-off at wavelength of 370 nm is in good-agreement with the ZnO band gap of 3.37 eV (λ = 368 nm), confirming that these flame-made ZnO photodetectors are inherently visible-blind.

![Graph showing responsivity and selectivity](image)

**Figure 3.13.** (a) Responsivity of the ZnO ultra-porous photodetectors as a function of the light wavelength and applied bias. (b) Photodetector responsivity and (inset) I$_{370}$/I$_{400}$ UV-visible selectivity as function of applied bias at a wavelength of 350, 370 nm and 400 nm light illumination.

The photodetector responsivity was further investigated as a function of applied bias at different wavelengths in the UV-A and visible spectrum. A linear relationship (Figure 3.13b) was obtained with increasing bias from 0 to 5 V indicating no carrier mobility saturation or sweep effect up to the maximum applied bias. The ultraviolet selectivity, defined as a ratio of device response at a wavelength of 370 nm and 400 nm (Figure 3.13b, inset) reached 60 at a bias of 5 V. This is more than sufficient to enable very selective detection of low intensity of UV light without the need for high wavelength filters and further amplification.
Figure 3.14a shows the photoresponse of an ultra-porous ZnO nanoparticle film to the UV illumination with different light density at a wavelength of 370 nm. The photo-current increased linearly by a factor of 4.5 (from 260 µA to 1.2 mA) with increasing light intensity from 20 to 100 µW.cm⁻² resulting in a maximal I_{photo}/I_{dark} ratio of 3.4×10⁵. This shows that in these ultra-porous electro-depleted nanoparticle films, the charge carrier photo-generation efficiency is proportional to the applied photon flux. The photo- to dark-current ratio obtained here at 100 µW.cm⁻² (3.4×10⁵) is very high even in comparison to other highly performing photodetectors made of electron-depleted ZnO nanoparticles² that reached similar ratios (ca. 3×10⁵) at higher light intensities (830 µW.cm⁻²). Furthermore, to the best of our knowledge, achievement of milliampere photo-currents at low ultraviolet light intensity of 100 µWcm⁻² while maintaining nanoampere dark-currents has not been previously reported (Table 5.1). This is a key improvement over state-of-the-art structures as it enables the direct integration of UV-photodetectors in CMOS-compatible micro-circuitry currently implemented in many wearable devices.

Figure 3.14. (a) Photo-current as a function of applied bias and inset, light intensity demonstrating milliampere currents at low light intensities of 100 µW.cm⁻². (b) Time-dependent photodetector response to alternative exposure to increasing light intensity at a bias of 5 V and a wavelength of 370 nm.
Figure 3.14b shows time-resolved photo-current measurements to alternating exposure to increasing UV light intensities (370 nm) and darkness. Regardless of the light intensities, the photo-current initially rapidly raised and thereafter gradually saturated under illumination, and then sharply dropped as the illumination was switched off. The initial response time of the ultra-porous ZnO films was less than 0.3 s in line with previous reports on electron-depleted ZnO nanoparticles. Rise and decay times were computed from the time required for the current to increase to 90% of the steady-state photo-current value and to decrease again by 90%, respectively. The rise and decay times during the on/off cycles were 250 and 150 s, respectively, and thus in line with that expected for pure ZnO nanostructured photodetectors (Table 5.1). The relatively long times required to reach a steady-state photo- and dark-current are attributed to the chemi/physisorption and photo-desorption of oxygen molecules from the ZnO nanoparticle surface (Figure 3.8). The rise and decay time could be further improved by replacing the ZnO nanoparticles with recently reported materials such as ZnS that offer faster photo-current dynamics.

3.4 Conclusions

In conclusion, we have developed a novel structural design for CMOS-compatible visible-blind photodetectors featuring ultra-high milliampere photo-currents, very low dark currents, very low UV intensity detection limit and low operation voltages. This excellent performance was attributed to the high film porosity and electron-depleted composition of these nanoparticle networks. Decreasing the primary particle size below twice the ZnO Debye length and providing ultra-porous film morphology enhanced adsorption/desorption of oxygen molecules from the nanoparticle surface and facilitated the penetration of UV light into the lowest film layers resulting in an on/off switch behaviour to UV light exposure. Furthermore, we have demonstrated a flexible and low-cost platform technology for the rapid fabrication and integration of ultra-porous electron-depleted nanoparticle photodetectors in
micro-machinable circuitry. This concept can be applied to other highly performing semiconductors such as wide bandgap SnO₂ for selective UV-B detection and fast-responding ZnS⁴³¹ for fibre optics.
Table 5.1. Figures of merit of state-of-the-art wide bandgap ZnO photodetectors.

<table>
<thead>
<tr>
<th>Photodetector</th>
<th>( d_p )</th>
<th>Bias</th>
<th>Dark-Current</th>
<th>Photo-current</th>
<th>( I_{\text{photo}}/I_{\text{dark}} ) Ratio</th>
<th>Intensity</th>
<th>Rise Time</th>
<th>Decay Time</th>
<th>Ref.</th>
</tr>
</thead>
<tbody>
<tr>
<td>ZnO ultra-porous nanoparticle networks</td>
<td>20 nm</td>
<td>5 V</td>
<td>3.61 nA</td>
<td>1.2 mA</td>
<td>3.4( \times 10^3 )</td>
<td>100 ( \mu \text{W/cm}^2 )</td>
<td>( \sim 250 ) s</td>
<td>( \sim 150 ) s</td>
<td>This Work</td>
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<tr>
<td></td>
<td></td>
<td></td>
<td></td>
<td>512 ( \mu \text{A} )</td>
<td>1.4( \times 10^3 )</td>
<td>40 ( \mu \text{W/cm}^2 )</td>
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<tr>
<td></td>
<td></td>
<td></td>
<td></td>
<td>260 ( \mu \text{A} )</td>
<td>7.2( \times 10^4 )</td>
<td>20 ( \mu \text{W/cm}^2 )</td>
<td></td>
<td></td>
<td></td>
</tr>
<tr>
<td>ZnO nanotetrapods network</td>
<td>--</td>
<td>2.4 V</td>
<td>--</td>
<td>~ 35 nA</td>
<td>4.5 ( \times 10^3 )</td>
<td>( \sim 20 ) ( \text{mW/cm}^2 )</td>
<td>68 ms</td>
<td>32 ms</td>
<td>1</td>
</tr>
<tr>
<td>ZnO nanoneedles</td>
<td>50-200 nm</td>
<td>0.3 V</td>
<td>--</td>
<td>~ 250 nA</td>
<td>312</td>
<td>( \sim 15 ) ( \text{mW/cm}^2 )</td>
<td>22 s</td>
<td>7-12 s</td>
<td>1</td>
</tr>
<tr>
<td>Colloidal ZnO nanoparticles</td>
<td>10 nm</td>
<td>5 V</td>
<td>7 pA</td>
<td>1.8 ( \mu \text{A} )</td>
<td>( = 2.6 \times 10^3 )</td>
<td>830 ( \mu \text{W/cm}^2 )</td>
<td>--</td>
<td>--</td>
<td>2</td>
</tr>
<tr>
<td>ZnS/ZnO nanobelts</td>
<td>~ 100 nm</td>
<td>5 V</td>
<td>0.67 ( \mu \text{A} )</td>
<td>4.64 ( \mu \text{A} )</td>
<td>6.92</td>
<td>0.91 ( \text{mW/cm}^2 )</td>
<td>0.3 s</td>
<td>1.7 s</td>
<td>4</td>
</tr>
<tr>
<td>ZnO-SnO(_2)</td>
<td>100-150 nm</td>
<td>17 V</td>
<td>7.9 nA</td>
<td>4.6 ( \times 10^3 )</td>
<td>0.45 ( \text{mW/cm}^2 )</td>
<td>32.2 s</td>
<td>7.8 s</td>
<td></td>
<td>3</td>
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<tr>
<td>ZnO nanowire</td>
<td>30 nm</td>
<td>5 V</td>
<td>15 pA</td>
<td>270 pA</td>
<td>18</td>
<td>--</td>
<td>43.7 s</td>
<td>--</td>
<td>9</td>
</tr>
<tr>
<td>ZnO epitaxial films</td>
<td>--</td>
<td>3 V</td>
<td>--</td>
<td>--</td>
<td>1.56 ( \times 10^3 )</td>
<td>300 ( \text{W/cm}^2 )</td>
<td>--</td>
<td>--</td>
<td>13</td>
</tr>
<tr>
<td>ZnO quantum dot/graphene</td>
<td>5 nm</td>
<td>3 V</td>
<td>91.6 pA</td>
<td>0.83 ( \mu \text{A} )</td>
<td>1.1 ( \times 10^4 )</td>
<td>6 ( \text{W/cm}^2 )</td>
<td>2 s</td>
<td>1 s</td>
<td>14</td>
</tr>
<tr>
<td>ZnO microtubes</td>
<td>~ 100 nm</td>
<td>5 V</td>
<td>1.5 ( \mu \text{A} )</td>
<td>900 ( \mu \text{A} )</td>
<td>600</td>
<td>21.7 ( \text{mW/cm}^2 )</td>
<td>5.9 s</td>
<td>638 s</td>
<td>15</td>
</tr>
<tr>
<td>ZnS-coated ZnO arrays</td>
<td>100 nm</td>
<td>3 V</td>
<td>--</td>
<td>--</td>
<td>1.25</td>
<td>150 ( \text{W/cm}^2 )</td>
<td>120 s</td>
<td>180 s</td>
<td>16</td>
</tr>
<tr>
<td>ZnO nanowire</td>
<td>60-70 nm</td>
<td>5 V</td>
<td>10 nA</td>
<td>100 ( \mu \text{A} )</td>
<td>( = 10^4 )</td>
<td>40 ( \text{mW/cm}^2 )</td>
<td>--</td>
<td>--</td>
<td>32</td>
</tr>
<tr>
<td>ZnO nanorods</td>
<td>150-300 nm</td>
<td>5 V</td>
<td>--</td>
<td>13 ( \mu \text{A} )</td>
<td>85</td>
<td>--</td>
<td>( &gt; 500 ) s</td>
<td>500 s</td>
<td>33</td>
</tr>
<tr>
<td>ZnO nanowire</td>
<td>150 nm</td>
<td>1 V</td>
<td>0.13 pA</td>
<td>--</td>
<td>1000</td>
<td>1.3 ( \text{mW/cm}^2 )</td>
<td>40 s</td>
<td>300 s</td>
<td>34</td>
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<tr>
<td>ZnO nanowire array</td>
<td>40 nm</td>
<td>5 V</td>
<td>~ 71 ( \mu \text{A} )</td>
<td>~ 100 ( \mu \text{A} )</td>
<td>1.4</td>
<td>--</td>
<td>0.4 ms</td>
<td>--</td>
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3.5 References


Chapter Four

Structural Engineering of Nano-Grain Boundaries for Low-Voltage UV-Photodetectors with Gigantic Photo- to Dark-Current Ratios
Abstract

Ultraporous networks of ZnO nanoparticles (UNN) have recently been proposed as a highly performing morphology for portable ultraviolet light photodetectors. Here, we show that structural engineering of the nanoparticle grain boundaries can drastically enhance the performance of UNN photodetectors leading to gigantic photo to dark current ratios with operation voltages below 1 V. Ultraporous nanoparticle layers were fabricated by scalable low-temperature deposition of flame-made ZnO aerosols resulting in highly transparent layers with more than 95% visible light transmittance and 80% UV-light absorption. Optimal thermally-induced necking of the ZnO nanoparticles increased the photo- to dark-current ratio, at a low light density of 86 µW.cm\(^{-2}\), from \(1.4 \times 10^4\) to \(9.3 \times 10^6\), the highest so far reported. This is attributed to the optimal interplay of surface depletion and carrier conduction resulting in the formation of an open-neck grain boundary morphology. These findings provide a robust set of guiding principle for the design and fabrication of nanoparticle-based optoelectronic devices.
4.1 Introduction

Portable UV photodetectors have application in numerous optoelectronic devices and components such as piezoelectric transducers, space communications, flame and missile launch detectors, and chemical sensors.\textsuperscript{1-4} Often, highly sensitive detectors with low UV-light detection limit and high signal-to-noise ratio are required. Most commercial devices are based on Si-based homojunctions and photomultipliers.\textsuperscript{5-7} Notwithstanding their numerous advantages, Si-based UV photodetectors exhibits some intrinsic limitations, such as detection of visible and infrared light photons, photo-degradation under sustained UV illumination, and requirement for cooling.\textsuperscript{8} Wide bandgap semiconductors such as GaN,\textsuperscript{9-11} ZnO\textsuperscript{12-13} and TiO\textsubscript{2}\textsuperscript{14-15} have been proposed as alternative visible-blind materials for high performance UV-photodetectors.

Recently, nanoscale engineering of ZnO-based devices, an n-type wide bandgap semiconductor, has led to significant performance enhancement and excellent photodetection properties.\textsuperscript{16-17} The ZnO absorption edge (3.37 eV) is conveniently located at the end of the visible spectrum and its direct bandgap structure provides a sharp photo-response contrast between the visible and UV spectra.\textsuperscript{12} Furthermore, ZnO is earth-abundant, and has high electron mobility\textsuperscript{18-22} both of which are favourable for fabrication of low-cost portable photodetectors. Nanostructured ZnO-based photodetectors with enhanced UV photoresponse have been fabricated by electrospinning,\textsuperscript{23} CVD\textsuperscript{24} and spin coating.\textsuperscript{17} Very recently, flame-made ultraporous networks of ZnO UNN have been reported\textsuperscript{12} as a highly performing super-structural design for visible-blind UV-photodetectors. These UNN devices demonstrated high milliampere photocurrents to light densities of 100 $\mu$W.cm$^{-2}$, low nanoampere dark-currents and operation bias of few volts.\textsuperscript{12}

Optimization of the nanoscale structure of these UNN has the potential to enhance their portability and performance while providing further insights on their photodetection
mechanism. In addition to the material composition, the key structural properties impacting the performance of wide bandgap photodetectors are the film porosity,\textsuperscript{12} particle morphology,\textsuperscript{25} thickness\textsuperscript{26} and grain necking.\textsuperscript{27} A major design parameter that has been so far poorly addressed is the type of inter-particle grain boundaries. Notably, as demonstrated for semiconductor gas sensors,\textsuperscript{28} the transduction of surface states-based chemo- and photo-electric response is significantly enhanced at the inter-grain boundary and its optimization can drastically improve device performance.\textsuperscript{29}

Here, we demonstrate that by structural engineering of the grain boundaries of wide bandgap semiconductor nanoparticles, superior UV-photodetectors featuring ultra-low dark-currents, very low operation voltages and high photocurrents in response to low light densities can be fabricated. Transparent ultraporous nanoparticle networks with transmission of ca. 95% of visible light (500 nm) and absorption of ca. 80% of UV light (340 nm) are rapidly synthesized by deposition of flame-made ZnO aerosols. The photoelectrical response measurement reveals that thermally-induced necking of the grain boundaries is essential for efficient photodetection. An optimal grain-boundary morphology leads to picoamperes dark-currents and a strong photoresponse resulting in the highest photo- to dark-current ratio (9.3 × 10\textsuperscript{6}) so far reported at low light densities of 86 µW.cm\textsuperscript{-2}. These findings provide a robust set of guiding principles for the engineering of portable nanoparticle-based UV-photodetectors.

\section*{4.2 Experimental}

\subsection*{4.2.1 Nanoparticles Deposition}

A flame spray pyrolysis (FSP) system was used for the synthesis and direct deposition of ZnO nanoparticle aerosols onto the glass substrates featuring a set of interdigitated electrodes. The photodetector nanoparticles were prepared as follows: Zinc Naphthenate (10% Zn, Sigma Aldrich) was diluted in Xylene (Sigma Aldrich) with a total metal atom
concentration of 0.3 mol.L⁻¹ for Zn. The prepared solution was supplied at a rate of 5 mL.min⁻¹ through a syringe pump, and dispersed into a fine spray with 7 L.min⁻¹ oxygen at a constant pressure drop of 2 bars. The spray was ignited by supporting premixed methane/oxygen flames (CH₄ = 1.2 L.min⁻¹, O₂ = 2 L.min⁻¹). A water-cooled substrate holder placed at 20 cm height above the burner (HAB) was utilized to keep the substrate temperature below 150 °C. The photodetector substrates were made of glass with interdigitated platinum lines with 5µm width and spacing and a total electrode area of 7×5 mm (G-IDEAU5, DropSens, Oviedo, Spain). More details about the device design and geometry were reported in previous work.¹² All substrates were cleaned with multiple ethanol/drying cycles and pre-annealed (Brother High Temperature Furnace XD-1.2KN) at 300 °C for 12 h at ambient pressure prior photo-detecting tests before nanoparticles deposition.

### 4.2.2 Materials Characterization

The morphology and patterning characteristics of the deposited particles and films were investigated by a Hitachi H7100FA transmission electron microscope (TEM) at 100 kV and an analytical scanning electron microscopy (SEM), using Zeiss Ultraplus (FESEM) at 3 kV. The crystal phases, size (dₓRD) and surface compositions were characterized by X-Ray diffraction using Bruker system (XRD, D₂ Phaser, U.S.A) equipped with Cu Ka radiation of average wavelength 1.54059 Å. The surface compositions were analysed by Fourier transform infrared spectroscopy (FTIR-ATR, Bruker-Alpha, U.S.A). The ZnO specific surface area (SSA) was measured by N₂ adsorption/desorption at -196.15 °C (Micromeritics, TriStar II, U.S.A), after degassing at 160 °C for 12 h. The prepared films were annealed in a furnace (Brother High Temperature Furnace XD-1.2KN) at different annealing temperature for 12 h at ambient pressure prior photo-detecting tests, to stabilize the nanoparticle size, avoid resistive-sintering during the photo-detection measurements and finding the optimal annealing temperature.
4.2.3 Photodetection Analysis

The specific detectivity, \( D \), and external quantum efficiency, \( EQE\% \), of the photodetectors annealed at different temperature were calculated as follows:

\[
D = \frac{R}{\left( 2e \cdot \frac{I_{dark}}{A} \right)^{1/2}} \tag{4.1}
\]

\[
EQE\% = \frac{R \times 1240}{\lambda\,(nm)} \times 100 \tag{4.2}
\]

where \( R \) is the responsivity, \( e \) is the electron charge, \( I_{dark} \) is the device dark current and \( \lambda \) is the wavelength. The optical properties of the ultraporous ZnO films were measured with a Perkin-Elmer (Lambda 1050 UV/Vis/NIR) Spectrophotometer and a 150 mm integrating sphere. All optical measurements were carried out at room temperature. For I-V measurements, DC currents were measured using a Picoammeter / Voltage source (Model 6487, Keithley). The detection of UV light was performed using a Newport Xenon lamp source 66920.

4.3 Results and Discussion

4.3.1 Nanostructured Device Characterization

Figure 4.1a-c shows a schematic of the ultraporous nanoparticle networks obtained by thermophoretic-driven deposition of ZnO aerosols on photodetector substrates (Figure 4.1a). ZnO nanoparticle aerosols were generated by atomization and combustion of a zinc naphtenate solution. The Zn-atom precursor solution concentration was set to 0.3 mol.l\(^{-1}\) in order to control the ZnO nanoparticle size. More details about the fabrication method were reported in previous work.\(^{12}\) In line with our recent report,\(^{12}\) gas-phase deposition of flame-made ZnO nanoparticles results in the self-assembly of homogenous films of nanoparticles with ca. 98% porosity, high purity, visible light transparency and ca. 80% UV light absorption.
The ZnO UNN surface was homogenous over hundreds of micrometres and contains both meso- and macropores (Figure 4.2a,b). Cross-section SEM images of the nanostructured film shows (Figure 4.2a) a UNN film thickness of approximately ca. 8.5 µm and a typical fractal-like composition (Figure 4.2b). The UNN growth rate was ca. 5 µm.min\(^{-1}\) and thus in good agreement with previous reports\(^{12,31}\). In this work, upon deposition, thermally-induced annealing of the nanoparticle grain boundaries was performed from 250 °C to 400 °C (Figure 4.1b). Characterization of the photodetector performance was pursued as a function of the illumination light intensities and annealing temperature, providing new insights of their photodetection mechanism and structural optimization (Figure 4.1c).

Figure 4.1. Schematic of (a) ultraporous ZnO nanoparticle network (UNN) self-assembly on glass substrates with interdigitated Pt electrodes. (b) Grain boundary necking was induced by annealing from 250 °C to 400 °C (c) The UV photodetection performance was characterized for each samples under direct exposure.

Figure 4.2. SEM cross-section images of a UNN ZnO device reveals (a) a fractal-like ultraporous morphology with (b) micro-scale pore sizes.

4.3.2 Optical Properties

Figure 4.3a shows the optical transmittance of the ZnO UNNs deposited on blank glass substrates as a function of their isothermal annealing temperature. The film average integral...
Transmittance for both UV and visible light is computed by subtraction of the fraction lost through the glass substrates as follows:

$$T_{Film} = \frac{I_{Film\ Out}}{T_{Glass}} \times 100$$  \hspace{1cm} (4.3)

where $T_{Film}$ is the film average transmittance, $I_{Film\ Out}$ is the transmittance through the glass and the film, and $T_{Glass}$ is the glass transmittance.

![Figure 4.3](image.png)

**Figure 4.3.** Optical (a) transmittance and (b) reflectance spectra of the ultraporous ZnO nanoparticle networks deposited on blank glass substrates (grey circles) as a function of the annealing temperature from 250 °C to 400 °C.

An annealing time of 12 h was selected to achieve a thermodynamically-stable grain size. After subtraction of the optical loses through the glass at 500 nm (10%), the films average transmittance was > 95% for the sintering temperatures. In the UV, the films had a sharp absorption cut-off above 370 nm. This is conveniently close to the end of the visible spectrum (400 nm) and well within the UV-A range (400 - 320 nm). Upon removing the fraction lost through the glass, the UV light transmittance through the film at a wavelength of 340 nm was computed to decrease from 22% of the as-prepared to 18% of the annealed samples at 250 °C. Further increasing the annealing temperature to 400 °C (Figure 4.3a, inset) decreased the UV light transmittance through the film to 14% ($\lambda = 340$ nm). This is likely due to the decrease of interstitial oxygen vacancies and a slight increase in surface roughness that may increase the optical density of these layers.
Figure 4.4. The scattering cross-section of particles with diameter of 16 nm (RT and 250°C), 17 nm (300°C), 27 nm (350°C) and 35 nm (400°C) at different illumination wavelengths.

Figure 4.5. SEM images of an exemplary film deposited of ZnO after 100 s deposition time on glass substrate at HAB of 20 cm (a,d) before and after annealing at (b,e) 300 °C and (c,f) 400 °C for 12 h. Higher magnification SEM of the UNN morphology reveals (e) some thin bridges of partially annealed ZnO nanoparticles and (f) large pores with diameter of several µm. Annealing preserve these ultraporous micro-scale morphology.
The reflectance spectra of these ZnO ultraporous films before and after annealing are shown in Figure 4.3b. The reflectance of the UNN increased with annealing temperature from 13.4% at 400 nm of the as-prepared to 18% of the annealed ones at 400 °C. This is consistent with the expected particle growth during annealing and it is in line with previous reports. The scattering cross-section calculations for ZnO spherical nanoparticles with different particle size of 16, 17, 27 and 35 nm are shown in Figure 4.4 in the Supporting Information. Notably, at this scale, a small increase in particle size results in a drastic increase in light scattering, as predicted by the Rayleigh-scattering regime.

![Figure 4.6](image)

**Figure 4.6.** (a) Representative transmission electron microscopy images of exemplary as-prepared ZnO nanoparticles deposited on glass substrates. (inset) The interplanar spacing of 2.6 Å corresponds well to the distance between two (002) planes of the hexagonal ZnO structure.

Figure 4.5 shows the evolution of the ZnO UNN morphology as a function of the annealing temperature. The films are highly porous and consist of large aggregates of ZnO nanoparticles, forming a three-dimensional, ultraporous network in line with recent modelling of their self-assembling. Their surface was characterized by a hierarchical nano-micro structure (Figure 4.2a,b) with thin bridges of ZnO particles enclosing large micro-pores. Usually, for low-temperature deposition as here (< 150 °C), the morphology of UNNs (Figure 4.5a,d) is mainly determined by the nanoparticle deposition dynamics as the substrate temperature is too low to induce any significant annealing of the ZnO nanoparticles.
Here, SEM analysis of the UNN surface morphology revealed that annealing up to 400 °C has no detectable impact on the microscale film morphology (Figure 4.5b-f). This is attributed to the limited sintering of the ZnO particles that at this moderate temperature does not result in micro-scale but only nano-scale restructuring.

![Figure 4.7](image)

**Figure 4.7.** *Sauter diameter (d_{BET}), crystal size (d_{XRD}) and ZnO nanoparticles specific surface area (SSA) of the UNN as a function of the annealing temperature.*

Figure 4.6 shows a TEM image of ZnO nanoparticles collected from the photodetector substrates. Most of the as-deposited particles were spherical nanoparticle with average diameter (d_{TEM}) of ca. 16 nm. This is in line with their sauter diameter of 16 nm (d_{BET}), measured by nitrogen absorption (Figure 4.7, red circles). Most of the as-deposited particles (Figure 4.6, inset) have no sintering necks and are held together in the UNN by van der Waals forces. Some nanorod-like structures were also observed (Figure 4.6, inset) which form due to ZnO preferential growth along its (100) plane. At higher magnifications, it is possible to identify clear lattice fringes with an interplanar spacing of ca. 2.6 Å (Figure 4.6, inset), which corresponds well to the distance between two (002) planes of the hexagonal wurtzite ZnO phase.
Figure 4.8a-b show the XRD and FTIR spectra of the ZnO nanoparticles before and after annealing. All the XRD patterns corresponded to the wurtzite ZnO phase (JCPDS No. 36-1451)\textsuperscript{12,23} with no secondary and amorphous components observed. Upon annealing up to 400 °C the crystal phase was preserved. However, the narrowing of the peaks width indicates a growing crystallite size from 11.6 nm of the as-deposited to 17 nm of the 400 °C annealed. Similarly, the sauter diameter of the ZnO nanoparticles increased from 16 to 35 nm.

The impurity content of the flame-made ZnO nanoparticles and UNNs were investigated by FTIR (Figure 4.8b). The FTIR spectra of the as-prepared samples indicate the weak presence of adsorbed organics and moistures. In particular, the broad peaks at 3455 and 1146 cm\textsuperscript{-1} are assigned to the O-H stretching vibration of hydroxyl groups attributed to the adsorption of atmospheric moisture.\textsuperscript{40} The two sharp peaks around 1600 and 1400 cm\textsuperscript{-1} are attributed to the asymmetrical and symmetrical stretching of zinc carboxylate, respectively, and may form due to adsorption of atmospheric CO\textsubscript{2}.\textsuperscript{41} Upon annealing, the UNNs maintained a similar FTIR spectra indicating that moisture and CO\textsubscript{2} are rapidly re-adsorbed on the ZnO nanoparticle surface.

Figure 4.8. (a) XRD patterns and (b) FTIR spectra of the UNN as a function of the annealing temperature.
4.3.3 Photodetection Properties

The spectral photo-detector responsivity of the UNN was investigated as a function of the annealing temperature in the UV and visible spectrum (Figure 4.9a). Figure 4.9b compares the device responsivity as a function of the annealing temperature from 250 to 400 °C at three different wavelengths, namely 350 nm (rectangles), 370 nm (circles) and 400 nm (triangles).

Figure 4.9. (a) Spectral responsivity of the UNN photodetectors as a function of the annealing temperature and illumination wavelengths. (b) Device responsivity as a function of the annealing temperature at a wavelength of 350, 370 nm and 400 nm and applied bias of 1 V.

All UNN photodetectors had negligible response to visible light down to a wavelength of 400 nm (Figure 4.9a,b). The visible-light responsivity for all annealed devices was in the order of 0.005 A.W⁻¹ at 400 nm (Figure 4.9b). This shows that independently of the grain morphology all UNN are visible-blind. The responsivity increased drastically with the illumination wavelength decreasing from 400 to 370 nm (Figure 4.9a). The maximal responsivity peaked at ca. 7 A.W⁻¹ for the 300 °C annealed UNN (Figure 4.9b) under a light illumination with wavelength of 370 nm, which matches well the bandgap of ZnO (3.37 eV).

Figure 4.10 shows the photoresponse of the ZnO UNN to 370 nm UV light with an intensity of 62 and 86 µW.cm⁻². The photo-current shows a stable response to repetitive on/off cycles with a rapid initial increase before slow saturation. Upon switching off the UV light, the photocurrent drops initially sharply, and thereafter more slowly while approaching
the initial values. Rise and decay times were computed from the time taken for the current to increase from 10% to 90% of the peak value and vice versa, respectively.

Figure 4.10. Time-dependent photodetector response of the UNN annealed at 300 °C to alternative exposure of light with a light density of 62 and 86 µW.cm⁻² at a bias of 0.5 V and a wavelength of 370 nm.

The rise and decay times of the detector annealed at 300 °C are 145 s and 181 s, respectively, which are in line with that reported for pure ZnO nanostructured photodetectors.¹²,⁴² These relatively long rise and decay times are attributed to the chemi/physisorption and photodesorption of oxygen molecules on ZnO nanoparticles surface.¹²,⁴²

Figure 4.11. (a) Photo- and (b) dark-current characteristics of the UNN devices as a function of the annealing temperature.
Figure 4.11a-b show the $I-V$ characteristics of the ZnO photodetectors as a function of the annealing temperature under different applied bias with (Figure 4.11a) and without (Figure 4.11b) UV illumination. The $I-V$ response was linear and symmetrical (Figure 4.11a) indicating an Ohmic behaviour with sufficient availability of charge carriers to maintain high photocurrents (Figure 4.11a). All the samples exhibited ultra-low dark currents in the range of 22 pA up to 20 nA (Figure 4.11b). This is attributed to strong impact of surface states on the ZnO conductivity that results in electron-depleted grains, and the very high film porosity that reduces the number of neighbouring grains.\textsuperscript{12} It was also found that removal of organic contaminants from the photodetector substrates by calcination at 300 °C before UNN deposition drastically decreases surface leakage and the dark currents that, here, are ca. 90 times smaller than that (2 nA)\textsuperscript{12} was previously reported for similar ZnO UNNs.

![Figure 4.12](image)

Figure 4.12. (a) $I_{\text{photo}}/I_{\text{dark}}$ ratio as a function of the annealing temperature and (b) dark- and photocurrent of the UNN annealed at the optimal temperature of 300 °C.

Notably, the photocurrent (Figure 4.11a) increased drastically from 0.38 $\mu$A at 1 V of the as-prepared device to 128 $\mu$A of 250 °C annealed ones. The UNN annealed at 300 °C exhibited the highest photocurrent of 205 $\mu$A at 1 V. Annealing the UNN at higher temperatures, such as 350 °C and 400 °C decreased the photocurrent slightly to 190 and 182 $\mu$A, respectively. This is attributed to the increase of back scattering with increased particle size as discussed above (Figure 4.4). More important, the decrease in photoresponse was
accompanied by a large increase in dark-current from 22 pA for device annealed at 300 °C to 7.5 and 20.5 nA for photodetectors annealed at 350 °C and 400 °C, respectively (Figure 4.11b). The highest photocurrent (205 µA) coupled with the lowest dark-current (22 pA) resulted in the highest performance of the device annealed at 300 °C (Figure 4.11c,d).

Figure 4.12a shows the $I_{\text{photo}}/I_{\text{dark}}$ of ZnO photodetectors annealed as a function of the annealing temperature under illumination of 370 nm with intensity of 86 µW.cm$^{-2}$ at bias of 1 V. The $I_{\text{photo}}/I_{\text{dark}}$ photoresponse increases from $1.4 \times 10^4$ of the as-deposited UNN to $9.3 \times 10^6$ of the ones, annealed at 300 °C (Figure 4.12b). However, further increasing the annealing temperature to 350 °C and 400 °C decreases the $I_{\text{photo}}/I_{\text{dark}}$ to $2.6 \times 10^4$ and $0.9 \times 10^4$, respectively. In addition, a specific detectivity and an External quantum efficiency (EQE%) of ca. $10^{12}$ and $2.3 \times 10^3$, respectively, have been computed (Figure 4.13) for the UNN photodetector annealed at 300 °C. The detectivity decreased rapidly for sintering temperatures below 250 °C and above 300 °C.

![Figure 4.13. The detectivity and EQE% of the devices after annealing at different temperature under the applied bias of 1 V and light density of 86 µW.cm$^{-2}$.](image)

**4.3.4 Photodetection Mechanism**

This optimal performance of the UNN annealed at 300 °C is attributed to the distinct contribution of light absorption, electron conduction and surface states in the resulting
photocurrent and dark current, as discussed below. In fact, the initial rise in photocurrent is attributed to the formation of sintering neck between the ZnO nanoparticles (Figure 4.14) that results in better electron transport through the ultraporous nanoparticle networks. The drop in photocurrent for annealing temperature above 350 °C is attributed to smaller specific surface area (SSA) for particles annealed at higher temperature. In fact, the ZnO nanoparticles SSA decreased significantly from 63 to 30 m².g⁻¹ by increasing the annealing temperature from 300 °C to 400 °C. This is schematically shown in Figure 4.14 for the as-prepared (Figure 4.14a) and annealed (Figure 4.14b-c) UNNs. Annealing at 300 °C has almost negligible effect on the particle size (Figure 4.14b and Figure 4.7, red circles) and morphology (Figure 4.5d). In contrast, annealing at 400 °C increased their sauter diameter from 16 to 35 nm (Figure 4.14c and Figure 4.7, red circles), this indicates a significant amount of grain necking, which is further confirmed by the TEM analysis.

![Figure 4.14. TEM images of the ZnO nanoparticles collected from the UNN (a) before and after annealing at (b) 300 °C and (c) 400 °C.](image)

The photo-response and electron conduction mechanisms of the ZnO UNN are discussed as a function of the annealing temperature and resulting structural properties in Figure 4.15a-c. Zinc oxide is a n-type semiconductor with electrical conductivity dominated by electron transport. The latter is characterized by three main regimes, namely the inner grain, the grain surface and the inter-grain boundary. The inner grain is usually defined as the region of the particle where bulk electrical conductivity is reached and the effect of surface states is
negligible. The surface region lays within the semiconductor Debye’s length from the surface and is characterized by a strong band bending and electron depletion due to adsorption of atmospheric O\textsubscript{2} that trap electrons from the semiconductor conduction band.\textsuperscript{28} For n-type materials this results in significantly lower electrical conductivity.

Figure 4.15. Schematic representation of the ZnO nanoparticle photodetection and inter-grain conduction as a function of the grain boundary morphology for the devices (a) before and after annealing at (b) 300 °C and (c) 400 °C.

The inter-grain boundaries are strongly affected by the type of annealing necks formed between the nanoparticles (Figure 4.15a-c). On one extreme, non-annealed particles that are held together by van der Waals forces experience very high electrical resistance as the charge carrier needs to be hopping between the grains (Figure 4.15a). Annealed particles are distinguished by their grain boundary morphology. Open necks are grain boundaries which are smaller than twice the Debye’s length (2\(\delta\)) and thus experience similar electrical conduction as the surface region. Closed necks are large, strongly annealed grain boundaries with size greater than twice the Debye’s length and approaching bulk conductivity.

Here, the Debye length\textsuperscript{28} was computed as follows:\textsuperscript{43}

\[
\delta = \sqrt{\frac{\varepsilon_s K_b T}{e^2 n_c}}
\]  
(4.4)
where $\varepsilon_s$ is the static dielectric constant ($13.5 \times 8.5 \times 10^{-12}$ F/m in ZnO), $K_b$ is the Boltzmann’s constant ($1.38 \times 10^{-23}$ J/K), $T$ is an absolute temperature (K), $e$ is the electrical charge of the carrier ($1.6 \times 10^{-19}$ C), and $n_c$ is the carrier concentration (ca. $5 \times 10^{16}$ cm$^{-3}$)$^{44}$. At room temperature ($T = 298$ K) for ZnO, this results in a Debye length of ca. 19 nm. According to the TEM images (Figure 4.14a), the non-annealed particles are smaller than twice the Debye’s length and fully depleted in dark condition (Figure 4.15a and Figure 4.11b) but due to the large number of inter-grain barriers caused by the lack of sintering necks, the device exhibits a high resistance and limited photocurrent rise under light illumination (Figure 4.15a and Figure 4.11a, purple triangles).

In contrast, annealing the UNN at 300 °C led to the formation of an open neck morphology between the ZnO nanoparticles (Figure 4.15b) and decreased the total film resistance resulting in the highest photocurrents rise (Figure 4.11a, red diamonds). Annealing the UNN at higher temperatures increased the particle size leading to a $d_{BET}$ of 35 nm at 400 °C annealing temperature, which is very close to twice the Debye’s length ($2\delta = 38$ nm) of ZnO at room temperature. This results in a closed neck morphology (Figure 4.15c). In fact, the TEM analysis reveals that many particles have a diameter of significantly larger than $2\delta$ (Figure 4.14c). As a consequence, these larger particles and inter-grain necks are only partially electron depleted$^{28}$ and exhibit a lower photo to dark current ratios under the same UV light illumination (Figure 4a, green hexagonal). In fact while their photocurrent is similar to the 300 °C UNN, their dark-current (20.5 nA) is 930 time higher (Figure 4.11b). Similar optimization mechanisms of the grain boundary morphology were found for SnO$_2$-based chemical sensors gas sensors$^{29}$ suggesting that enhancement of electro-transduction of chemical- and photo-induced variations in surface states may be optimally enhanced for a grain and neck size close to twice the Debye’s length of the semiconductor.

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4.4 Conclusions

In conclusion, we have investigated the effect of the grain boundary morphology on the photodetection mechanism of UNN-based UV-photodetectors. Although annealing, up to 400 °C, had no significant impact on the macro-scale morphology and optical properties, the inter-grain structure changed significantly resulting in different electron conduction mechanism. The optimized device featured ultra-low dark current of 22 pA and high photocurrent of 205 µA at a light intensity of 86 µW.cm⁻² and bias of 1 V. The resulting $I_{\text{photo}}/I_{\text{dark}}$ ratio ($9.3 \times 10^6$) is the highest so far reported at this light intensity. This optimal performance was attributed to two main mechanisms, namely the inhibition of the photocurrent in the as-prepared samples due to electron hopping at the grain boundaries, and the increase of the dark-current in the strongly annealed samples due to their closed-neck grain morphology. In contrast, thermal-induced formation of an electron-depleted open-neck inter-grain morphology resulted in very low pA dark-currents and high photocurrents. These findings provide further insights on the photodetection mechanism of these wide bandgap semiconductors and a set of principles for the optimization of nanoparticle-based optoelectronic devices.
4.5 References


Chapter Five

Tunable Band-Selective UV-Photodetectors by 3D Self-Assembly of Heterogeneous Nanoparticle Networks
Publication relevant to this chapter:


Abstract

Accurate detection of ultraviolet radiation is critical to many technologies including wearable devices for skin cancer prevention, optical communication systems and missile launch detection. Here, we present a highly performing nanoscale architecture for band-selective UV-photodetectors that features unique tunability and miniaturization potential. The device layout relies on the 3D integration of ultraporous layers of tailored nanoparticles. By tailoring the transmittance window between the indirect band gap of TiO₂ nanoparticles and the sharp edge of the direct band gap of ZnO, we achieve a band-selective photoresponse with tunable bandwidth to less than 30 nm and photo- to dark-current ratios of several millions at a light intensity of 86 µW.cm⁻² and operation bias of 1 V. We showcase the potential of this integrated morphology by fabrication of the first inherent UVA photodetector with selectivity against the edge of the UVB and visible light of nearly 60 times. This tunable architecture and nanofabrication approach are compatible with state-of-the micromachining technologies, and provide a flexible solution for the engineering of wearable band-selective photodetectors.
5.1 Introduction

Ultraviolet radiation is the highest energy component of the solar spectrum reaching the earth’s surface.\(^1\) Nature relies on its unique attributes for numerous purposes. Band-selective absorption and reflection of UV-light is the invisible language of butterflies and enables the safe mating of numerous species.\(^2\)-\(^3\) In the skin, UV-light stimulates the synthesis of vitamin D, an essential compound for many metabolic processes.\(^4\) UV radiation is also the most important environmental factor in the pathogenesis of skin cancer.\(^5\) While UVC \((100\leq \lambda <280\, \text{nm})\) radiation is blocked by the ozone layer,\(^6\)-\(^7\) UVA \((315\leq \lambda <400\, \text{nm})\) and UVB \((280\leq \lambda <315\, \text{nm})\) pass through and cause numerous diseases.\(^8\) These include erythema,\(^9\) DNA damage,\(^10\) apoptotic cell death,\(^11\) skin pigmentation\(^12\) and skin cancer\(^13\). Studies over the past two decades\(^14\)-\(^15\) show that UVA damages skin cells called keratinocytes in the basal layer of the epidermis, where most skin cancers start.\(^16\) UVB, the main cause of skin reddening and sunburn, tends to damage the skin's more superficial epidermal layers.\(^17\) It also plays a contributory role in tanning, burning and photo-aging. Wearable devices for band-selective measurement of UVA and UVB have numerous applications including personal assessment of UV light exposure.\(^18\)-\(^20\)

Nanostructured wide bandgap semiconductors such as TiO\(_2\)\(^21\) and ZnO\(^22\)-\(^23\) are inherently visible-blind and can detect very low intensity of ultraviolet light by variations in the concentration of their surface-states.\(^24\)-\(^25\) Jin et al.\(^24\) reported a solution-processed UV photodetector based on colloidal ZnO nanoparticles with photo- to dark-current ratio of ca. \(2.6\times10^5\) at 830 \(\mu\text{W.cm}^{-2}\) light density and applied bias of 5 V. Highly performing and scalable electrospun ZnO-SnO\(_2\) nanofibers films\(^25\) featured up to \(4.6\times10^3\) \(I_{\text{UV}}/I_{\text{dark}}\) ratios under UV light intensities of 450 \(\mu\text{W.cm}^{-2}\). Recently, ultraporous networks of electron-depleted ZnO nanoparticles,\(^23\) made by aerosol self-assembly, have demonstrated excellent performance as photodetectors featuring milliampere high photocurrents, more than \(10^5\)
photo- to dark-current ratios at 5 V bias and low light intensities of 86 µW.cm$^{-2}$. Furthermore, their aerosol-based synthesis approach is compatible with state-of-the-art CMOS-micromachining processes$^{26}$ enabling the parallel wafer-level fabrication of chip-size devices of few hundreds µm$^2$. However, a key limitation of these wide band gap semiconductors is their broad photoresponse$^{23}$ that cannot distinguish between UVA and UVB radiation.

Fang et al.$^{28}$ have recently demonstrated the band-selective detection of visible light by tuning the bandgap of perovskite single-crystals. Ren et al.$^{29}$ reported the fabrication of band-selective infrared photodetectors based on InAs$_x$P$_{1-x}$ nanowires.$^{29}$ A key challenge of these approaches is the requirement of fine-tuning simultaneously multiple material properties, such as spectral absorbance, electron-hole recombination and carrier mobility.$^{29}$ For example, for InAs$_x$P$_{1-x}$ nanowires, the peak photocurrent decreased by an hundred fold from ca. 70 to 0.17 nA with increasing content from 0 to 0.7. An alternative approach, demonstrated for chemical sensors,$^{30}$ is the 3D integration of functional layers of semiconductor nanoparticles. In this type of devices, each material can be individually optimized for a specific function resulting in an outstanding device-level performance.

Here, we present a nanoscale architecture for band-selective UV photodetectors that features excellent tunability, light detection performance and miniaturization potential. The device layout relies on the 3D integration of ultraporous functional layers of ZnO, SiO$_2$ and TiO$_2$ nanoparticles. A band-selective photoresponse is obtained by exploiting the transmittance window between the indirect bandgap of TiO$_2$ and the sharp-edge of the direct bandgap of ZnO. The bandwidth of these integrated metal-oxide nanoparticle networks (IMONNs) can be easily tuned from 85 to less than 30 nm. Optimal devices can be efficiently operated below 1 V and achieve UVA- to dark-current ratio of several millions and selectivity of nearly 60 times over UVB and visible light irradiation. Higher applied voltages of up to 10 V$^{23-25}$ have been often utilized to obtain this high photo-to dark-current ratios.
This is a challenge for their integration in wearable devices, where reaching operation voltages of 10 V requires bulkier battery components. In addition to the rapid CMOS-compatible fabrication process, this flexible device architecture could be extended to the visible and infrared spectral regions by selection of the appropriate nanoparticle semiconductor layers.

5.2 Experimental Section

5.2.1 Nanoparticles Deposition

A flame spray pyrolysis system was used for the synthesis and direct deposition of ZnO, SiO₂ and TiO₂ nanoparticles films onto the glass substrates featuring a set of interdigitated electrodes. The photodetector nanoparticles were prepared as follows: Zinc Naphthenate (10% Zn, Sigma Aldrich), hexamethyldisiloxane (HMDSO, Sigma Aldrich, purity > 99%) and titanium (IV) isopropoxide (TTIP, Sigma Aldrich, purity > 97%) were diluted in Xylene (Sigma Aldrich) with a total metal atom concentration of 0.3, 0.05 and 0.5 mol.l⁻¹ for Zn, Si and Ti respectively. All the solutions were supplied at a rate of 5 ml.min⁻¹ through a syringe pump, and dispersed into a fine spray with 7 L.min⁻¹ oxygen at a constant pressure drop of 2 bars. The spray was ignited by supporting premixed methane/oxygen flames (CH₄ = 1.2 L.min⁻¹, O₂ = 2 L.min⁻¹). A water-cooled substrate holder placed at 20 cm height above the burner (HAB) was utilized to keep the substrate temperature below 150 °C. The photodetector substrates were made of glass with interdigitated platinum lines with 5µm width and spacing and a total electrode area of 7×5 mm (G-IDEAU5, DropSens, Oviedo, Spain). More details about the device design and geometry are reported in previous work.²³ All substrates were cleaned with multiple ethanol/drying cycles before nanoparticles deposition.
5.2.2 Materials Characterization

The morphology and patterning characteristics of the deposited particles and films were investigated by a Hitachi H7100FA transmission electron microscope (TEM) at 100 kV and an analytical scanning electron microscopy (SEM), using Zeiss Ultraplus (FESEM) at 3 kV. The crystal phases, size ($d_{\text{XRD}}$) and surface compositions were characterized by X-Ray diffraction using Bruker system (XRD, D2 Phaser, U.S.A) equipped with Cu Ka radiation of average wavelength 1.54059 Å. The average primary particle diameter ($d_{\text{TEM}}$) was measured by TEM analysis at least 800 nanoparticles for each material and with the aid of an image processing software (ImageJ). This resulted in a visible primary particle diameter ($d_{\text{TEM}}$) of 18 ± 3 nm and 12 ± 2 nm for TiO$_2$ and ZnO, respectively. The substrates were kept in a furnace (Brother High Temperature Furnace XD-1.2KN) at 300 °C for 12 h, at ambient pressure prior photo-detecting tests, to decrease grain boundary barriers to electron conduction in the ZnO layer, increase the overall assembly stability and avoid resistive-sintering during the photo-detection measurements.

5.2.3 Photodetection Analysis

Absorbance spectra of the ultraporous and dense ZnO films deposited were measured with a Perkin-Elmer (Lambda 1050 UV/Vis/NIR) Spectrophotometer and a 150 mm integrating sphere. All optical measurements were carried out at room temperature. The film average integral transmittance is computed by subtraction of the fraction loss through the glass substrate. For $I-V$ measurements, DC currents were measured using a Picoammeter / Voltage source (Model 6487, Keithley). The detection of UV light was performed using a Newport Xenon lamp source 66920 and the UV-Vis absorption spectra were recorded in the wavelength range 250-500 nm using Princeton Instrument Acton SP2500 (0.500m Imaging Triple Grating Monochromator/Spectrograph).
5.3 Results and Discussion

5.3.1 IMONN Device Characterization

Figure 5.1 shows a schematic description of the IMONN layout. The device consists of three vertically-stacked ultraporous metal-oxide nanoparticle networks. The bottom layer is a photoresistor composed of electron-depleted ZnO nanoparticles. This n-type semiconductor morphology, with a direct bandgap of ca. 3.37 eV, has recently demonstrated excellent performance for broad-band detection ($\lambda < 400$ nm) of UV-light.

![Figure 5.1](image.png)

**Figure 5.1.** Schematic and band diagram of a band-selective UV photodetector based on an integrated metal-oxide nanoparticle network (IMONN) architecture. This is comprised of a photoresistor ZnO bottom layer, a very thin amorphous SiO$_2$ space layer and an anatase TiO$_2$ long-pass filter top layer.

The top layer acts as a tunable long-pass filter and is composed of an ultraporous network of anatase TiO$_2$ nanoparticles. The cut-off wavelength through this layer can be fine-tuned from 325 to ca. 400 nm by exploiting the wavelength-dependent absorbance of anatase TiO$_2$, an indirect band gap semiconductor. To electrically insulate the filter TiO$_2$ and photoresistor ZnO layer (Figure 5.1), a UV-transparent dielectric layer of SiO$_2$ nanoparticles is used as spacer. The theoretical upper and lower band-selective response of this TiO$_2$/SiO$_2$/ZnO IMONN layout correspond to the edge ($\lambda_{\text{upper}} = 375$ nm) of the ZnO bandgap and the cut-off wavelength of the anatase TiO$_2$ top layer ($\lambda_{\text{lower}} = 325$ - ca. 380 nm), respectively.
These devices were fabricated by sequential deposition of flame-made nanoparticle aerosols. The particle size of each metal-oxide layer was controlled by the metal-atom concentrations of the precursor solution set to 0.3, 0.05 and 0.5 mol.l\(^{-1}\) for the ZnO, SiO\(_2\) and TiO\(_2\) nanoparticles, respectively. Transmission electron microscopy (TEM) analysis of the ZnO and TiO\(_2\) nanoparticles collected from the aerosols (Figure 5.2a-d) reveals a spherical shape and a visible primary particle diameter \(d_{TEM}\) of \(18 \pm 3\) nm and \(12 \pm 2\) nm, respectively. This is in good agreement with previous reports on the flame-made TiO\(_2\)\(^{31-32}\) and ZnO\(^{23}\). The SiO\(_2\) nanoparticles consisted of larger agglomerates with more strongly sintered primary particles. As the role of the SiO\(_2\) is to act as a spacer between the ZnO and TiO\(_2\) layers, and they do not play a role in the photo-generation of electron-holes, their larger size than the ZnO has no impact on the devices performance.

![Figure 5.2. TEM images of the constituents (a) ZnO, (b) SiO\(_2\) and (c) TiO\(_2\) nanoparticles.](image)

These nanoparticles were self-assembled on the photodetector substrate surface by sequential thermophoretic-driven aerosol deposition resulting in an ultraporous network of TiO\(_2\), SiO\(_2\) and ZnO nanoparticles. This approach has been recently modelled\(^{33}\) and enables multi-layer morphologies with carefully controlled individual layer thickness and composition.\(^{30}\) An aerosol deposition time of 100 s was chosen for ZnO in line with recent reports on high-performance broad-band UV photodetector\(^{23}\). A SiO\(_2\) nanoparticle deposition time of 25 s was found to lead to excellent UV light transmittance and sufficient electrical insulation between the TiO\(_2\) and ZnO layers. The impact of the TiO\(_2\) layer thickness on the
resulting optical properties and device performance was further investigated as a function of the TiO₂ film thickness from 1.6 to 6.6 µm.

Figure 5.3a shows SEM image of the top pure ZnO UNN. The surface morphology of an exemplary TiO₂/SiO₂/ZnO IMONN consist of a ZnO, SiO₂ and TiO₂ layer with 9.5, 0.12 and 5.3 µm thickness is presented in Figure 5.3b. The morphology of the resulting layer is uniform and ultraporous with a hierarchical nano- and micro-scale pore size distribution. The film porosity of the TiO₂/SiO₂/ZnO network, computed by gravimetric and cross-sectional SEM analysis, is ca. 98%. This is in good agreement with previous reports on single nanoparticle layers deposited by thermophoretic-driven aerosol self-assembly²⁶,³⁴. In fact, this integrated TiO₂/SiO₂/ZnO morphology can hardly be distinguished from that of the bottom ZnO nanoparticle layer (Figure 5.3a,b).

![Figure 5.3. Top-view SEM image of an exemplary (a) pure ZnO UNN and (b) TiO₂/SiO₂/ZnO IMONN consist of a ZnO, SiO₂ and TiO₂ layer with 9.5, 0.12 and 5.3 µm thickness, respectively.](image)

The film morphology was not affected by the sequential deposition of the different aerosols and there were no variations in the morphology noticed (Figure 5.3a,b). Cross-sectional SEM analysis reveals that sequential aerosol deposition of the SiO₂ nanoparticles on the ZnO layer does not vary the average layer thickness (Figure 5.4). This is attributed to the high surface roughness of aerosol-deposited nanoparticle layers³³ and the very low SiO₂
precursor concentration (0.05 mol.l$^{-1}$) and aerosol deposition time (25 s) utilized here that results in the deposition of a very small SiO$_2$ nanoparticle volume$^{35}$. In fact, the thickness of SiO$_2$ layer deposited for 25 s on a bare glass substrate was ca. 120 nm (Figure 5.5).

In contrast, aerosol deposition of TiO$_2$ nanoparticles for 75 s increased the SEM cross-sectional thickness from 9.5 $\mu$m of the ZnO bottom layer to ca. 16 $\mu$m (Figure 5.6a,b). This is in line with the significantly higher concentration (0.5 mol.l$^{-1}$) of the TiO$_2$ precursor$^{36}$. The TiO$_2$/SiO$_2$/ZnO network thickness increased linearly from 11 $\mu$m to 16 $\mu$m with increasing TiO$_2$ nanoparticle aerosol deposition time from 15 to 75 s indicating a constant TiO$_2$ layer growth rate of ca. 5 $\mu$m.min$^{-1}$.

![Figure 5.4](image)

**Figure 5.4.** (a) Cross-section SEM image of the SiO$_2$/ZnO structure and EDX qualitative elemental mapping along the cross-section revealing the location of the (b) Si and (c) Zn atoms.

![Figure 5.5](image)

**Figure 5.5.** Cross-section SEM image of a pure SiO$_2$ nanoparticle layer deposited on a glass substrate with an aerosol deposition time of 25 s.

Figure 5.7a,b show the X-ray diffraction (XRD) and Fourier Transform Infrared Spectroscopy (FTIR) measurements of the TiO$_2$/SiO$_2$/ZnO devices and that of the individual ZnO, SiO$_2$ and TiO$_2$ flame-made nanoparticles. The XRD spectra of ZnO and TiO$_2$ correspond to the hexagonal wurtzite (JCPDS No. 36-1451) and tetragonal anatase (JCPDS
The resulting average ZnO and TiO$_2$ crystal sizes are $12.9\pm1$ nm for both materials. Notably, the SiO$_2$ nanoparticles XRD spectrum was characteristic of an amorphous material with a broad hump at a 2$\theta$ of 22°. The XRD spectra of the TiO$_2$/SiO$_2$/ZnO network (Figure 5.7a) matched well the combined XRD peaks of the individual ZnO and TiO$_2$ nanoparticles and the accentuated amorphous hump of the SiO$_2$. The average crystal sizes of the anatase and wurtzite phase in the TiO$_2$/SiO$_2$/ZnO network are $15.8\pm1$ nm and $15.3\pm1$ nm, respectively, and thus close to that of the corresponding nanoparticle aerosols.

**Figure 5.6.** Visible film thickness of (a) IMONN devices as a function of TiO$_2$ deposition time with a ZnO and SiO$_2$ deposition time of 100 and 25 s, respectively and of (b) the single layers as a function of aerosol deposition time.

The composition of the TiO$_2$/SiO$_2$/ZnO network was further assessed by FTIR analysis (Figure 5.7b). This confirmed the integration of these three nanoparticle aerosols in a single structure. For the ZnO nanoparticles, a strong absorption band was observed at 505 cm$^{-1}$ which is usually associated with oxygen deficiency and/or oxygen vacancy ($V_O$) defect complex in ZnO$^{37}$. The broad absorption band at 3438 cm$^{-1}$ is assigned to the O-H stretching vibration of hydroxyl groups and attributed to adsorption of moisture.$^{38}$ The FTIR spectra of the SiO$_2$ nanoparticles was characterized by a strong broad IR band at 1089 cm$^{-1}$ with a shoulder at 1200 cm$^{-1}$ that are attributed to the transverse-optical and longitudinal-optical
modes of the Si-O-Si asymmetric stretching vibrations. The smaller band at 956 cm\(^{-1}\) is indicative of silanol groups and Si-O symmetric stretching vibrations. The band at 800 cm\(^{-1}\) is attributed to the Si-O-Si symmetric stretching vibrations, whereas the band at 474 cm\(^{-1}\) is assigned to the O-Si-O bending vibrations. In the TiO\(_2\)/SiO\(_2\)/ZnO network, many of these bands overlap with the Ti-O modes and cannot be clearly assigned to the SiO\(_2\). However, the Si-O-Si asymmetric stretching vibrations are detectable also on the TiO\(_2\)/SiO\(_2\)/ZnO structure as a broad band from 1000 to 1250 cm\(^{-1}\). In the TiO\(_2\) spectra, the absorption bands at 672, 739 and 960 cm\(^{-1}\) are attributed to the Ti-O stretching modes. The FTIR spectra of the TiO\(_2\)/SiO\(_2\)/ZnO network (Figure 5.7b) matches the contributions of the individual nanoparticles further confirming the successful integration of these nanomaterials in a single ultraporous structure.

**Figure 5.7.** (a) XRD and (c) FTIR spectra of the IMONN structure and of the individual ZnO, SiO\(_2\) and TiO\(_2\) nanoparticle constituents.

**Figure 5.8.** (a) Cross-section SEM image of the IMONN structure reveals a uniform highly porous and crack-free morphology. EDX qualitative elemental mapping along the cross-section (d) of the IMONN reveals the location of the (e) Zn, (f) Ti and (g) Si atoms.
The three-dimensional distribution of the ZnO, SiO₂ and TiO₂ nanoparticles in the network was investigated by cross-sectional SEM elemental mapping (Figure 5.8a-d). The vertical distribution of the Ti, Si and Zn atoms is in line with the sequence of aerosol deposition. The Zn is localized in the first 9.5 µm thickness (Figure 5.8b) while the Ti atoms (Figure 5.8c) are mostly relegated above 10 µm. In contrast, the Si atoms, strongly visible in the glass substrate, were randomly distributed within the ZnO layer (Figure 5.8d). This is in line with very rough top surface morphology of these aerosol-deposited nanoparticle layers that can be easily penetrated and filled by deposition of a sequential nanoparticle aerosols. This cross-sectional composition is also in good agreement with the observed layer growth rates (Figure 5.6) and confirms the vertical stacking of the ZnO and TiO₂ nanoparticle layers.

5.3.2 Optical Properties

Figure 5.9 shows the optical transmittance spectra of single TiO₂ layers as a function of their film thickness (Figure 5.9a), and of a TiO₂/SiO₂/ZnO network upon sequential deposition of each nanoparticle aerosol (Figure 5.9b). All films were highly transparent to visible light. The optical transmittance spectra of the IMMON devices before and after subtraction of the fraction loss through the glass substrate and its optical image (inset) of the optical IMMON device with a 4.4 µm thick TiO₂ layer on glass substrates placed over a printed paper are presented in Figure 5.10. Notably, the film transmittance of TiO₂/SiO₂/ZnO structure with the thickest TiO₂ film of 6.6 µm is 91.6% at the wavelength of 500 nm. The single ZnO layer (Figure 5.9b) had a sharp drop in transmittance below 370 nm, in line with its direct bandgap of 3.37 eV. This is quite close to the end of the visible spectrum (400 nm) and well within the UVA range (315-400 nm). This sharp absorption edge is not dependent from the thickness of the ZnO layer. In stark contrast, the absorption edge and cut-off wavelength of the single TiO₂ layer was strongly dependent on its thickness. Notably, for the
same thickness and a wavelength of 375 nm, the TiO$_2$ layer had significantly higher light transmittance than the ZnO layer (Figure 5.11a).

**Figure 5.9.** Optical transmittance spectra of (a) a single ultraporous TiO$_2$ layers deposited on blank glass substrates (grey circles) with different film thickness. The arrow show the fine tuning of the cut-off wavelength by increasing the TiO$_2$ film thickness from 1.6 to 6.6 $\mu$m. (b) Comparison of the transmittance spectra of a pure ultraporous ZnO layer and of the IMONN structure upon each sequential step with a SiO$_2$ and TiO$_2$ film thickness of 0.12 and 6.6 $\mu$m, respectively.

This is despite the anatase TiO$_2$ phase having a lower bandgap (3.2 eV) than the wurtzite ZnO phase (3.37 eV). The cut-off wavelength of the single TiO$_2$ nanoparticle layer increased from 325 to 350 nm (Figure 5.9a) with increasing TiO$_2$ layer thickness from ca. 1.6 $\mu$m to 6.6 $\mu$m. The blue-shift observed for the these ultraporous layers is attributed to the indirect band gap structure of anatase TiO$_2$\textsuperscript{46-47}. This is in good agreement with previous studies\textsuperscript{48} showing that the absorption edge of indirect bandgap semiconductors can be fine-tuned by adjusting the film porosity, and thus the effective refractive index and the film thickness. This is because the absorptivity of anatase TiO$_2$ increases with decreasing wavelength even for photons having energy above the TiO$_2$ bandgap and thus there is not a sharp transition. As a result, the effective transmittance is strongly dependent on the wavelength and film thickness.

In contrast, gross-tunning of the UV light absorption was achieved with the ZnO nanoparticle layer by changing its thicknesses. Hanini et al.\textsuperscript{48} reported that annealing at 550
°C for 20 min shifted the absorption edge of anatase TiO$_2$ from 3.42 to 3.04 eV and attributed it to an increase in film packing density and oxygen deficiency. Here, at the edge of the UVB spectrum ($\lambda = 320$ nm), the transmittance through the anatase TiO$_2$ layer decreased to less than 2% for a TiO$_2$ layer with 6.6 µm thickness, while 30% of UVA transmittance ($\lambda = 340$ nm) was preserved. As a result, these ultraporous TiO$_2$ layers can efficiently block UVB radiation while transmitting a significant fraction of UVA.

Figure 5.10. Optical transmittance spectra of IMMON devices (a) before and (b) after subtraction of the fraction loss through the glass substrate and optical image (inset) of IMMON device with 4.4 mm thick TiO$_2$ layer (45 s) on a glass substrate placed over a printed paper.

Figure 5.9b shows the evolution of the optical properties of the TiO$_2$/SiO$_2$/ZnO network upon each aerosol deposition step. The spectrum of the ultraporous ZnO layer is in line with that recently reported$^{23}$ for single ZnO layer broad-band UV photodetectors. Upon deposition of the SiO$_2$ space layer, the spectrum of the resulting SiO$_2$/ZnO structure was indistinguishable from the ZnO. This is due to the high transparency of aerosol-deposited SiO$_2$ layer as previously discussed for their application as antifogging coatings$^{35}$. In contrast, a TiO$_2$ film thickness of 1.6 µm drastically decreased the transmittance of UV light (Figure 5.11b). In the UVA ($\lambda = 370$ nm), the transmittance through the TiO$_2$/SiO$_2$/ZnO network with a TiO$_2$ film thickness of 6.6 µm (Figure 5.9b) was ca. 20%, and decreased to only 0.1% in the UVB domain ($\lambda = 310$ nm). These results show that the optical properties of the
The TiO$_2$/SiO$_2$/ZnO network can be easily tuned by adjusting the thickness of the top TiO$_2$ layer. Most importantly, we demonstrate that, despite the closely located bandgap of ZnO (3.37 eV) and TiO$_2$ (3.2 eV), a tunable transmittance window (Figure 5.11b) can be engineered between the top TiO$_2$ filter and the bottom ZnO photoresistive layers.

**Figure 5.11.** Optical transmittance spectra of (a) ultraporous single ZnO and TiO$_2$ layers deposited on blank glass substrates (grey circles) after 45 s deposition time, and (b) ultraporous TiO$_2$ layers deposited on blank glass substrates (grey circles) as a function of the deposition time (15 and 75 s) and comparison with a ZnO film deposited with a deposition time of 100 s.

### 5.3.3 Photodetection Properties

Figure 5.12a,b present the real and normalized photodetection performances of the TiO$_2$/SiO$_2$/ZnO networks as a function of the TiO$_2$ layer thickness. Notably, deposition of a 1.6 µm thick layer of TiO$_2$ nanoparticles transformed the broad-band spectral response of the single ZnO layer (Figure 5.12b, circles) into a band-selective one (Figure 5.12b, down triangles). Increasing the TiO$_2$ film thickness from 1.6 to 6.6 µm narrowed the bandwidth of the spectral response while preserving the peak response at a wavelength of 370 nm. This spectral responsivity (Figure 5.12b) is ideally located in the UVA range. The bandwidth, defined as the full width at half maximum, of the photodetector response (Figure 5.13) decreased linearly from 85 nm of the pure ZnO layers to 29 nm of the TiO$_2$/SiO$_2$/ZnO networks with 6.6 µm thick TiO$_2$ layer.
Figure 5.12. (a) Real and (b) normalized responsivity spectra of the IMONN devices as a function of TiO$_2$ film thickness.

Thicker TiO$_2$ layers are expected to lead to narrower bandwidth response with the lower limit being the amount of UV light reaching the bottom ZnO layer. As the TiO$_2$/SiO$_2$/ZnO networks with a bandwidth of 29 nm have photo- to dark-current ratios in the order of millions, this architecture should easily reach bandwidth of a few nanometers. It is worth mentioning that in the absence of the SiO$_2$ layer (Figure 5.14), the TiO$_2$ layer contributes to the photo-response resulting in a broad-band detector. Notably, the photo-response of the TiO$_2$/ZnO was still lower than that of the pure ZnO below 350 nm.

However, it was significantly higher (e.g. 500% at 315 nm) than with the SiO$_2$ space layer. The drop in the photo-response of the TiO$_2$/ZnO layout is attributed to the lower conductivity of the TiO$_2$ layer than that of the pure ZnO. This results in lower photo-currents than for the single ZnO layer despite the photo-generation of electron/hole pairs in the TiO$_2$ layer. A major figure of merit of the TiO$_2$/SiO$_2$/ZnO networks is that while the ultraporous TiO$_2$ layer efficiently blocks the UVB radiation reaching the underlying ZnO structure, it let a significant fraction of the UVA light through and did not affect the dark-current of the devices (ca. 18-22 pA).
**Figure 5.13.** Photoresponse bandwidth of the IMONN devices as a function of TiO₂ film thickness. (inset) Exemplary real responsivity spectra of a device with TiO₂ film thickness of 6.6 µm featuring a bandwidth of 29 nm.

**Figure 5.14.** Normalized responsivity spectra of a IMONN device with (squares) and without (diamonds) the SiO₂ space layer.

For all devices, the I-V characteristics under dark and UV light (370 nm) reveal good ohmic contacts. Notably, the on/off photo- to dark-current ratios are in the order of several millions at a low light intensity of 86 µW.cm² and a bias of 1 V. This $\text{I}_{\text{UVA}}/\text{I}_{\text{dark}}$ ratio ($9.3 \times 10^6$) is ~ 465 times higher than the highest previously reported for similar light intensity and operation bias$^{23}$. At a wavelength of 370 nm and a bias of 1V, the photocurrent decreased
only from 205 µA to 79 µA with increasing TiO₂ film thickness from 1.6 to 6.6 µm (Figure 5.15). This corresponds to a relatively small change in photo- to dark-current ratio (Figure 5.16, circles) that, at a bias of 1 V and 40 µW.cm⁻², decreased linearly with increasing TiO₂ film thickness from 4.2×10⁶ of the pure ZnO to 1.6×10⁶ of the TiO₂/SiO₂/ZnO networks with 6.6 µm thick TiO₂ layer. The latter photo- to dark-current ratio (1.6×10⁶) is still ~180 times higher than the highest previously reported²³ (2×10⁴) at the similar light intensity and bias. Notably, the UVA selectivity of these TiO₂/SiO₂/ZnO networks against the edge (λ = 315 nm) of UVB (I_UVA/I_UVB) increased drastically from 0.82 to 58 with increasing TiO₂ film thickness from 1.6 to 6.6 µm (Figure 5.16), while the selectivity against the edge (λ = 400 nm) of the visible light spectrum (I_UVA/I_vis) decreased only from 92 to 59 (Figure 5.16, squares).

Figure 5.15. I-V characteristics of the IMONN devices as a function of the TiO₂ film thickness at an illumination wavelength of 370 nm and light density (LD) of 86 µW.cm⁻².

Figure 5.17 shows a comparison of the photodetector performance of a single ZnO layer (Figure 5.17a) and a TiO₂/SiO₂/ZnO network with a 4.4 µm thick TiO₂ layer (Figure 5.17b). For both devices, the photocurrent increased linearly with increasing light density indicating no carrier mobility saturation and sweep-out effect up to the maximum light density...
investigated here. Notably, integration of an ultraporous TiO$_2$ layer with a thickness of ca. 4.4 µm increased the $I_{UV\text{A}}/I_{UV\text{B}}$ selectivity by a factor of 20 (from ca. 0.82 to 16) while decreased the responsivity from 6.8 A.W$^{-1}$ of the single ZnO layer to 4.0 A.W$^{-1}$ of the TiO$_2$/SiO$_2$/ZnO network. This resulted in an excellent performance with detection of low UVA light intensity of less than 10 µW.cm$^{-2}$ and a bandwidth of 51 nm.

![Figure 5.16](image-url)  
**Figure 5.16.** Figure of merit of the IMMON devices as a function of the TiO$_2$ deposition time: photoresponse selectivity in terms of UVA to UVB (square) and visible light (hexagons) responsivity ratios and photo- to dark-current ratio (circles).

![Figure 5.17](image-url)  
**Figure 5.17.** Comparison of the photoresponse to the UVA, UVB and visible light of (a) a single layer ZnO and (b) an IMONN device 4.4 µm thick TiO$_2$ layer as a function of the light density. Notably, the IMONN shows excellent UVA selectivity while the single ZnO layer cannot distinguish between UVA and UVB.
Current band-selective photodetector technologies are based on bulky assembly of Si-homojunctions and optical filters that have limited miniaturization potential and portability.\textsuperscript{49-50} Amongst other, this design can enable the fabrication of portable dual UVA and UVB radiation monitors. While the UVA radiation can be directly obtained by a single or a series of band-selective TiO\textsubscript{2}/SiO\textsubscript{2}/ZnO devices, the UVB component can be computed by measuring the whole UV spectrum with a broad-band ZnO devices and subtracting the UVA measured by a coupled IMONN device.

\textbf{5.4. Conclusions}

In conclusion, we have presented a novel solid-state architecture for high-performance tunable band-selective photodetectors. The device layout consists of an integrated ultraporous network of tailored nanoparticles with distinct functionalities, namely an electron-depleted photo-responsive nanoparticle layer, a dielectric spacer layer, and a tunable highly transparent filter layer. Notably, the spectral photo-response of the devices can be fine-tuned by the top filter layer. Rapid fabrication of band-selective UVA photodetectors with ultra-low dark currents of 22 \(\text{pA}\), high photocurrents of 182 \(\mu\text{A}\) at low light intensities of 86 \(\mu\text{W.cm}^{-2}\) and bias of 1V, were demonstrated. The bandwidth of these photodetectors was easily tuned from 85 to 29 nm. These band-selective devices featured the highest photo- to dark-current ratios so far reported at this light intensity with a \(I_{\text{UVA}}/I_{\text{dark}}\) of \(8.2 \times 10^6\) for thinnest and \(3.6 \times 10^6\) for the thickest TiO\textsubscript{2} layer, respectively. An outstanding UVA to UVB and to visible light selectivity in excess of 58 times was also achieved. This solid-state architecture can be implemented with other top - bottom layer compositions such as GaAs (1.4 eV) - Si (1.1 eV), and SnO\textsubscript{2} (3.7 eV) - ZnS (3.54 eV) enabling the fabrication of portable band-selective photodetectors for the UV, visible and infrared spectrums.
5.5. References


Chapter Six

Nanoarchitectonics of Three-Dimensional Heterojunctions for Fast-Responsive Visible-Blind UV Photodetectors
Publication relevant to this chapter:


Abstract

Visible-blind ultraviolet photodetectors are a promising emerging technology for the development of a new class of optoelectronic devices with greatly reduced power consumption and size requirements. A standing challenge is to drastically improve the sluggish response time of these nanostructured devices. Here, we present a three-dimensional nanoscale heterojunction architecture for fast-responsive visible-blind UV photodetectors. The device layout consists of p-type NiO clusters densely packed on the surface of an ultraporous network of electron-depleted n-type ZnO nanoparticles. This 3D structure can detect very low UV light densities while operating with a near-zero power consumption of ca. 4×10⁻¹¹ watts and a low bias of 0.2 mV. Most notably, heterojunction formation decreases the device rise and decay times by 26 and 20 times, respectively. These drastic enhancements in photoresponse dynamics are attributed to the stronger surface band bending and improved electron-hole separation of the nanoscale NiO/ZnO interface. These findings demonstrate a superior structural design and a simple, low-cost CMOS-compatible process for the engineering of high-performance wearable and integrated optoelectronic devices.
6.1 Introduction

Wide bandgap semiconductors, such as SiC, GaN, TiO$_2$ and ZnO have attracted considerable attention for their potential applications in nanoscale electronic and optoelectronic devices.$^{1-5}$ Among these materials, ZnO is a promising candidate for visible-blind UV photodetection due to its large and direct band gap (ca. 3.4 eV),$^{6-9}$ low-cost and ease of manufacturing. These excellent features enable efficient detection of UV light and a high selectivity against the visible spectrum ($R_{UV}/R_{vis}$).$^{6-7,10-12}$ An additional key requirement for many applications including biological and chemical analysis, missile detection, optical communication, and radiation monitoring are fast photoresponse dynamics.$^{7,13}$ Despite progress, the response dynamics of wide bandgap semiconductors such as ZnO is usually in the range of 30-200 s,$^{6-7,14-16}$ due to adsorption and desorption of O$_2$ trapping states.$^{17}$ To overcome this bottleneck, many studies have focused on the nanoarchitectonics of the ZnO morphology with efficient designs including nanowires,$^{18-19}$ nanorods,$^{1,20}$ nanodisks$^{21-22}$ and nanoparticles$^{6-7,23}$. In particular, optimized Scotty contacts have led to faster photoresponse dynamics$^{1,24-25}$ but typically require high operation bias of up to 20 V to obtain sufficient responsivity.$^{26-27}$

Several p-type semiconductors, such as GaN,$^{17,28}$ NiO,$^{29-30}$ Si$^{31-32}$ and Ge$^{33}$ have been explored as nanocomposite materials to enhance the response dynamics of n-type ZnO photodetectors. Among them, NiO, a p-type semiconductor with a room temperature bandgap of 3.6 eV, has attracted attention due to its transparency in the visible and UVA spectrum.$^{34-35}$ In addition, NiO presents a low lattice mismatch with ZnO (9\%) and forms a type-II alignment with the ZnO n-type band structure.$^{36}$ Recently, Retamal et al.$^{15}$ coated the surface of ZnO nanowires with monocrystalline NiO nanoparticles increasing the photo- to dark-current ratios from ca. 16 of the pure ZnO nanowires to $3.7 \times 10^4$ of the NiO/ZnO at a bias of 10 V and light density of 314 µW.cm$^{-2}$. In addition, the decay time was decreased from 657 s
of the pure ZnO to 133 s of the NiO-coated ZnO nanowires. Despite these progresses, the photoresponse time of these visible-blind photodetectors is still too slow for many real-world uses.

Here, we present a highly performing nanoscale architecture for the engineering of fast-responding wide bandgap UV photodetectors. Decoration of a 98% porous film of n-type ZnO nanoparticles with p-type NiO clusters resulted in a three-dimensional network of nanoscale heterojunctions (3DNH). The built-in electric fields between the nanoscale p- and n-type domains enable the rapid separation of the photogenerated electron-hole pairs decreasing the photo-current rise and decay times by 26- and 20 folds, respectively. This 3DNH design also features excellent responsivities of more than 12 A.W⁻¹, photo to dark ratios exceeding 10⁷ and ultra-high directivities of up to 3×10¹² Jones at a bias of 1 V and light density of 80 µW.cm⁻².

6.2 Experimental

6.2.1 Nanoparticles Deposition

A flame spray pyrolysis (FSP) system was used for the synthesis and direct deposition of ZnO nanoparticle aerosols onto the glass substrates fabricated with a set of interdigitated electrodes. The photodetector nanoparticles were prepared as follows: Zinc Naphthenate (10% Zn, Sigma Aldrich) was diluted in Xylene (Sigma Aldrich) with a total metal atom concentration of 0.3 mol.L⁻¹ for Zn. The prepared solution was supplied at a rate of 5 mL.min⁻¹ through a syringe pump, and dispersed into a fine spray with 7 L.min⁻¹ oxygen at a constant pressure drop of 2 bars. The spray was ignited by supporting premixed methane/oxygen flames (CH₄ = 1.2 L.min⁻¹, O₂ = 2 L.min⁻¹). A water-cooled substrate holder placed at 20 cm height above the burner (HAB) was utilized to keep the substrate temperature below 150 °C. The photodetector substrates were made of glass with interdigitated platinum
lines with 5µm width and spacing and a total electrode area of 7×5 mm (G-IDEAU5, DropSens, Oviedo, Spain). More details about the device design and geometry were reported in previous work. All substrates were cleaned with multiple ethanol/drying cycles and pre-annealed (Brother High Temperature Furnace XD-1.2KN) at 300 °C for 12 h, at ambient pressure prior photo-detecting tests before nanoparticles deposition.

6.2.2 Materials Characterization

The morphology and patterning characteristics of the deposited particles and films were investigated by a Hitachi H7100FA transmission electron microscope (TEM) at 100 kV and an analytical scanning electron microscopy (SEM), using Zeiss Ultraplus (FESEM) at 3 kV. Nickel oxide films were deposited by an AJA ATC 2400 magnetron sputtering system using a Ni target in an Ar/O₂ ambient (18/2 sccm). The chamber was evacuated to a base pressure of 9×10⁻⁷ Torr before deposition. Sputtering deposition was performed at a gas pressure of 4×10⁻³ Torr for 5, 25 and 40 seconds at room temperature with a power of 200 W. The prepared films were annealed in a furnace (Brother High Temperature Furnace XD-1.2KN) at 300 °C for 12 h, at ambient pressure prior photo-detecting tests, to stabilize the nanoparticle size and avoid resistive-sintering during the photo-detection measurements.

6.2.3 Photodetection Analysis

The optical properties of the ultraporous ZnO films were measured with a Perkin-Elmer (Lambda 1050 UV/Vis/NIR) Spectrophotometer and a 150 mm integrating sphere. All optical measurements were carried out at room temperature. For I-V measurements, DC currents were measured using a Picoammeter / Voltage source (Model 6487, Keithley), under the excitation of UV light from a Newport Xenon lamp source 66920.
6.3 Results and Discussion

6.3.1 Nanostructured Heterojunction Fabrication

Figure 6.1 shows a schematic of the 3DNH fabrication by rapid two-step gas-phase synthesis. First, a ZnO nanoparticle network is rapidly self-assembled on interdigitated electrodes by nanoparticle aerosol deposition (Figure 6.1a) as recently reported.\(^6\)-\(^7,37\)

This results in a very homogenous surface (Figure 6.2a) characterized by micro-sized pores between thin bridges of ultra-fine ZnO nanoparticles (Figure 6.2b). These nanoparticle networks have a film thickness of ca. 9 µm and an average porosity of 98%. Transmission electron microscopy (TEM) analysis of the ZnO particles collected from the substrates shows (Figure 6.2c) a spherical shape and a visible (d\(_{TEM}\)) average particle diameter of ca. 18 nm. Decoration of the ZnO surface with NiO clusters was achieved by magnetron sputtering using a Ni target in an Ar/O\(_2\) ambient (18/2 sccm) at a flat-substrate deposition rate of 11 nm\,min\(^{-1}\) (Figure 6.1b).

![Figure 6.1](image_url)  
*Figure 6.1. (a) An ultraporous ZnO nanoparticle networks is self-assembled on glass substrate with interdigited Pt electrodes by nanoparticle aerosol deposition. (b) Physical sputtering deposition of the NiO clusters on the ZnO nanoparticle networks.*

The resulting NiO/ZnO network is also uniform and ultraporous with no detectable changes in the micro-scale morphology (Figure 6.2d-e). However, TEM analysis (Figure 6.2f) revealed that upon sputtering, the ZnO nanoparticles are surrounded by a thin layer of
nanoscale clusters 2 - 5 nm in diameter. In order to decrease the grain boundary barriers to electron conduction, these ultraporous NiO/ZnO networks were post-sintered at 300 °C for 12 h with no assessable impact on the film morphology and crystallinity.6-7

Figure 6.3a shows the optical transmittance spectra of ZnO nanoparticles deposited on blank glass substrates as a function of NiO deposition time. Both the pure ZnO and the NiO/ZnO films were highly transparent to visible light with a relatively sharp cut-off below 370 nm. This is conveniently close to the end of the visible spectrum (400 nm) and well within the UV-A range (400 - 315 nm).

6.3.2 Optical Properties

The optical transmittance spectra of the devices before and after subtraction of the fraction loss through the glass substrate are presented in Figure 6.3. The UV light transmittance, at a
wavelength of 340 nm, (Figure 6.3) slightly decreased from 17% of the pure ZnO to 15% upon 40 s NiO sputtering time (equivalent to ca. 7.3 nm NiO bulk thickness). Similarly, the reflectance (Figure 6.4) of these ultraporous films at a wavelength of 400 nm increased from 14.3% of the pure ZnO to 16.6% upon 40 s NiO sputtering. This is attributed to grain growth, observed by TEM, upon NiO sputtering (Figure 6.2c,f), which is expected to increase light back-scattering38.

**Figure 6.3.** Optical transmittance spectra of pure ZnO (orange circles) and NiO/ZnO networks deposited on blank glass substrates (grey circles) with different sputtering times of 5 s (blue triangles), 25 s (green rectangles) and 40 s (red diamonds) (a) before and (b) after subtraction of the fraction loss through the glass substrate.

The three-dimensional distribution of the ZnO nanoparticles and NiO clusters in the ultraporous network was investigated by cross-sectional SEM elemental mapping (Figure 6.5a-d). Intensity line profiles extracted from the film cross-section show the normalized Zn, Ni and O element distributions (Figure 6.5e,f). It confirms that the self-assembled ZnO nanoparticle networks are porous enough for the Ni atoms to penetrate deep into the film and reach down to its bottom section. However, the Ni concentration is not uniform and it decreases approaching the substrate surface. The increase in oxygen atom signal toward the bottom of the film is attributed to the contribution from the glass substrate’s oxygen atoms.
Figure 6.4. Optical transmittance of the devices after subtraction of the fraction loss through the glass substrate.

Figure 6.5. (a) Cross-section SEM image of an exemplary NiO/ZnO networks with 40 s NiO sputtering time. EDX qualitative elemental mapping along the cross-section for (b) Ni, (c) Zn and (d) O atoms. (e) The film cross-section and (f) the extracted intensity line profiles showing the normalized Zn, Ni and O element distributions.
6.3.3 Photodetection Properties

Figure 6.6 shows the spectral responsivity of the photodetectors as a function of the illumination wavelength for different NiO sputtering time at the applied bias of 1 V. All ultraporous photodetectors had negligible response to visible light down to a wavelength of 400 nm. By definition, responsivity is the ratio of photo-current obtained by a device per unit area to the incident light power at a given wavelength. The visible-light responsivity for all photodetector devices was very low in the order of 0.01 A.W⁻¹ at 400 nm (Figure 6.6).

![Figure 6.6. Spectral responsivity of the pure ZnO and NiO/ZnO networks as a function of the NiO sputtering time, illumination wavelengths and applied bias.](image)

This corresponds to a photo-current of 360 nA. Notably, decreasing the wavelength below 400 nm, and thus entering the UV domain, sharply increased the responsivity of all devices, which reached their peak value at about 370 nm. The sharp cut-off at a wavelength of 370 nm is in good-agreement with the ZnO band gap of ca. 3.4 eV (λ = 370 nm) which is smaller than that of NiO (3.6 eV). This suggests that rise in photo-current is mostly due to photogeneration of electron-holes in the ZnO domain. A maximal responsivity of ca. 13 A.W⁻¹ was achieved with a 40 s NiO sputtering time (Figure 6.6). This responsivity (13 A.W⁻¹) is nearly
twice as high as that of the pure ZnO devices (7.3 A.W\(^{-1}\)), and quite high with respect to that of other highly performing nanoparticle films (0.5 to 7 A.W\(^{-1}\))\(^6,13\).

**Figure 6.7.** (a) I-V characteristics of the pure ZnO and NiO/ZnO networks as a function of the NiO sputtering time, illumination wavelengths and applied bias. (c) Photo-currents at \(\lambda = 370\) nm and dark-currents of the devices as a function of the NiO sputtering time.

Figure 6.7a illustrates the I-V photoresponse of the pure ZnO and NiO/ZnO networks as a function of applied bias from 0 to 1 V at wavelength of 370 nm and a light density of 80 \(\mu\)W.cm\(^{-2}\). For all samples, the I-V response was linear (Figure 6.7a) indicating an ohmic behaviour with sufficient availability of charge carriers. Notably, the photo-currents of the NiO/ZnO devices were significantly higher than those of the pure ZnO ones. Already after the shortest NiO sputtering time of 5 s, the photo-current increased slightly from 203 \(\mu\)A of the pure ZnO to 235 \(\mu\)A of the NiO/ZnO 3DNH. The devices with longest NiO sputtering time (40 s) exhibited the highest photo-currents of 345 \(\mu\)A (at 1 V), which is 70% higher than that of the pure ZnO (Figure 6.7a). Notably, in addition to increasing the photo-currents the NiO/ZnO 3DNH also decreased the dark-currents (Figure 6.7b).

In addition to the photodetectors responsivity, the specific detectivity (D) is a key figure-of-merit to describe the smallest detectable light density by a photodetector. This can be calculated accordingly to:

\[
D = \frac{\sqrt{AB}}{NEP}
\]

(6.1)
where $A$ is the effective area of the detector, $B$ is bandwidth and $NEP$ is the noise equivalent power. If the dark-current is the major contribution to the noise limiting the detectivity, this equation can be simplified to:

$$D = \frac{R}{\left(2e \cdot \frac{I_{\text{dark}}}{A}\right)^{1/2}}$$  

(6.2)

where $R$ is the responsivity, $e$ is the electron charge and $I_{\text{dark}}$ is the device dark-current.

Figure 6.8 shows the detectivity of the ZnO photodetectors before and after NiO sputtering and their corresponding responsivity at a bias of 1 V.

**Figure 6.8.** The detectivity and responsivity of the fabricated devices as a function of the NiO sputtering time.

The detectivity value increased from $0.9 \times 10^{12}$ Jones of the pure ZnO to $1.4 \times 10^{12}$ Jones of the NiO/ZnO 3DNH with 5 s NiO deposition time, and reached $3.0 \times 10^{12}$ Jones with 40 s NiO deposition time (Figure 6.8). Notably, a detectivity as high as 3 trillion Jones obtained from this NiO/ZnO 3DNH architecture has not been reported for photodetectors made of one- and two-dimensional nanostructures, due to the challenge in achieving simultaneously high responsivity and low dark-currents.
Figure 6.9. (a) Normalised and (b) unnormalised photo-current dynamics and (c) rise (circles) and decay (square) times of the pure ZnO and NiO/ZnO networks as a function of the NiO sputtering time at a bias of 0.3 V, light density (LD) of 80 µW.cm$^{-2}$ and illumination wavelength of 370 nm.

Figure 6.9a shows the normalised time-resolved photo-response of the pure ZnO and NiO/ZnO networks to 370 nm UV light with a light density of 80 µW.cm$^{-2}$. The raw photo-currents are presented in Figure 6.9b. For all devices, the photo-current initially increased rapidly and thereafter gradually saturated under illumination, and then descended as the illumination was switched off. Rise and decay times were computed from the time required for the photo-current to increase to 90% of the steady-state value and to decrease again by 90%, respectively. The rise and decay times of the pure ZnO during the on/off cycles were 132 and 179 s, respectively (Figure 6.9c) which is in line with that reported$^{6-7,15}$ for pure ZnO nanostructured photodetectors. This relatively long time, required to reach the steady-states
photo- and dark-currents, is attributed to the slow photo-desorption and chemi/physisorption of oxygen molecules on the ZnO nanoparticle surface. Upon heterojunction formation, the photo-current rise and decay times decreased significantly (Figure 6.9c) reaching 5 and 9 s, respectively, with a NiO sputtering time of 40 s. This is attributed to the fast electron-hole separation in the nanoscale solid-state heterojunction, and partial passivation of the ZnO surface by NiO. The latter, replaces the slower O$_2$ adsorption/desorption processes resulting in 20-26 times faster response times.

Figure 6.10. (a) Schematic representation of the photodetection mechanism of the pure ZnO and NiO/ZnO networks with corresponding surface band bending (SSB). (b) Energy level diagrams of the p-type NiO and n-type ZnO domains with respect to the vacuum level. (c) Schematic of energy band structure and electron-hole pair separation in NiO/ZnO heterojunction with equilibrated Fermi level ($E_F$).

6.3.4 Photodetection Mechanism
Figure 6.10a shows a schematic of the photo-detection mechanism of these NiO/ZnO networks vs. that of the pure ZnO ones. The lower dark-current and higher photo-current of NiO/ZnO devices are attributed to the formation of nanoscale open-circuit heterojunctions. In the dark, for the pure ZnO devices,\textsuperscript{6,7,37} oxygen molecules adsorb on the nanoparticle surface and capture free electrons from the semiconductor conduction band (Figure 6.10a). This results in a low-conductivity depletion layer near the surface of the ZnO, which suppresses the dark-current of these ultraporous nanoparticle networks.\textsuperscript{6,7,37} For the NiO/ZnO 3DNH devices, the Fermi energy equilibrates across the p-type and n-type domains resulting in a built-in electric field at the NiO/ZnO interface. This increases the electron-depletion of the ZnO surface resulting in a larger upward surface band bending (SBB) (Figure 6.10b,c)\textsuperscript{41} and even lower dark-currents (Figure 6.7b) than the pure ZnO. As the fraction of the ZnO surface decorated with NiO increases with increasing NiO sputtering time, the dark-current of the NiO/ZnO devices is further decreased.

Under UV light illumination with photon energies exceeding the ZnO band gap, electron-hole pairs are generated.\textsuperscript{6,7,13} For pure ZnO, the photogenerated holes migrate to the surface and discharge the adsorbed oxygen ions through surface electron-hole recombination. This reduces the depletion region and increases the free carrier concentration,\textsuperscript{6} resulting in the observed photo-current rise. Once the UV illumination is terminated, the accumulated holes recombine with the unpaired electrons, while oxygen gradually reabsorbs on the ZnO surface resulting in a slow current decay.\textsuperscript{6,7} For the NiO/ZnO networks, the photogenerated holes can rapidly migrate in the adjacent p-type domain,\textsuperscript{15,41} leading to prolonged electron lifetime and thus increased photo-current. Once the UV illumination is terminated, the excited electron-holes can recombine at the NiO/ZnO interface resulting in a rapid decay of the photo-current as this solid-state process does not require re-adsorption of the O\textsubscript{2} molecules.
The faster solid-state photo-response dynamics, and higher photo-current (345 µA) and lower dark-currents (18 pA) of the NiO/ZnO networks resulted in significantly superior photodetector performance. Figure 6.11 shows the $I_{UV}/I_{dark}$ ratio of ZnO photodetectors before and after NiO clusters deposition as a function of NiO deposition time under illumination of 370 nm with a light density of 80 µW.cm$^{-2}$ at a bias of 1 V. The $I_{UV}/I_{dark}$ ratio increased from $2.9 \times 10^6$ of the pure ZnO to $5.5 \times 10^6$ of the NiO/ZnO 3DNH with 5 s NiO deposition time.

![Figure 6.11](image)

**Figure 6.11.** $I_{UV}/I_{dark}$ ratio of photodetector devices with different NiO deposition time at the wavelength of 370 nm and the applied bias of 1 V.

Further increasing the NiO deposition time to 40 s increased the $I_{UV}/I_{dark}$ to $1.9 \times 10^7$. This is ca. 6 times higher than that of the pure ZnO, and the highest ratio so far reported for UV photodetectors under similar illumination and applied bias. This is attributed to the nanoscale size and 3D architecture of these carrier-depleted NiO/ZnO heterojunctions. While these NiO/ZnO networks absorb up to 80% of the incoming UV light (Figure 6.3), they are composed of individual nanoscale heterojunctions with a size of ca. 20 nm which is close to the Debye lengths of ZnO (19 nm)$^{6-7}$ and NiO (1-2 nm)$^{44}$. This is different from previously reported NiO-coated nanowires,$^{15}$ where the electron-depletion layer is limited to a fraction
(ca. 30%) of the ZnO nanowire radius (60 nm). As a result, the higher photo- to dark-current ratios obtained here (Figure 6.11) are attributed to the full depletion of the ZnO core and shorter hole migration lengths that results in significantly lower dark-currents and faster photo-response dynamics.

### 6.3.5 Low-Power Consumption Devices

In addition to fast response dynamics and high detectivity, low power-consumption is an important requirement for wearable devices. Here, the NiO/ZnO 3DNH with a sputtering time of 40 s NiO were operated down to a bias of less than 2 mV and were capable of detecting UV light densities below 80 µW.cm⁻² with very large photo- to dark-current ratios. Figure 6.12a presents the $I-V$ characteristics of the NiO/ZnO networks with 40 s NiO sputtering time, as a function of the applied bias from 0 to 2 mV in dark and under 370 nm UV light with a density of 80 µW.cm⁻². The $I-V$ response was linear (Figure 6.12a) with a photo-current of 0.4 µA at a bias of only 0.2 mV. These relatively high photo-currents coupled with the very low dark-current of 1 pA resulted in a photo- to dark-current ratio of $4 \times 10^5$ (Figure 6.12a), which is the highest ratio reported at this ultra-low voltage and low light density.¹⁵⁻¹⁶

The spectral responsivity of the NiO/ZnO 3DNH at the applied bias of 0.2 mV is illustrated in Figure 6.12b as a function of the illumination wavelength. It shows that this 3DNH architecture is able to detect low UV light density of 80 µW.cm⁻² at a bias of 0.2 mV with a responsivity and detectivity of ca. 15 mA.W⁻¹ and $1.14 \times 10^{10}$ Jones, respectively. Recently, Shen et al.⁴⁷ fabricated a self-powered UV photodetector based on solution-processed p-NiO/n-ZnO nanorod array heterojunction featuring 0.23 s and 0.21 s rise and decay times, respectively. In another approach,⁴⁸ a self-powered ZnO/Spiro-MeOTAD heterojunction UV photodetector was demonstrated using spin coating and then, sputtering
techniques resulting in shorter rise and decay times of 0.16 and 0.2 s, respectively at zero bias.

**Figure 6.12.** (a) Logarithmic and linear (inset) I-V characteristics of the NiO/ZnO networks with 40 s NiO sputtering time with and without UV light at a bias from 0 to 2 mV. (b) Spectral responsivity of the NiO/ZnO networks with 40 s NiO sputtering time as a function of illumination wavelengths at a bias of 0.2 mV.

However, these devices had low responsivities of 0.4 mA.W\(^{-2}\) and 0.22 mA.W\(^{-2}\), respectively.\(^{47,48}\) Notably, in addition to the excellent photodetector performance, this two-step fabrication approach is CMOS-compatible, low-cost and can be easily implemented on various substrates offering a powerful tool for the nanoarchitectonics of miniaturized optoelectronic devices.

### 6.4. Conclusions

In conclusion, we have presented a novel architecture for the engineering of visible-blind photodetectors featuring ultra-low external power consumption (4×10\(^{-11}\) watts), very high signal to noise ratios (> 10\(^5\)) and very low operation voltages (0.2 mV). The photoresponse dynamics of these 3D nanoscale heterojunctions is significantly faster (20-26 times) than that of equivalent photodetectors made of pure ZnO nanoparticle networks. This is attributed to the formation of open-circuit nanoscale heterojunctions at the NiO/ZnO interface and the very small migration length from the n-type to the p-type domains. This leads to a drastic
decrease of the response and recovery times, from 132 and 179 s of the pure ZnO photodetectors to 5 and 9 s of these ultraporous NiO/ZnO networks. These findings demonstrate a superior architecture for the engineering of miniaturized wearable UV-photodetectors with largely suppressed dark-currents, fast photo-current dynamics and ultra-low power consumption.
6.5. References


Chapter Seven

Summary and Outlooks
In this thesis, the synthesis of ultraporous ZnO nanoparticle networks by flame spray pyrolysis (FSP) and their controlled direct deposition on electronic substrates for the fabrication of highly performing photodetectors were investigated. This is a significant improvement over established wide bandgap semiconductors that are produced by multi-step and wet-phase processes. In particular, novel flame-based methods used in this research for the synthesis of highly porous wide bandgap semiconductor (ZnO) films resulted in visible-blind UV photodetectors with significantly higher detecting performances compared to classical chemical and physical vapour deposition processes. The unique properties of these fully transparent ultraporous films are summarised in a new class of nanostructured photodetectors that combines several benefits of classical aerosol and wet-methods synthesis.

In this regard, the self-assembly of nanomaterials into three-dimensional hierarchical structures was explored in second chapter by modelling and simulating the dynamic behaviours of ultra-fine nanoparticles from freely diffusing particles to ballistically depositing ones. In order to determine a comprehensive mechanistic description of the nanoparticles accumulation and their self-assembly behaviours, the dynamics of unbound nanoparticles was investigated over three orders of magnitude in scale. As a result, a novel deposition mechanism and regime, named Randomly Oriented Ballistic Regime, was proposed in which successfully capture the full spectrum of size-dependent self-assembly dynamics. This enables quantitative predictions of micro- to nano-particle interaction with their surroundings providing a unified model of their diverging self-assembly mechanisms.

In the third chapter, a novel hierarchical morphology was presented for visible-blind UV photodetectors using ultraporous nanoparticle networks fabricated by flame spray pyrolysis synthesis and aerosol deposition of ZnO nanoparticle films. The
fabricated device exhibited an extremely high photo-to-dark-current ratio of $3.4 \times 10^5$ which was the highest ratio so far reported. This strong response is attributed to the unique morphology and composition of these films. In fact, the very high porosity of these nanoparticle networks facilitates the penetration of oxygen into the lowest nanoparticle layers and ensures the participation of the whole film in the photodetection mechanism. Decreasing the primary particle size below twice the ZnO Debye length and providing ultra- porous film morphology enhanced adsorption/desorption of oxygen molecules from the nanoparticle surface and facilitated the penetration of UV light into the lowest film layers resulting in an on/off switch behaviour to UV light exposure. These results show that electron-depleted particles are critical but not sufficient to obtain high photo- and low dark-currents at low UV light intensities.

In the fourth chapter, optimal grain boundary morphologies for these wide bandgap semiconductor nanoparticles were explored by structural engineering of the grain boundaries of ZnO nanoparticles in ultraporous nanoparticle networks. The photoelectrical response measurement revealed that thermally-induced necking of the grain boundaries is essential for efficient photodetection. The annealing temperature of $300 \ ^\circ\text{C}$ was presented as the optimal annealing temperature for ultraporous networks made by ZnO nanoparticle resulting in optimal photodetection performance. This optimal performance was attributed to two main mechanisms, namely the inhibition of the photocurrent in the as-prepared samples due to electron hopping at the grain boundaries, and the increase of the dark-current in the strongly annealed samples due to their closed-neck grain morphology.

In the fifth chapter, a nanoscale architecture was presented for band-selective UV photodetectors that featured excellent tunability, light detection performance and
miniaturization potential. The device layout relies on the 3D integration of ultraporous functional layers of ZnO, SiO$_2$ and TiO$_2$ nanoparticles. A band-selective photoresponse was obtained by exploiting the transmittance dielectric window (SiO$_2$ layer) between the indirect bandgap of TiO$_2$ and the sharp-edge of the direct bandgap of ZnO. Under the UV illumination, the top layer acts as a tunable long-pass filter absorbing light photons with the wavelength below 325 nm while photons with longer wavelength can reach the bottom ZnO layer. However, to electrically insulate the filter TiO$_2$ and photoresistor ZnO layer, a UV-transparent dielectric layer of SiO$_2$ nanoparticles was used as spacer. In fact, although the top TiO$_2$ layer is absorbing short wavelength photons but as it is not electrically connected to the device, no significant absorption peak was detected for the wavelength below 325 nm. The bandwidth of these photodetectors was easily tuned from 85 to 29 nm by increasing the TiO$_2$ film thickness. This solid-state architecture can be implemented with other top-bottom layer compositions such as GaAs (1.4 eV) - Si (1.1 eV), and SnO$_2$ (3.7 eV) - ZnS (3.54 eV) enabling the fabrication of portable band-selective photodetectors for the UV, visible and infrared spectrums.

In the sixth chapter, a highly performing nanoscale architecture was presented for the engineering of fast responding wide bandgap UV photodetectors. In order to improve the response speed of the device, a three-dimensional nanoscale heterojunction architecture was fabricated using p-type NiO clusters densely packed on the surface of an ultraporous network of electron-depleted n-type ZnO nanoparticles. The switching speed of the photocurrent dynamics was more than 20 times higher for three-dimensional network of nanoscale heterojunctions (3DNH) device (presented in chapter 6) compared to the other 3D structures (pure ZnO devices) presented in the thesis. This higher dynamic speed is attributed to the formation of nanoscale open-circuit heterojunctions. In fact, 3DNH structure caused fully depleted ZnO core and shorter hole
migration lengths, that results in significantly lower dark-currents and faster photo-response
dynamics compared to a pure ZnO device.

In summary, the findings of this thesis demonstrate a highly performing structure and a
flexible and scalable platform technology for the rapid low-cost fabrication and integration of
ultraviolet photodetectors in CMOS-compatible portable devices. This is a superior
architecture for the engineering of miniaturized wearable UV photodetectors with
largely suppressed dark-currents, fast photo-current dynamics and ultralow power
consumption. This concept can be applied to other highly performing semiconductors such
as wide bandgap for selective UV detection, fast photo-current dynamics and ultra-low power
consumption devices.
7.1. References


Chapter Eight

Future Work
This thesis has demonstrated superior structural design and a simple, low-cost CMOS-compatible process for the engineering of high-performance wearable devices using a rapid (≤ 100s) one-step synthesis and self-assembly of transparent ultra-porous films composed of electron-depleted crystalline ZnO nanoparticles. However, many opportunities for extending the scope of this thesis still remain. This section presents some of these directions.

8.1. Modelling

In the second chapter of this thesis, the dynamics of unbound nanoparticles is investigated over three orders of magnitude in scale aiming to determine a comprehensive mechanistic description of their accumulation and self-assembly behaviours. This enables quantitative predictions of micro- to nano-particle interaction with their surroundings providing a unified model of their diverging self-assembly mechanisms. However, modelling and simulation of light interaction with nanoparticles and its penetration through the film in both porous and dense structures would be significantly useful in terms of photodetection application.

8.2. Photoresponse Speed

Visible-blind ultraviolet photodetectors are an emerging technology for the development of wide bandgap optoelectronic devices with greatly reduced power consumption and size requirements. However, a standing challenge for many applications, including wearable monitors for skin cancer prevention, is to drastically improve the slow response time of these nanostructured devices. In this thesis, we demonstrate that nanoscale heterojunctions made of three-dimensionally co-located n- and p-type semiconductors enables more than 20 times faster photo-response dynamics while improving signal to noise ratio and detectivity. Despite this progress, the photoresponse speed of these visible-blind photodetectors is still too slow for many real-world uses.
8.3. Long Term Stability

The ultrahigh porosity of these ultraporous nanoparticle networks is beneficial to ensure penetration of oxygen and thus formation of electron-depleted ZnO particles in the whole film structure and in particular in the lowest layers adjacent to the electrodes. However, this high available surface area might have negative effect on the photodetector performance after storage in the air atmosphere for a long time. In fact, after a long time storage, a significant amount of water vapour might be absorbed on the surface and negatively impact the photodetection performance of the device. More investigation is required to find a way to passivate the surface of these ultraporous nanostructured devices to prevent reducing their performance with time passing.

8.4. Mechanical Stability

These ultra-porous nanoparticle coatings are usually characterized by a fragile structure that can be destroyed after a few cycle abrasion tests. This weak mechanical stability is attributed to ultrahigh porosity of these porous nanostructured devices. However, further studies are required to demonstrate a higher mechanical stability while preserving ultrahigh porosity of these nanostructures.

8.5. Flexibility

Development of flexible and stretchable sensing materials has recently shown the potential to offer additional opportunities to increase the selectivity of these nanostructured sensors. Here, in addition to the engineering of the ultraporous nanostructured devices, the realization of a flexible device can be very interesting and appealing. However, this requires further optimization and could be suited for a dedicated follow-up study. In that case, this research area can be greatly benefitting from the development of flexible and transferable electronics.
Appendix A

Ultra-Porous Nanoparticle Networks: A Biomimetic Coating Morphology for Enhanced Cellular Response and Infiltration
Publication relevant to this chapter:


Abstract

Orthopedic treatments are amongst the most common cause of surgery and are responsible for a large share of global healthcare expenditures. Engineering materials that can hasten bone integration will improve the quality of life of millions of patients per year and reduce associated medical costs. Here, we present a novel hierarchical biomimetic coating that mimics the inorganic constituent of mammalian bones with the aim of improving osseointegration of metallic implants. We exploit the thermally-driven self-organization of metastable core-shell nanoparticles during their aerosol self-assembly to rapidly fabricate robust, ultra-porous nanoparticle networks (UNN) of crystalline hydroxyapatite (HAp). Comparative analysis of the response of osteoblast cells to the ultra-porous nanostructured HAp surfaces to that of spin coated HAp surfaces revealed superior osseointegrative properties of the UNN coatings with significant cell and filopodia infiltration. This flexible synthesis approach to engineering UNN HAp coatings on titanium provides a platform technology to study the bone-implant interface for improved osseointegration and osteoconduction.
A.1 Introduction

The rapid rise of nanofabrication technologies is enabling the engineering of hierarchical materials and surfaces that mimic the complex morphology and composition of biological tissue.\textsuperscript{1-2} This is critical to bone tissue engineering where the interaction between the synthetic implant and bone is determined by the implant’s surface properties. Bone injuries account for a large proportion of surgeries and healthcare expenditures.\textsuperscript{2-3} These procedures often require the permanent implantation of synthetic structures such as prostheses and grafts in the bone. The success of these implants is determined by their osseointegration with the surrounding bone tissue. This long-term integration requires materials stability and careful engineering of biomimetic interfaces. This is challenging as mammalian bone is a composite material composed of hierarchically assembled mineralised collagen together with a small portion of non-collagenous protein and lipids. This assembly of mineralised collagen fibrils can lead to varied bone structure and morphologies depending on its location and function. The most biologically active section of mammalian bones, namely the trabecular region, features a honey-comb type spatial arrangement of mineralised collagen fibrils\textsuperscript{4-5} with a porosity range of 30-95\%\textsuperscript{6-7}.

Currently, much effort is focused on the nanofabrication of enhanced HAp coatings that may ultimately improve the integration of orthopaedic implants. Synthesis of nanostructured HAp coatings is currently pursued by numerous methods including plasma spraying,\textsuperscript{8} sol-gel\textsuperscript{9,10} and magnetron sputtering\textsuperscript{11}. Plasma spraying is the gold standard for the commercial production of implant coatings. Notwithstanding its numerous merits, this approach results in dense films with limited chemical homogeneity and mechanical properties\textsuperscript{12}. These two-dimensional plasma-sprayed interfaces do not adequately mimic the highly porous three-dimensional structure of bone tissue and may result in shorter in vivo residence times compared with a coating with superior biomimicry.\textsuperscript{13} In other studies,\textsuperscript{14,10} porous HAp
coatings (15.5-75% porosity) were fabricated using micro-porous biphasic calcium phosphate (BCP) granules mixed with organic pore makers and sol-gel. The resulting calcium phosphate was amorphous and calcination at 600 °C to 1050 °C was required for crystallization.

Thermo- and electrophoretically-driven deposition of nanoparticle aerosols has been, recently, demonstrated as a flexible tool for the synthesis of three-dimensional morphologies with excellent optoelectronic and chemical properties. This gas-phase approach shares some of the advantages of plasma-spraying such as scalability and high deposition rates while enabling fabrication of up to 98% porous morphologies and more accurate control of the key structural features. However, previous attempts to produce crystalline HAp aerosols by high-throughput spray flames have led to amorphous compounds. Furthermore, these ultra-porous nanoparticle coatings are usually characterized by a fragile structure that is easily destroyed by capillary forces and are not suitable for biological applications. Enhancing their mechanical stability for operation in liquid environments has been only partially successful.

Here, we demonstrate the synthesis of a three-dimensional nanocrystalline HAp morphology that mimics the high porosity and micro-nano structural hierarchy of the trabecular bone region. Ultra-porous nanoparticle networks of crystalline HAp are fabricated in one-step by rapid self-assembly of meta-stable core-shell nanoparticle aerosols and in-situ thermally-induced self-organization. This results in ultra-porous and micro-rough films composed of strongly sintered nanostructures that withstand capillary forces and handling. Up to five to ten times denser morphologies are obtained as a comparative structure by classical spin-coating of the same flame-made nanoparticles. The performance of this synthetic UNN morphology is assessed by primary osteoblast cultures revealing unique cellular response and infiltration. We believe that this rapid and scalable synthesis route
offers a powerful platform for the large-scale and low-cost fabrication of ultraporous inorganic coatings with application extending from regenerative medicine to implantable devices.

**A.2 Experimental**

**A.2.1 Precursor Preparation**

Flame spray pyrolysis (FSP) was used for the synthesis and direct deposition of Hydroxyapatite (HAp) nanoparticles. Nanoparticles were prepared as follows: Calcium Naphthenate (Sigma Aldrich, 2(C₁₁H₇O₂)Ca, ca. 35% in mineral spirits (4% Ca)) and Tributyl phosphate (Sigma Aldrich, C₁₂H₂₇O₄P) were mixed together at a Ca/P molar ratio of 1.667, matching the natural HAp composition. The solution was supplied at a rate of 5 mL min⁻¹ through a needle and dispersed into a fine spray with an oxygen dispersion of 5 L min⁻¹. This spray was ignited by a supporting annular premixed methane/oxygen flame (CH₄ = 1.2 L min⁻¹, O₂ = 3.2 L min⁻¹).

**A.2.2 HAp Coating Synthesis**

Nanoparticles were deposited by orthogonal impingement of hot aerosol generated by FSP on the substrate placed at 6 cm height above the burner (HAB). The substrates were 1 mm thick Titanium alloy (Ti-6Al-4V, grade 5, Revolution Advanced Metals & Materials) disks with a diameter of 15 mm. Before nanoparticles deposition, the disk surface was cleaned in an ultrasonic bath with ethanol for 20 min. The aerosol temperature (Tᵢ) on the exposed substrate surface was measured by digital thermometer (RS, model #206-3738). Dense morphologies were obtained by spin-coating of the same flame-made HAp nanoparticles collected on glass-fiber filters placed at 50 cm HAB. A quantity of 1 mL pure water and acetyl acetone with volume ratio of 10:1 was added to the 0.3 g of HAp particles with 2 droplets of Triton X-100 as a surfactant. A spin coater (VTC-100 Vacuum Spin Coater, MTI
Corporation) was used at a speed of 1000 rpm for 60 s to spin-coat the above solution on the Ti disk. These films were sintered at 850 °C for 1 h to remove all impurities and achieve a 100% pure HAp. The morphology and patterning characteristics of the deposited particles and films were investigated by a Hitachi H7100FA transmission electron microscope (TEM) at 100kV and an analytical scanning electron microscopy (Zeiss Ultraplus FESEM) at 3kV. The crystal phases, size (d_{XRD}) and surface compositions were analyzed by X-ray diffraction with a D_2 Phaser (Bruker, U.S.A) and Fourier transform infrared spectroscopy (FTIR-ATR, Bruker-Alpha, U.S.A). The average crystal sizes of the HAp and calcium oxide phases were computed from the XRD peaks in the 2θ range of 30 - 35° and 35 - 40°, respectively. The HAp specific surface area (SSA) was measured by N₂ adsorption/desorption at -196.15 °C (Micromeritics, TriStar II, U.S.A), after degassing at 300 °C for 4 h. The HAp/Ti alloy interface strength was investigated under the ASTM D4060-14 standard with a Taber abrasion (Dongguan Jianqiao Testing Equipment Co., LTD, Model JQ-802A). The test was performed under two-body (high-stress) condition using a pair of abrading wheels 52 mm in diameter at 250 g load. The morphology of all coatings was investigated with a Zeiss Ultraplus FE-SEM at 3 kV and white light interferometer (WLI) (Veeco, Wyko NT9100, U.S.A). High temperature differential scanning calorimetry (DSC) analysis was conducted from 30 to 1000 °C at a 10 °C min⁻¹ ramp under nitrogen atmosphere in a STA 8000 (Perkin Elmer, U.S.A).

### A.2.3 Cell Culture

This procedure was approved by the Animal Research Ethics Committee of Australian National University (Reference Nr. A2013/41). Primary osteoblasts were isolated from femur bone of adult Swiss mice according to the ANU animal ethics guidelines. The femur was cleaned thoroughly, minced and digested using collagenase (Sigma Aldrich) at a concentration of 10 mg mL⁻¹ at 37 °C for 20 min. The digested mass was washed with phosphate buffered saline (PBS) and plated on tissue culture plates (TCP) and maintained
with Dulbecco's Modified Eagle's medium (DMEM - HyClone) containing 10% foetal bovine serum (FBS, Gibco) and 1% penicillin streptomycin antibiotics (HyClone). Confluent cultures were mechanically detached using cell scrapers (HyClone) and seeded at a density of 10,000 cells per sample (HAp coating on Ti substrate) in 24 well plates.

A.2.4 Biological SEM sample preparation

Cell morphology was assessed after 14 days of culture. Culture medium was replaced with 3% glutaraldehyde and incubated for 2 h at room temperature for cell fixation. After fixation, the wells were washed with deionized water. The samples were then dehydrated in a series of graded ethanol solutions with final dehydration in 100% ethanol. The samples were then treated with hexamethyldisilazane (HMDS) and allowed to air dry.

A.2.5 Immunofluorescence analysis

Isolated primary murine bone cells cultures on the HAp coated samples were washed with PBS, and fixed with 4% paraformaldehyde (Sigma-Aldrich) for 10 min. Cells were permeabilized with 0.1% Triton X-100 (Sigma-Aldrich), blocked for non-specific staining using 3% bovine serum albumin (BSA, Sigma) and then immunostained with Phalloidin-TRITC (Millipore) and anti-osteocalcin antibody (R&D systems) for 1 h at room temperature. Thereafter, they were revealed with anti-species-specific Alexa fluor 488 (Life Technologies). The samples were mounted using anti-quenching mounting medium (Vectashield, Vector laboratories) and observed under a fluorescence microscope for imaging (Olympus IX 71).

A.3 Results and Discussion

A.3.1 Flame Synthesis of Core-Shell Nanoparticle

Highly concentrated aerosols of hydroxyapatite (HAp) nanoparticles were produced by combustion of calcium naphthenate in tributyl phosphate solutions (Figure A.1). Previous
attempts to produce crystalline hydroxyapatite nanoparticles by highly turbulent and scalable spray flames\textsuperscript{26} have usually resulted in nearly completely amorphous Ca/P compounds\textsuperscript{24}. To overcome this limitation, here, a custom-built atomizer design (Figure A.1) has been utilized that enables higher atomization pressure than previously investigated (\(\approx 1.5\) bar)\textsuperscript{24}.

\textbf{Figure A.1.} Schematics of (a) flame spray pyrolysis synthesis and (b) aerosol self-assembly of three dimensional ultra-porous films made of HAp nanoparticles at 6 cm height above the burner (HAB). The produced HAp nanoparticles have core-shell structure after nucleation while aerosol deposition on hot Ti-alloy leads to a pure HAp phase with no detectable trace of lime and other impurities.

Figure A.2 shows the effect of the atomization pressure on the nanoparticle size and morphology. The atomization pressure was increased from 2 to 9 bar while maintaining a constant flow rate by radially decreasing the annular cross-section of the atomization gas (O\textsubscript{2}) outlet. For all conditions, transmission electrons microscopy (TEM) analysis of the nanoparticle aerosols revealed a fraction of spherical core-shell nanoparticles (Figure A.2a-d, insets). These particles were characterized by bright cores and dark shells (Figure A.2a-d,
Figure A.1) indicating a phase segregation. X-ray diffraction (XRD) revealed a crystalline structural (Figure A.3a) composed of two phases matching the peaks of hydroxyapatite (Ca$_5$(PO$_4$)$_3$OH) and calcium oxide (CaO).

![Figure A.2](image)

**Figure A.2.** Representative transmission electron microscopy images of the flame-made HAp nanoparticle aerosols at an atomization pressure of (a) 2 bar, (b) 3 bar, (c) 5 bar and (d) 7 bar.

At low atomization pressure (2 bar), some trace amounts of amorphous materials and/or very small crystals (< 3 nm) were indicated by an amorphous hump centered at a $\theta$ of 31° (Figure A.3a). The intensity of the latter decreased with increasing atomization pressure and above 5 bars highly crystalline powders were obtained. Similarly, the content of the calcium oxide impurities decreased significantly from 12% to 6% with increasing atomization pressure from 2 to 9 bar (Figure A.3a and Figure A.3b). These results were confirmed by FTIR analysis (Figure A.4). Bands commonly assigned to phosphates were observable in all samples at ~ 563, 604, 962, 1029 and 1087 cm$^{-1}$.27
Figure A.3. (a) Composition of the as-prepared HAp nanoparticles as a function of the atomization pressure by X-ray diffraction. (b) The particle size ($d_{\text{BET}}$), crystal size ($d_{\text{XRD}}$) and lime content of HAp nanoparticles collected from filter produced at atomization pressure from 2 up to 9 bar.

The bands at 962, 1029 and 1087 cm$^{-1}$ are attributed to the characteristic symmetric stretching of the phosphate ($\text{PO}_4^{3-}$) in HAp while those at 563 and 604 cm$^{-1}$ are attributed to its bending mode. A small hump centered around a wavenumber of ~875 cm$^{-1}$ suggests partial replacement of $\text{PO}_4^{3-}$ in HAp lattice by carbonate. The incorporation of carbonate is common during the formation of biological apatite.

Figure A.4. Composition of the as-prepared HAp nanoparticles as a function of the atomization pressure by Fourier transform infrared spectroscopy.
Following the XRD phase composition, the nanoparticles’ dark shells (Figure A.2a-d, Figure A.1) are attributed to the higher mass density of the CaO phase while the bright cores are associated with the hydroxyapatite phase in line with previous reports on segregated multi-components nanoparticles. This is in good agreement with the high fraction of single-core structures observed at high atomization pressures and higher fraction of multi-core particles at low atomization pressures (Figure A.2a-d, insets).

**Figure A.5.** Representative TEM images of flame-made HAp nanoparticles upon sintering for 1 h at (a) 550 °C, (b) 850 °C and (c) 1050 °C.

In fact, the HAp crystal size increased from 9 nm to 17.5 nm and the calcium oxide crystal size increased from 19 nm to 21.5 nm with increasing atomization pressure from 2 to 9 bar (Figure A.3b). The high amount of crystalline HAp, obtained here, is attributed to high partial water pressure obtained by oxidation of the precursor solution. Its segregation in the particle core is tentatively attributed to the rapid heating and high temperatures experienced by the particles during their residence time in the flame that may lead to dehydroxylation of their surface. Higher atomization pressures are expected to result in smaller droplets and a shorter high temperature residence. This could decrease surface dehydroxylation and promote the formation of larger crystalline nanoparticle cores. Increasing the moderate temperature residence time (e.g. with an hot wall reactor) of the optimally synthesized core-shell nanoparticles at an atomization pressure of 7 bar is expected to eventually lead to fully crystalline single-phase HAp nanoparticles. This is in good agreement with the TEM analysis.
Figure A.2d, inset) showing an increase in HAp core with increasing atomization pressure from 2 to 7 bar. As a result, a pressure of 7 bar was chosen as the optimal atomization condition as it led to 94wt% of crystalline HAp phase and warranted stable spray flame conditions.

Figure A.6. The (a) XRD patterns and b) particle size ($d_{\text{BET}}$), crystal size ($d_{\text{XRD}}$) and CaO content of HAp nanoparticles as a function of the sintering temperature.

The synthesis mechanism of these core-shell nanoparticles is further analyzed below along their process parameters and thermodynamic stability. The sintering temperature had a significant impact on the particle morphology and composition (Figure A.5a-c). Already at 550 °C, formation of hard agglomerates was observed and the as-prepared core-shell morphology was replaced by a uniform composition (Figure A.5a-c). This is in contrast with the high thermal stability of crystalline HAp and suggests that the as-prepared nanoparticles are meta-stable nanocomposites captured due to the strong quenching in the flame reactors. In fact, the particle diameter ($d_{\text{BET}}$) increased from 35 to 210 nm with increasing sintering temperature from as-prepared to 1050 °C (Figure A.5c and Figure A.6b, red circles). Simultaneously, the HAp and calcium oxide crystal sizes increased from 17 and 20 nm to 22 and 30 nm, respectively, with increasing sintering temperature from as-prepared to 750 °C (Figure A.6b). This also led to a rapid drop in the CaO content from 7 wt% to less than 1 wt%
Sintering temperatures above 850 ºC led to a pure HAp phase with no detectable trace of calcium oxide and other impurities (Figure A.6a).

**Figure A.6b.** Figure A.7. Differential scanning calorimetry (DSC) of the HAp nanoparticles collected from filter at an atomization pressure of 7 bar reveals no crystallization and decomposition up to 1000 ºC.

These nanoparticle aerosols were further investigated by DSC and FTIR analysis. The former (Figure A.7) indicates that no amorphous to crystalline phase transformation and decomposition occurs up to 1000 ºC. This is in very good agreement with previous studies\(^{23,34}\) and the very low content of calcium oxide impurities (≤ 6 wt%) of the as-prepared samples. The small nicks observed below 700 ºC and close to 900 ºC are within instrument accuracy. Figure A.8 shows the FTIR analysis of the HAp particles as a function of the sintering temperatures. Compared to the as-prepared particles (Figure A.4), the sintered ones showed characteristics of larger HAp crystals with well distinguishable FTIR peaks. A major difference notable in the sintered samples was the presence of OH band at 630 cm\(^{-1}\). In contrast, the FTIR spectra of the (as-prepared) particles containing CaO did not have this OH band. This is commonly attributed to the stretching vibration mode of lattice OH.\(^{27}\) Its post-sintering appearance is attributed to the transformation of the calcium oxide shell (CaO) into stoichiometric HAp (Ca\(_5\)(PO\(_4\))\(_3\)OH) in good agreement with the XRD analysis (Figure A.6a).
A.3.2 Rapid Nanofabrication of Biomimetic and Robust UNN

Ultra-porous nanoparticle networks were rapidly (< 30 s) fabricated by hierarchical self-assembly of these aerosols on Ti-alloys, commercially utilized for bone implants. The substrates were orthogonally aligned to the spray flame (Figure A.1) and at 6 cm height above the burner head resulting in a surface temperature of 1000 ± 10 °C. This temperature is lower than that commonly utilized for commercial plasma spraying coating (> 1200 °C)\textsuperscript{35-36} and did not have any detectable effect on the substrate.

Figure A.9a shows a typical UNN film obtained by 10 s exposure of the substrate to the hot nanoparticle aerosols. The resulting film had a three-dimensional micro- and nano-scale surface roughness (Figure A.9a) characterized by large micro-scale pores surrounded by dense agglomerated regions. Analysis of the film cross-sections (Figure A.9b) revealed a homogeneous morphology over several hundred micrometres with a thickness of 19 µm and variations in the order of ± 2 µm. The substrate-film interface was continuous with no visible cracks and delamination suggesting a robust bond between the film and the Ti-alloy. An initial analysis of the bonding strength of the HAp/Ti interface was performed by 10 cycle abrasion tests with a Taber abrasion instrument (Dongguan Jianqiao Testing Equipment Co.,
LTD, Model JQ-802A) revealing a promising mechanical stability. In contrast to previous studies on UNN, the HAp films survived the capillary forces during immersion in simulated body fluid\textsuperscript{18}. Further studies are required to provide a full characterization of the structural properties of these coatings.

**Figure A.9.** (a) Representative SEM images of an exemplary ultra-porous HAp nanoparticle network (UNN) self-assembled for 10 s on the surface of a Ti-alloy substrate. Cross-section SEM analyses of the (b,c) UNN coatings obtained at 10 and 20 s aerosol-deposition time. The cross-section SEM images in panel b and c are at the same scale.

Furthermore, increasing the deposition time from 10 s to 20 s, increased the film thickness from 19 to 36 µm (Figure A.9b-c). This results in a very high film growth rate of 1.8 µm s\textsuperscript{-1}. Constant, but significantly lower film growth rates of 7 nm s\textsuperscript{-1} have been reported also for deposition of flame-made TiO\textsubscript{2}\textsuperscript{37} nanoparticles and are in line with that expected for thermophoretically-driven deposition\textsuperscript{38}. The increase in surface roughness with increasing thickness is in good agreement with recent models of the self-assembly of nanoparticles from the gas phase onto solids\textsuperscript{39}. The latter predicts that in the diffusion regime the density of first nanoparticle layers are up to 5 times higher than that obtained far from the surface where micro-scale branch-like agglomerated are formed\textsuperscript{39}.

The film porosity was computed from the SEM cross-sectional thickness and deposited film mass density (Figure A.10). The latter increased from 0.54 to 0.99 mg cm\textsuperscript{-2} with
increasing deposition time from 5 to 25 s. It is important to notice that during the first 10 s the surface of the substrate heats rapidly from room temperature to ca. 1000 ºC. This decreases the thermophoretically driven particle flux from 0.1077 mg cm\(^{-2}\) s\(^{-1}\) upon 5 s to 0.0083 mg cm\(^{-2}\) s\(^{-1}\) upon 15 s. The latter deposition rate remained constant with no variations up to the longest deposition time (25 s) investigated here. In contrast to previous studies,\(^{18,25}\) the porosity increased from 81% to 93% with increasing deposition time from 5 to 25 s (Figure A.10). These porosities are significantly lower than that previously achieved by low (98%)\(^{18,40}\) and moderate temperature (95%)\(^{25}\) deposition of flame-made metal-oxide nanoparticles. This is attributed to the low thermodynamic stability of the core-shell nanoparticles undergoing in-situ sintering on the substrates during deposition from the gas-phase.

![Figure A.10.](image)

*Figure A.10. (a) Visible film thickness and porosity, (b) XRD patterns and (c) FTIR spectra of the HAp coatings as a function of the aerosol-deposition time.*

The UNN self-assembly dynamics was investigated as a function of the deposition time by TEM (Figure A.11), XRD (Figure A.12a) and FTIR analysis (Figure A.12b). All the as-prepared coatings had a pure HAp composition (Figure A.12) with no trace of CaO and/or other amorphous impurities. The relative intensity of the HAp peaks increased rapidly with increasing time in line with the rapid increase in film mass density. The HAp crystal size increased from 40 to 67 nm with increasing deposition time from 5 to 25 s. This is up to 4
times larger than the crystal size of the particles collected from the aerosols at the same atomization pressure (Figure A.3b). It confirms that significant densification of the coatings is due to in-situ sintering during deposition. The higher porosity of the thicker films is attributed to the self-assembly dynamics leading both to less particle neighbors and larger inter-branch pore as the film thickness increases\textsuperscript{39}.

\textbf{Figure A.11.} TEM images of the particles collected from (a) the filter and (b) removed from the substrates after 5 s aerosol-deposition.

TEM analysis of the HAp particles collected from the substrates (Figure A.11b) revealed that all the core-shell structure had undergone a phase transformation resulting in a homogeneous HAp composition similar to that obtained upon sintering at 800 °C. The purity of the as-prepared coatings was assessed by FTIR analysis (Figure A.12b) revealing a pure inorganic composition. The FTIR main peaks at 550 - 606 cm\textsuperscript{-1} and 960 - 1080 cm\textsuperscript{-1} were attributed to the phosphate bonding and stretching, respectively. This is in line with previous studies and further confirms the achievement of a highly pure HAp phase. This is particularly important as the presence of CaO in HAp ceramics, designed for medical applications, is not desirable due to the conversion of CaO into Ca(OH)\textsubscript{2}\textsuperscript{33}. This results in gradual tension and formation of hairline cracks in the ceramic material\textsuperscript{41} undermining its mechanical properties.
A.3.3 Cellular adhesion and Infiltration

Promoting cellular adhesion and infiltration into the ultra-porous HAp coatings are recognized as the first key steps for improving the osseointegration on metallic implants. Here, the biological performance of these three-dimensional UNN morphologies was explored using primary Swiss mice osteoblasts as a representative system for the interface of bone implants. To this aim, murine femur cells with osteocalcin producing osteoblasts were cultured in triplicate on HAp coated and spin coated Titanium alloys. Figure A.13 shows magnifications of SEM micrographs depicting cell-cell and cell-coating interactions after 14 days on a UNN and a spin-coated surface. The osteoblast were firmly attached to the ultra-porous coating (Figure A.13b) and responded to its morphology by formation of nano-scale filopodia of less than 100 nm in diameter (Figure A.13c-d). Filopodia are cytoskeletal projections of the cell membrane that probe the microenvironment and are known as a mode of recognition and interaction for the cells\textsuperscript{42}. The latter infiltrated the coatings through its macro- and nano-pores. Here, a unique extensive penetration of nano-scale filopodia and cell infiltration into the inorganic coatings was observed. Previous studies\textsuperscript{43-44} have reported that highly branched cellular morphologies on Ti implant surfaces resulted in higher

\textbf{Figure A.12.} (a) XRD patterns and (b) FTIR spectra of the HAp coatings as a function of the aerosol-deposition time.
mineralization with no significant differences in cell viability when compared with control substrate. Thus, this cellular response to our UNN indicates that our structures have higher osseointegration and in turn higher osteoconductivity than current plasma spraying technologies.

**Figure A.13.** Representative SEM images of (a) the flame-made UNN and (b) dense spin-coated surface. False colored SEM micrographs of the osteoblast growth after 14 days on the surface of the (b-d) UNN and (f-h) dense spin-coated surfaces. On the ultra-porous nanoparticle network surface, the cell-cell and cell-materials interactions resulted in a visible attachment of osteoblasts to the coating surface (b-c). Magnifications show (d) the formation of nano-scale filopodia. In stark contrast, no cellular infiltration and filopodia formation was observed on the dense spin-coated surfaces (f-h).

In stark contrast, the dense morphology obtained by spin-coating of the same flame-made nanoparticles resulted in poor cell adhesion and infiltration. These spin-coated surfaces were
characterized by a smoother morphology having similar nano-scale texture (Figure A.13e) to the UNN coatings (Figure A.13a) but lacking the hierarchical micro-structure of the latter (Figure A.13a). SEM analysis of these spin-coated samples revealed that most of the cells failed to adhere to the nano-textured surface (Figure A.13f-h). Furthermore, no cellular infiltration and filopodia formation was observed. This cellular response is similar to that obtained with other approaches such as plasma spray, sol-gel and magnetron sputtering that have been extensively used to fabricate nanostructured HA surfaces. These dense morphologies have not resulted in cellular infiltration inside the coating structure and only seldom in micro-scale filopodia formation. This is attributed to their micro-scale flat surface that do not may also result in poor cell adhesion.

Figure A.14. Immunostaining images of (a,e) Nuclei, (b,f) Osteocalcin and (c,g) F-Actin proteins on the surface of (a-d) the UNN self-assembled with an aerosol-deposition time of 20 s and (e-h) spin-coated sample. Topographical merge of the Nuclei, F-Actin and Osteocalcin distribution on (d) flame-made and (h) spin-coated samples.

The very positive response of the osteoblasts to the UNN morphology was confirmed by immunostaining analysis of two key cytoskeletal markers, F-Actin (Figure A.14a) and Osteocalcin (Figure A.14b). Osteocalcin is a non-collagenous protein that is known to be
secreted only by functional bone forming cells, osteoblasts. F-Actin is a linear polymer microfilament that is essential for cellular functions such as mobility and contraction during division. The expression of cytoplasmic F-Actin and secreted osteocalcin (Figure A.14c) by bone cells on these ultra-porous and micro-rough morphologies suggest that its three-dimensional structure and composition positively influence the key cellular processes such as adhesion and protein expression. Both are required for osteoconduction and long-term osseointegration of bone implants.

![Ultra-Porous NPs Network vs Spin-Coated](image)

Figure A.15. White Light Interferometry (WLI) micrographs of (a) ultra-porous HAp coating with 25 seconds deposition time compared to (b) spin-coated films.

In natural bone, the structure of the extracellular matrix and function of cells are regulated by macro- and nano-scale cues provided by both the stroma and parenchyma. These include a pure composition, micro- and nano-scale pore sizes and, in the most active regions of the bone, up to 93% porosity that are all well matched by these flame-made structures. The pore size distribution of the flame-made coatings was investigated by white light interferometry (WLI) and shows that the pore size reaches up to hundreds of micrometer (Figure A.15a). Although this is still lower than that of cancellous bone, it is a significant improvement over plasma-sprayed coatings and spin-coating (Figure A.15b), where the coatings feature flat surfaces or sub-micrometer pore size distributions. These promising results substantiated by
the excellent morphological response of the osteoblasts suggest that the UNN morphology is highly desirable for cellular growth.\textsuperscript{50-51}

A.4. Conclusions

In summary, we have presented a biomimetic, fully inorganic material structure for tissue engineering that can be utilized to study the early events of osseointegration and osteoconduction. Ultra-porous nanoparticle networks of nanocrystalline hydroxyapatite with up to 93\% porosity were fabricated by a scalable and low-cost approach that enables the ultra-rapid coating of commercial grade implants. The response of bone cells to these morphologies was assessed by primary osteoblast cultures. It was found that the nano- and micro-scale hierarchical structures of the UNN surface demonstrated superior cell infiltration and nanoscale cell-cell and cell-biomaterial interaction that can result in enhanced osseointegration. These promising results demonstrate the potential of this scalable synthetic platform and structural design for the fabrication of biomaterials for bone tissue engineering with application extending from osseointegration of implantable devices to regenerative medicine.
A.5. References

1. Liu, K.; Yu, D.; Cho, Y.-Y.; Bode, A. M.; Ma, W.; Yao, K.; Li, S.; Li, J.; Bowden, G. T.; Dong, Z.; Dong, Z., Sunlight UV-Induced Skin Cancer Relies upon Activation of the p38α Signaling Pathway. *Cancer Res.* **2013**, *73*, 2181-2188.


Appendix B

Hierarchically-Driven Cell-Cell Communication and Coating In-Growth
Abstract
Understanding the mechanisms underlying the cellular response to a micro-environment is critical to the design of programmable biomaterials for tissue engineering and regenerative medicine. State-of-the-art nano-material synthesis and self-assembly processes can produce complex structures that mimic surface properties, composition and partially the morphology of biological systems. However, determining key structural properties that control cell attachment and proliferation has been challenging, and contradictory results are currently reported for similarly nano-structured materials. Here, we investigate osteogenesis, the process of laying down new bone material by osteoblast cells, on bio-inert substrates as an exemplary implantable organic-inorganic interface with the second highest frequency of surgical applications. We identify critical multi-scale features that drastically enhance the cellular response to the same nano-texture. It is observed that ultra-porous hierarchical morphologies promote early-stage osteo-induction as indicated by extensive coating ingrowth and nano-filopodia formation. We propose that cellular integration is mediated by two-way recognition of specific nano- and micro-topographical cues between the host tissue and micro-environment providing a set of determinant features for engineering of enhanced third-generation biomaterials.
B.1 Introduction

Nano-texturing has been successfully applied to numerous biological interfaces demonstrating the potential to significantly improve the interaction of bio-inert materials with a surrounding cellular matrix. Amongst surgically implantable structures, the surface of bone implants has been extensively investigated due to its vast social and economic impact potential. Clinical trials have recently revealed that the most frequent cause for implant failure is insufficient early-stage bone formation at the biomaterial-tissue interface after implantation. This is driving multi-disciplinary research efforts to elucidate the response of bone cells to biocompatible surfaces and accelerate early-stage bone healing.

In an attempt to improve osteo-integration, hydroxyapatite (HAp), the main inorganic component of mammalian bones, is routinely applied as thin nanocystalline coating on implantable bio-inert supports such as a titanium-based alloys. Plasma spraying has emerged as the gold standard for commercial HAp coatings due to its scalability and reliability. However, the integration of plasma-sprayed implants into the bone parenchyma is insufficient for long-term use. This is mainly attributed to their dense morphology that is impenetrable to osteoblasts resulting in insufficient adhesion. Although it is broadly recognized that the coating’s morphology has significant impact on the cellular response, key structural parameters to promote the sought early-stage osteo-induction and long-term bonding strength have not yet been determined.

Several processes such as plasma spraying, sol-gel and electron beam sputtering have been successfully applied to the nano-fabrication of synthetic HAp and other biocompatible calcium phosphate-based films. Sol-gel impregnation, for example, results in mesoporous films that may enable coating in-growth, and thus
provide better long-term mechanical stability. However, mesoporous films have not demonstrated significant improvements over plasma spraying. A promising alternative morphology is offered by the self-assembly of nanoparticle aerosols into ultra-porous, hierarchical micro-nano structures. This is a flexible one-step process that can be easily scaled-up utilizing state-of-the-art flame synthesis reactors as low-cost and continuous nanoparticle aerosol sources.

Aerosol self-assembled coatings are characterized by up to 98% porous morphologies composed of mesoporous nanoparticle agglomerates separated by micro-sized pores. Furthermore, nanoparticle aerosol self-assembly allows nano-scale control over the key structural properties such as thickness, porosity and composition. This enables a systematic investigation and optimization of the coating properties. A major challenge to the application of aerosol self-assembly to bone tissue regeneration is the poor adhesion and cohesion of the resulting nanoparticle network. In fact, the fragile nanoparticle ultra-porous structures obtained by aerosol deposition results in weak van der Waals adhesion and rapidly disintegrates even upon immersion in liquid solutions. However, partial sintering of the depositing nanoparticles during coating self-assembly has shown to significantly increase the resulting mechanical stability at the cost of a small porosity reduction.

Here, we demonstrate the feasibility of controlling the response of cells to a surface by presenting a hierarchical nano-textured micro-environment. We synthesize robust, ultra-porous, nano-crystalline HAp coatings by high temperature aerosol self-assembly. Up to five times denser coatings are obtained as a comparative morphology by spin-coating of the same flame-made nanoparticles. The impact of the coating’s key structural properties is systematically investigated by topographical mapping of the chemical and mechanical responses of osteoblast cells to gradually more
hierarchical micro-environments. These findings provide new key insights and a flexible synthesis platform for the design and fabrication of enhanced biomaterials for regenerative medicine, implantable electronics and biological interfaces.

B.2 Experimental

B.2.1 Nanoparticle Aerosol Generation

Flame spray pyrolysis was used for the synthesis and direct deposition of Hydroxyapatite (HAp) nanoparticles. Nanoparticles were prepared as follows: Calcium Naphthenate (Sigma Aldrich, approx. 35% in mineral spirits (4% Ca)) and Tributyl phosphate (Sigma Aldrich, C_{12}H_{27}O_{4}P) were mixed together at a Ca/P molar ratio of 1.677, similar to bone composition. The mixture was stirred robustly for 30 min. The solution was supplied at a rate of 5 mL.min\(^{-1}\) through a custom-built atomizer and dispersed into a fine spray with 5 L.min\(^{-1}\) oxygen at a pressure drop of 5 bar. The spray was ignited by a supporting ring-shaped premixed methane/oxygen flame (CH\(_4\)=1.2 L.min\(^{-1}\), O\(_2\)=2 L.min\(^{-1}\)).

B.2.2 HAp Coating Synthesis

Nanoparticles were deposited by orthogonal impingement of hot aerosol generated by FSP on the substrate placed at 6 cm height above the burner (HAB). The substrates were 1 mm thick Titanium alloy (Ti-6Al-4V, grade 5, Revolution Advanced Metals & Materials) disks with a diameter of 15 mm. Before nanoparticles deposition, the disk surface was cleaned in an ultrasonic bath with ethanol for 20 min. The aerosol temperature (T\(_F\)) on the exposed substrate surface was measured by digital thermometer (RS, model #206-3738). Dense morphologies were obtained by spin-coating of the same flame-made HAp nanoparticles collected on glass-fiber filters placed at 50 cm HAB. A quantity of 1 mL pure water and acetyl acetone with volume ratio of 10:1 was added to the 0.3 g of HAp particles with 2
droplets of Triton X-100 as a surfactant. A spin coater (VTC-100 Vacuum Spin Coater, MTI Corporation) was used at a speed of 1000 rpm for 60 s to spin-coat the above solution on the Ti disk. These films were sintered at 850 °C for 1 h to remove all impurities and achieve a 100% pure HAp. The morphology and patterning characteristics of the deposited particles and films were investigated by a Hitachi H7100FA transmission electron microscope (TEM) at 100kV and an analytical scanning electron microscopy (Zeiss Ultraplus FESEM) at 3kV. The crystal phases, size (dXRD) and surface compositions were analyzed by X-ray diffraction with a D2 Phaser (Bruker, U.S.A) and Fourier transform infrared spectroscopy (FTIR-ATR, Bruker-Alpha, U.S.A). The average crystal sizes of the HAp and calcium oxide phases were computed form the XRD peaks in the 20 range of 30 - 35º and 35 - 40º, respectively. The HAp specific surface area (SSA) was measured by N2 adsorption/desorption at -196.15 °C (Micromeritics, TriStar II, U.S.A), after degassing at 300 °C for 4 h. The HAp/Ti alloy interface strength was investigated under the ASTM D4060-14 standard with a Taber abrasion (Dongguan Jianqiao Testing Equipment Co., LTD, Model JQ-802A). The test was performed under two-body (high-stress) condition using a pair of abrading wheels 52 mm in diameter at 250 g load. The morphology of all coatings was investigated with a Zeiss Ultraplus FE-SEM at 3 kV and white light interferometer (WLI) (Veeco, Wyko NT9100, U.S.A). High temperature differential scanning calorimetry (DSC) analysis was conducted from 30 to 1000 °C at a 10 °C min⁻¹ ramp under nitrogen atmosphere in a STA 8000 (Perkin Elmer, U.S.A).

**B.2.3 Cell Analysis**

This study was approved by the Animal Research Ethics Committee of Australian National University (Reference Nr. A2013/41). Primary osteoblasts were isolated from femur bone of adult Swiss mice according to the ANU animal ethics guidelines. The femur was cleaned thoroughly, minced and digested using collagenase (Sigma Aldrich) at a concentration of 10 mg.mL⁻¹ at 37 °C for 20 min. The digested mass was washed with 1x
Phosphate Buffered Saline (PBS) and plated on tissue culture plate (TCP) and maintained with Dulbecco's Modified Eagle's medium (DMEM - HyClone) containing 10% Foetal Bovine Serum (FBS, Gibco) and 1% Penicillin Streptomycin antibiotics (HyClone). Confluent cultures were mechanically detached using cell scrapers (HyClone) and seeded at a density of 10,000 cells per sample in 24 well plates.

**B.2.4 Proliferation studies**

Cell adhesion and proliferation on the scaffolds were determined using the colorimetric Vybrant MTT Proliferation assay kit as per manufacturer’s protocols (Life Technologies). For the assay, samples were rinsed with PBS to remove unattached cells and incubated with 10% MTT reagent in a serum free medium for a period of 3 h at 37 °C. Absorbance of the obtained dye was measured at 490 nm using a spectrophotometric plate reader (TECAN Infinite® 200 PRO series).

**B.2.5 Immunofluorescence analysis**

Isolated primary murine bone cells grown on samples were washed with PBS, and fixed with 4% paraformaldehyde (Sigma) for 10 min. Cells were permeabilized with 0.1% Triton X-100 (Sigma), blocked for non-specific staining using 3% bovine serum albumin (BSA, Sigma) and then immunostained with Phalloidin-TRITC (Millipore) and anti-osteocalcin antibody (R&D systems) for 1 h at room temperature and then, revealed with anti-species-specific Alexa fluor 488 (Life Technologies). The samples were mounted using anti-quenching mounting medium (Vectashiled, Vector laboratories) and observed under a fluorescence microscope for imaging (Olympus IX 71).

**B.3 Results and Discussion**

**B.3.1 Aerosol Self-Assembly of Ultra-Porous Hierarchical Coatings**
Aerosols of nanoparticles were synthesized by atomization, combustion and in-flame nucleation of liquid precursor solutions as recently described for other oxides\textsuperscript{17}. Hierarchical ultra-porous coatings were obtained in one-step by deposition of these hot nanoparticle aerosols having an initial average primary particle diameter of 34 nm. To achieve sufficient coating mechanical stability, here, the deposition distance from the burner was further decreased from 10 cm of previous studies\textsuperscript{17} to 6 cm. This resulted in in-situ sintering of the depositing nanoparticle flux and covalent bonding of the self-assembled network. Figure B.1 shows exemplary morphologies obtained by short time (≤ 25 s) orthogonal impingement of these hot nanoparticle aerosols on implantable titanium alloy substrates. For all deposition times (Table B.1), a hierarchical coating morphology was observed. This was characterized by relatively dense mesoporous agglomerates separated by large micro-sized pores (Figure B.1a,b). Cross-sectional analysis revealed uniform coating of the underlying substrate and a very rough surface structure (Figure B.1d,e). Most importantly, although the flame temperature at the deposition height was ca. 1200 °C, the coatings preserved a nano-scale texture (Figure B.1b, inset) and were constituted by only partially sintered particles of a few tens of nanometers in diameter. These results are in line with the uniform collapse and multi-center re-agglomeration of low temperature (< 150 °C) aerosol-deposited ultra-porous (ca. 98%) nanoparticle networks upon in-situ flame annealing\textsuperscript{19}.

Here, these partially sintered coatings had significantly improved mechanical properties and were able to withstand multiple wetting-drying cycles and handling. A more compact, also mechanical stable, morphology was obtained by spin-coating and post-sintering of the same flame-made nanoparticles collected on water-cooled glass fiber filters. These coatings were visibly more dense and characterized by a smoother surface (Figure B.1f) sporadically interrupted by some cracks extending throughout their cross-section (Figure B.1c). Cracks are
commonly observed in wet-deposition of thick nanoparticle layers, and are usually attributed to solvent evaporation. Higher magnification images of the crack-free regions revealed a similar nano-scale texture (Figure B.1c, inset) to the aerosol-deposited coatings with the main difference being the lack of a hierarchical multi-scale micro-structure.

![Figure B.1](image)

**Figure B.1.** Surface morphology (a-c) and cross-section SEM images of HAp coatings on Ti substrates made by (a,d) 5 s and (b,e) 25 s aerosol-deposition and by (c,f) spin coating of the same flame-made particles.

The surface morphology of all coatings was further investigated by white light interferometry (Figure B.2). It was found that increasing the aerosol deposition time from 5 to 25 s increased the root mean square (rms) surface roughness from 1.73 to 3.82 µm and the average coating porosity from 81% to 95%. In contrast, spin-coating led to a much less rough surface with a rms of 0.91 µm and an average porosity of 52%. These robust and well-reproducible coating morphologies enabled us to investigate the cellular response to similarly nano-textured crystalline HAp environments presenting, however, a systematically increased level of micro-structural hierarchy from 0.91 to 3.82 µm.
Table B.1. Summary of the coating key structural properties and cellular response.

<table>
<thead>
<tr>
<th>$T_d$ (s)</th>
<th>$\varepsilon_f$ (%)</th>
<th>Ra (µm)</th>
<th>Optical Density</th>
<th>Filopodia Formation</th>
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</thead>
<tbody>
<tr>
<td></td>
<td></td>
<td></td>
<td>After Day 7</td>
<td>After Day 14</td>
</tr>
<tr>
<td>Spin-Coated</td>
<td></td>
<td></td>
<td></td>
<td></td>
</tr>
<tr>
<td>5</td>
<td>52</td>
<td>0.92</td>
<td>0.11</td>
<td>0.15</td>
</tr>
<tr>
<td>10</td>
<td>81</td>
<td>1.73</td>
<td>0.1</td>
<td>0.4</td>
</tr>
<tr>
<td>15</td>
<td>85</td>
<td>2.43</td>
<td>0.12</td>
<td>0.42</td>
</tr>
<tr>
<td>20</td>
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<td>0.14</td>
<td>0.46</td>
</tr>
<tr>
<td>25</td>
<td>95</td>
<td>3.34</td>
<td>0.14</td>
<td>0.48</td>
</tr>
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Figure 2. WLI micrographs of aerosol-deposited coatings with (a,d) 5 s and (b,e) 25 s deposition time and comparison with the (c,f) spin-coated samples.

B.3.2 Hierarchically-Driven Cell Response

The initial phases of cell communication with a surface are adhesion, spreading and proliferation. These cellular processes subsequently affect differentiation, mineralization and bio-integration. Here, we have investigated the early-stage response of primary osteoblasts to six, well-defined, nano-textured micro-environments. From the cell’s micro-scale perspective, the spin-coated surfaces are a quasi-two-dimensional topography (rms < 1 µm) while the aerosol-deposited coatings are micro-rough, three-dimensional environments. Murine femur cells with osteocalcin producing osteoblasts (Figure B.3a,b) were cultured in
triplicate on each of the six HAp micro-environments and tissue culture plate, utilized as control.

*Figure B.3. a) Isolated cells from mice femur, b) Osteocalcin producing osteoblasts.*

The response of murine osteoblast cells to these structurally different surfaces was initially assessed by proliferation assays and immunostaining. After 7 days of incubation, all micro-environments resulted in similar osteoblast proliferation (Figure B.4, blue bars). This reveals that the flame-made HAp nanoparticles are biocompatible and enable cell growth without additional surface functionalization. Most importantly, after 14 days, the proliferation dynamics on the different coating diverged and appeared to be promoted by the hierarchical structure. Between day 7 and 14, all the hierarchical coatings showed a statistically significant ($p \leq 0.05$), greater than 3-fold, increase in osteoblast proliferation (Figure B.4, pink bars). Increasing the average coating porosity from 81% to 95% increased the optical density from 0.41 to 0.52. Furthermore, while, in the tissue culture plates, cell numbers had roughly doubled after 14 days, the ultra-porous (95%) aerosol-deposited coatings resulted in a 3.5 fold increase in cell number indicating that very high porosity can promote cell proliferation. In stark contrast, on the spin-coated films very little proliferation was observed with the optical density increasing only from 0.15 to 0.11 (ca. 26%) during the same
incubation period. This further substantiates that comparable composition and nano-texturing can result in drastically different cellular responses if presented in a different micro-structural context. As further discussed below, this is attributed to the promotion of early-stage surface adhesion that enables focal point signaling and re-mineralization.

![Figure B.4. Optical density of samples with different film porosity (52 to 98%) and on the tissue culture plate (TCP) after 7 and 14 days incubation.](image)

Topographical analysis of cell spreading and protein expression revealed an increased cell-cell and cell-coating interaction with higher porosity. Figure B.5a-f show the co-expression of F-Actin and osteocalcin, a marker protein secreted only by osteoblast cells, on the surface of the 85% and 95% porous coatings. While the 85% porous coatings led to isolated high concentration of F-actin, the ultra-porous ones (95%) led to fibre interconnection across distant colonies, suggesting a higher level of cell-cell interaction. This significantly stronger and wide-spread F-actin expression suggests that the cells are responding to the micro- and nano-scale surface features of the ultra-porous coatings by early-stage adhesion and enhanced proliferation.

Mapping of osteocalcin expression confirmed that increasing structural hierarchy and porosity promote cell re-organization and biochemical activity. Osteocalcin is produced in the
cytoplasm of osteoblasts and under optimal environmental conditions, is continuously secreted into the surrounding matrix. The 85% porous coatings were characterized by small osteocalcin domains co-localized with the F-actin expression, suggesting osteocalcin confinement to the cell cytoplasm. In contrast, in the 95% porous coatings, it was not possible to observe specific osteocalcin domains, suggesting its early-stage secretion from the cell into the HAp micro-environments. Osteocalcin secretion results in bone formation by promoting proliferation and stimulating expression of genes for collagen, osteonectin, osteopontin, and alkaline phosphatase production. This indicates that the ultra-porous coatings have reached an advanced stage of cellular re-organization that precedes osteon and bone formation.

![Figure B.5. Cell spreading and the protein co-expression of F-Actin and Osteocalcin on the surface of HAp films with 85% (a-c) and 95% (d-f) porosities.](image)

The merged topographical mapping of F-actin and osteocalcin co-expression reinforces these observations demonstrating that the ultra-porous (95%) coatings induce osteocalcin expression between F-actin sites. As osteocalcin is a chemo-attractant, the interaction between distantly located cells in these coatings is attributed to its secretion and collection along the surface micro-pores, resulting in a pathway for cell-cell recognition and communication. Our results suggest that, if accompanied by a nano-scale texturing, high
micro-structural hierarchy (> 1 µm) is an osteo-inductive topographical feature. In fact, cellular adhesion is mediated by a series of adhesion proteins and specific integrin receptors at the cell membrane. In the first phase of attachment, the substratum gap between the cell and biomaterial is reduced from 50 nm to less than 15 nm resulting in the formation of F-actin rich focal adhesion points.\textsuperscript{23} As a result of the observed protein co-expression, the hierarchical micro-roughness of the 95% porous coatings appear to reduce the migration time required by the cells to find a satisfactory location. This is expected to promote early-stage adhesion followed by signals that localize protein kinases and regulate the survival, growth, morphological deformation, migration, and differentiation of cells.\textsuperscript{23}

\textbf{B.3.3 Coating In-Growth and Cell-Cell Communication}

The cell response was further investigated by scanning electron microscope (SEM) analysis of cell cultures after an incubation period of 14 days (Figure B.6). In line with the topographical mapping of the F-actin and osteocalcin co-expression, the cellular morphology was observed to respond to the coating porosity and structural hierarchy. The spin-coated samples were almost cell-free with a few surviving osteoblasts found mainly in the proximity of cracks (Figure B.6a). Surface examination revealed that most of the cells failed to adhere to the nano-textured surface. In contrast, the 81% porous coatings harboured a dense and homogenously distributed cell population (Figure B.6b). However, at this relatively low porosity, the cell morphology was predominantly circular with a diameter of a few micrometres and no visible cell-cell interaction. In these samples, only a few elongated cells were observed extending along the surface micro-pores. For both circular and elongated cells, the cell membrane showed minor deformations (Figure B.6f,j) in agreement with the observed F-actin and osteocalcin topography (Figure B.5a,b). This indicates an active and dense cell population but an early-stage of re-organization. Here, it is proposed that at 81%
porosity, the micro-sized pores (Table B.1) of the hierarchical coatings enable robust cell anchoring, but spatially-limit further growth resulting in mostly isolated semi-circular cells.

![False colored SEM micrographs of cell attachment and growth on HAp coating prepared by (a,e,i) spin-coating and aerosol-deposition (b-l) with different porosity and micro-structural hierarchy.](image)

**Figure B.6.** False colored SEM micrographs of cell attachment and growth on HAp coating prepared by (a,e,i) spin-coating and aerosol-deposition (b-l) with different porosity and micro-structural hierarchy.

However, we found that increasing the structural hierarchy and porosity above 81% had a major impact on the resulting cell morphology and growth with cells becoming significantly bigger and exhibiting strong deformations of their membranes. On the 95% porous coatings, we observed the formation of numerous nano-sized filopodia and tight junctions (Figure B.6.d,h,i). We also detected extensive penetration of these filopodia and cell infiltration into the inorganic coatings. Filopodia are F-actin rich cytoplasmic projections that cells use to probe their micro-environment. They are an
important feature of cells during migration and wound healing. They serve as a first point of recognition and protrusion prior to signal transduction for cellular activity. Filopodia are known to play pivotal roles in cellular processes such as adhesion to the extracellular matrix, cellular migration and guidance towards organ development in embryogenesis. Here, filopodia formation and penetration into the underlying inorganic micro-environment is attributed to the multi-scale porosity of the ultra-porous coatings that enables early-stage cell adhesion and in-growth during gradual coating re-mineralization.24

**B.3.4 Colonization Mechanisms of the Ultra-Porous Hierarchical Coatings**

Hydroxyapatite micro-environments have been widely utilized for their promotion of cellular adhesion, differentiation25 and osteogenesis26. However, here, we have observed for the first time that specific multi-scale nano- and micro-features can promote cell-cell communication and in-growth into an inorganic coating. This suggests that the contradictory results reported for similarly nano-textured HAp coatings may arise from different micro-scale features. These findings led us to propose a model (Figure B.7) of the key structural cues and surface colonization dynamics observed in the ultra-porous hierarchical coatings. We subdivide the cell’s response in three main phases. In the first phase, the cells start the adhesion process by rapidly localizing stable adhesion/anchoring sites in the surface micro-pores. For the hierarchical coatings, this results in uniform colonization of the hierarchical surface, whereas on the quasi-two-dimensional surfaces, the cells seem to preferentially adhere to the proximity of cracks formed during the solvent evaporation process (Figure B.6a).

During the second phase, the adhered cells start to respond to the surrounding hierarchical environment. All the HAp coatings exhibit similar properties due to the
equivalent nano-scale features and composition that results in comparable Ca\(^{2+}\) and PO\(_3^{-4}\) ion release rates. It is during this phase, where the combined micro- and nano-scale porosity plays a key role.

**Figure B.7.** Schematic of the three main phases of micro-environment colonization proposed for the hierarchical ultra-porous (95%) nano-textured HAp coatings

First, the large micro-size pores enable unconstrained cell growth and enhanced adhesion as observed by the extensive F-actin expression (Figure B.5d). Thereafter, the ultra-high porosity of these coatings signals to the cells low local-density, and thus space for growth promoting deformation of the cell membrane. In contrast, the cells perceive the small mesopore of the spin-coated films as a dense, impenetrable surface inhibiting cell growth and activity (Figure B.6a,e,i). The coating porosity required to induce widespread membrane deformation was found to be above 90%. This is similar to the density of the most active human trabecular bone regions.

In the third phase, the optimally adhered cells that are surrounded by sufficiently porous and chemically favorable micro-environments start to release osteocalcin. Its infiltration into the porous coating structure guides the growth of filopodia that respond to the mesopore texture by producing nano-scale elongated morphologies. This ultimately results in cellular in-growth into the coating improving bio-integration and long-term mechanical stability. In parallel to this vertical migration, the horizontal
spreading of osteocalcin through the surface micro-pores enables cell-cell communication and recognition. This ultimately results in their inter-connection and very early-stage osteon formation. This last phase was observed only in the ultra-porous (95%) hierarchical coatings revealing that a set of specific multi-scale morphological features is required to advance from an osteo-conductive, second generation, biomaterial to an osteo-inductive third generation micro-environment able to communicate programmable cues for the adhesion, growth, proliferation and differentiation of cells.

**B.4. Conclusions**

In summary, natural cellular growth is characterized by active communication between neighbouring cells and surrounding extracellular matrix. Recent advances in biomaterial research have repeatedly proven the importance of nano-structures for successful tissue engineering. However, contrasting results have been reported for similar composition and nano-scale features. Here, we show that an extracellular nano- and micro-structural hierarchy can provide input to growing cellular tissue to promote proliferation, adhesion and scaffold in-growth. We demonstrate the one-step ultra-fast (≈ 25 s) synthesis of hierarchical coatings that significantly enhance bio-integration. This is driven by a synergistic chemical and morphological response of cells to more than 90% porous, micro-rough, nano-textured surfaces that results in early-stage cell adhesion, membrane deformation and nano-filopodia formation. These findings provide a well-defined set of structural parameters and a flexible ultra-fast coating technology to control the early-stage response of bone cells with potential application extending from bone grafting to implantable devices such as micro-chips for drug release, neural and cardiac function monitoring.
B.5. References


